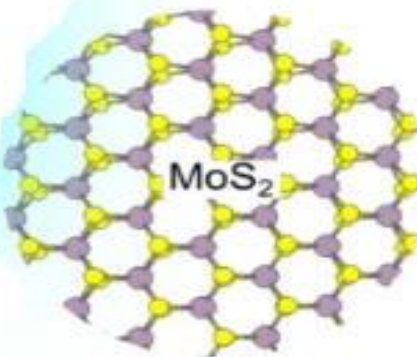
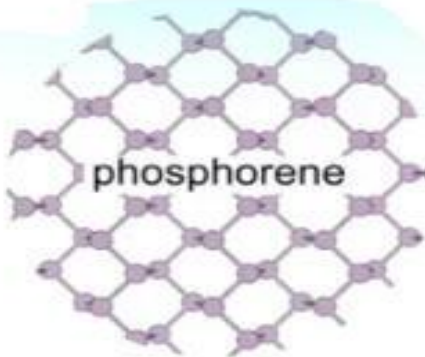
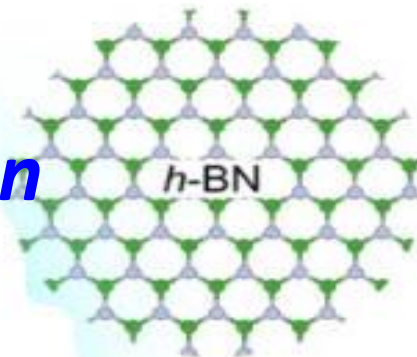
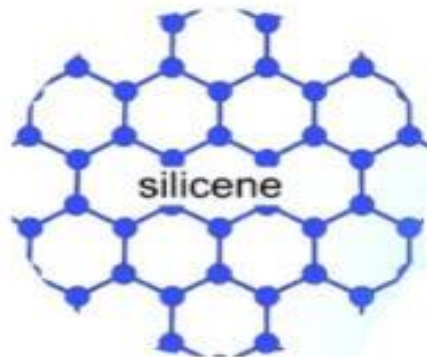
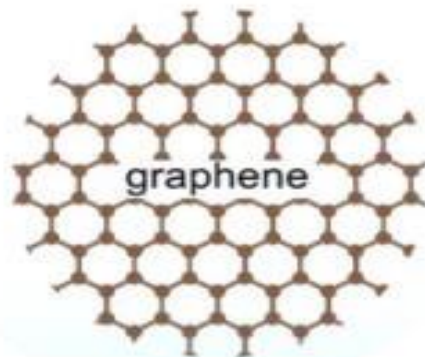




VUV Spectroscopy on 2D Materials

吳宇中

NSRRC

2D Materials

black phosphorus

MX_2 (MoS_2 , WS_2 , MoSe_2 ...)

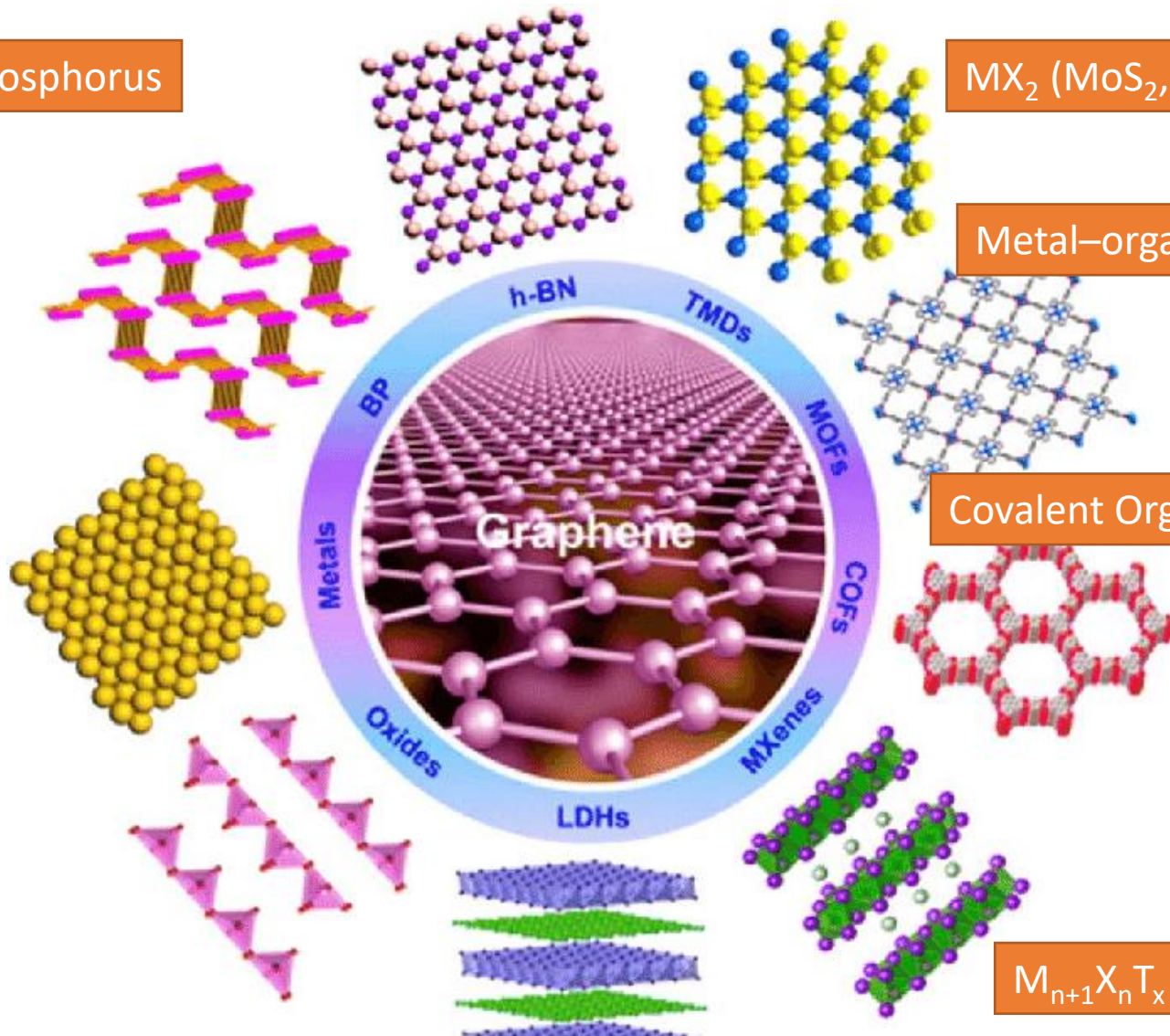
Metal–organic framework

Covalent Organic Frameworks

$\text{M}_{n+1}\text{X}_n\text{T}_x$ ($\text{T} = \text{O}, \text{F}, \text{OH}, \text{Cl}$)

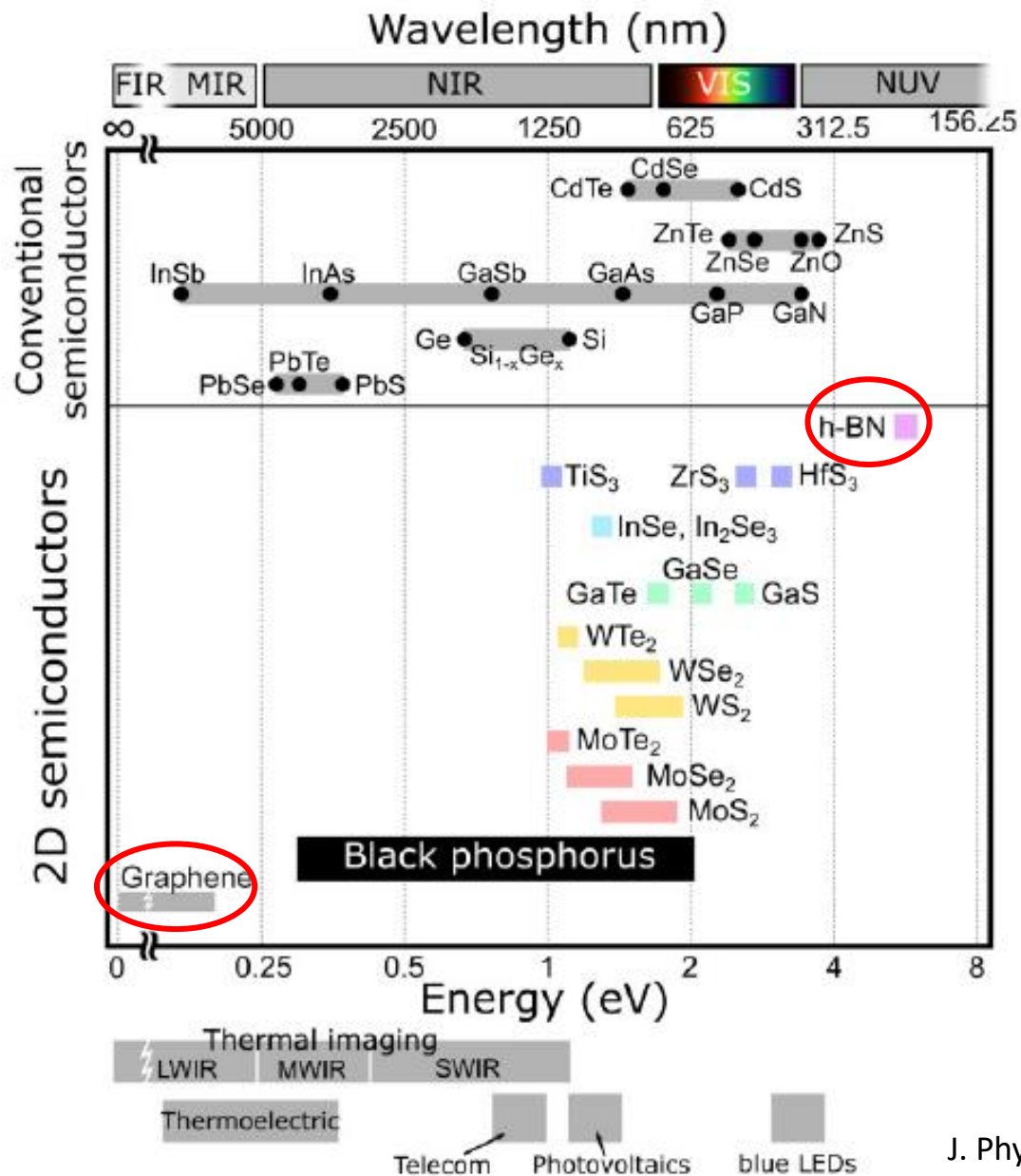
Layered double hydroxides (LDHs)

Chin. Opt. Lett. 16, 020004 (2018)

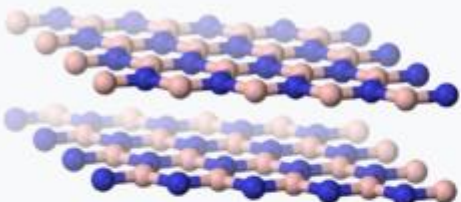
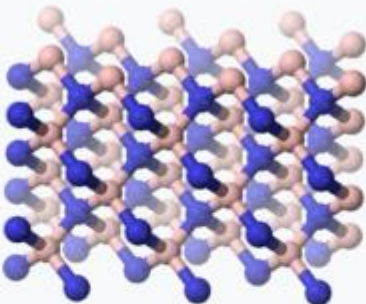
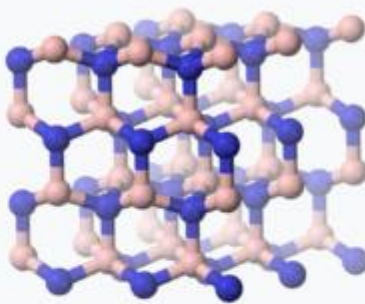


Far-UV Spectroscopy of Hexagonal Boron Nitrides (hBN)

Band Gap



Boron Nitride

		
Hexagonal form (h-BN) hexagonal analogous to graphite	Cubic form (c-BN) sphalerite structure analogous to diamond	Wurtzite form (w-BN) wurtzite structure analogous to lonsdaleite

Properties of amorphous and crystalline BN, graphite and diamond.

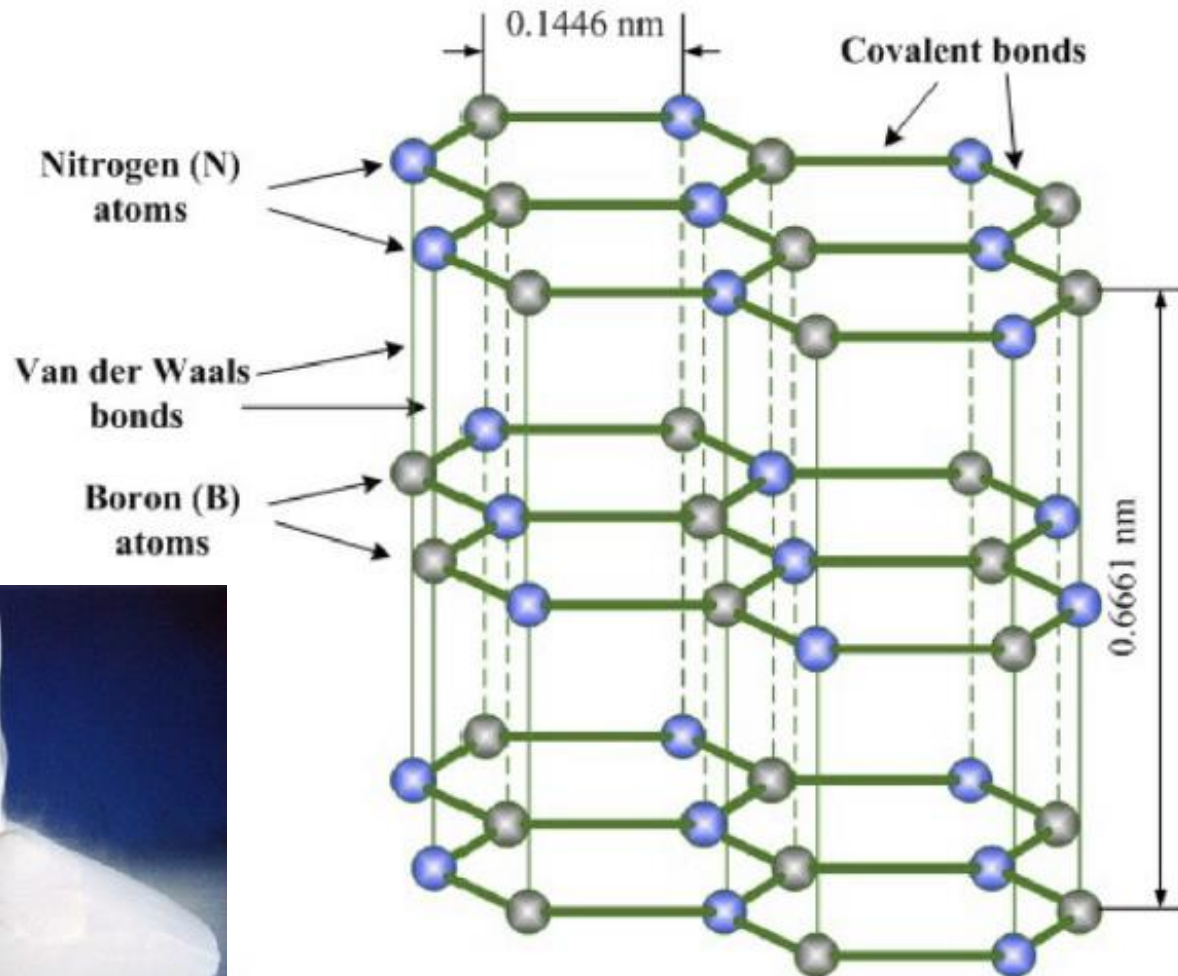
Some properties of h-BN and graphite differ within the basal planes (||) and perpendicular to them (⊥)

Material	a-BN	h-BN	c-BN	w-BN	graphite	diamond
Density (g/cm ³)	2.28	~2.1	3.45	3.49	~2.1	3.515
Knoop hardness (GPa)	10		45	34		100
Bulk modulus (GPa)	100	36.5	400	400	34	440
Thermal conductivity (W/(m·K))	3	600 , 30 ⊥	740		200–2000 , 2–800 ⊥	600–2000
Thermal expansion (10 ⁻⁶ /°C)		-2.7 , 38 ⊥	1.2	2.7	-1.5 , 25 ⊥	0.8
Bandgap (eV)	5.05	5.2	6.4	4.5–5.5	0	5.5
Refractive index	1.7	1.8	2.1	2.05		2.4
Magnetic susceptibility (μemu/g) ^[6]		-0.48 , -17.3 ⊥			-0.2...-2.7 , -20...-28 ⊥	-1.6

Sources: amorphous BN,^{[7][8][9]} crystalline BN,^{[10][11]} graphite,^[12] diamond.^[11]

White Graphite : Hexagonal Boron Nitride (*h*-BN)

Hexagonal boron nitride structure



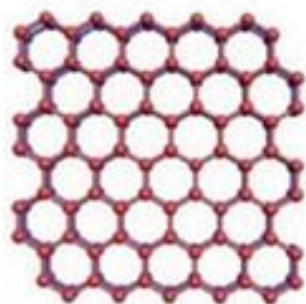
Stacking, Isoelectronic, Isostructural

Current Graphene Science **2**, 97 (2018)

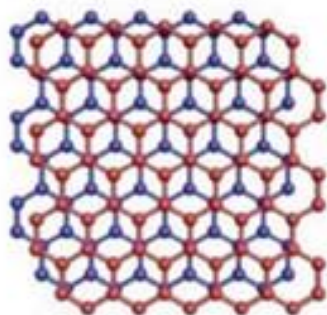
B: $1S^2 2S^2 2P^1$

C: $1S^2 2S^2 2P^2$

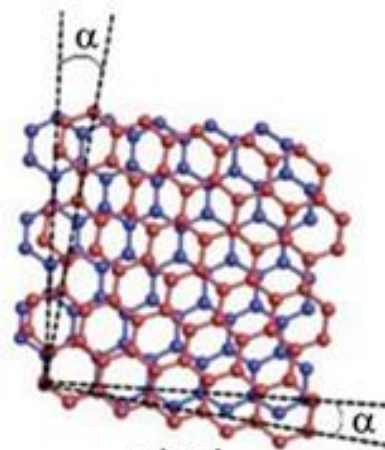
N: $1S^2 2S^2 2P^3$



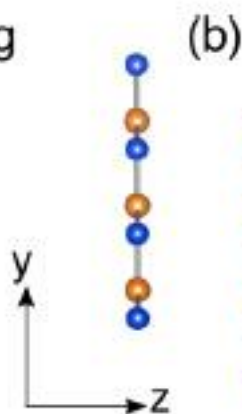
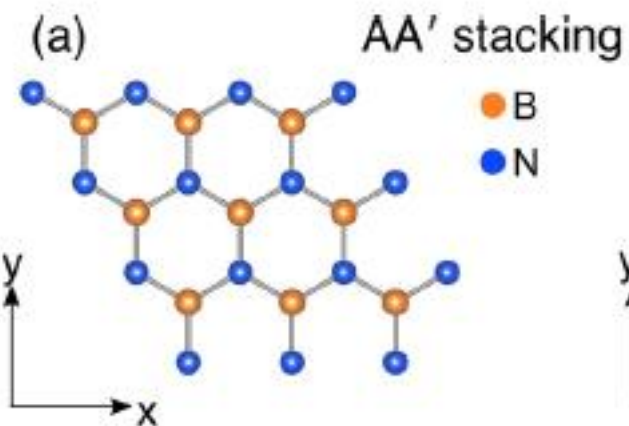
AA-stacked
bilayer-graphene



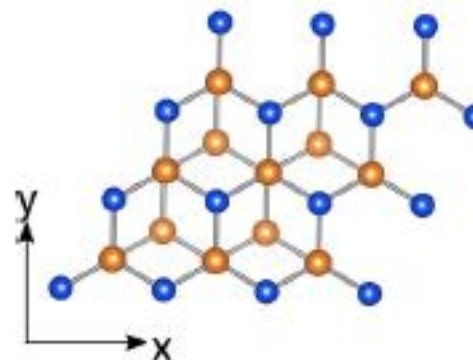
AB-stacked
bilayer-graphene



twisted
bilayer-graphene



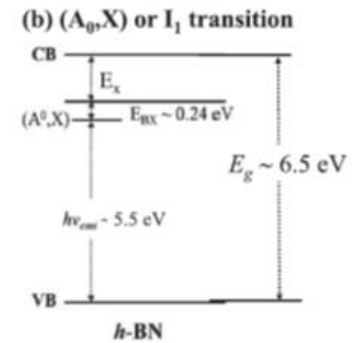
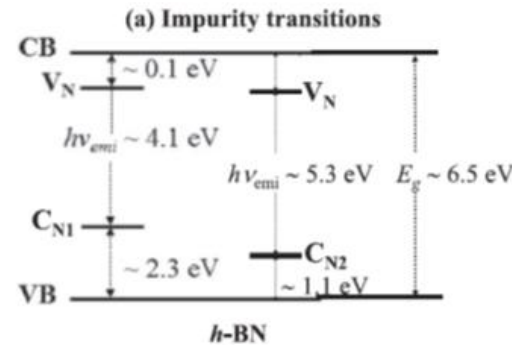
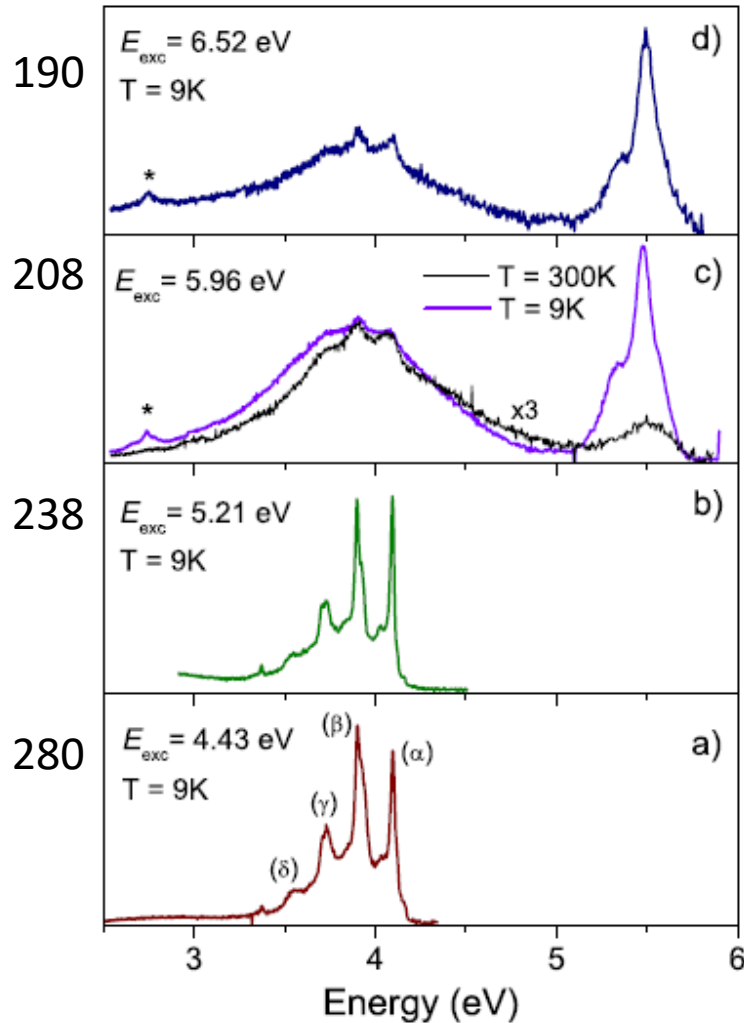
(c) AB stacking



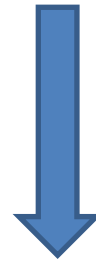
JPCC. **122**, 25524 (2018)

Photoluminescence of Bulk hBN

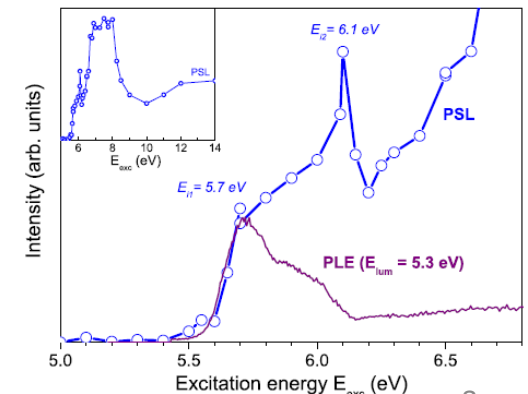
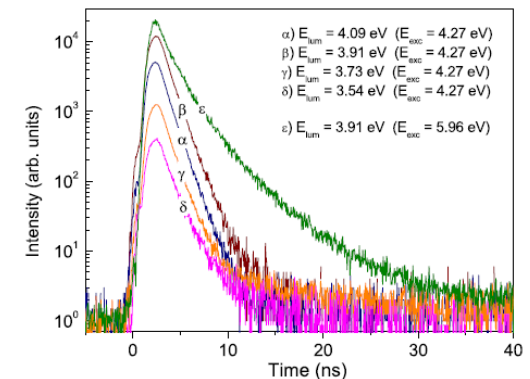
(5.5 eV, 225



$\tau \sim \text{ns}$
Frenkel-type excitons
Large Stoke Shift



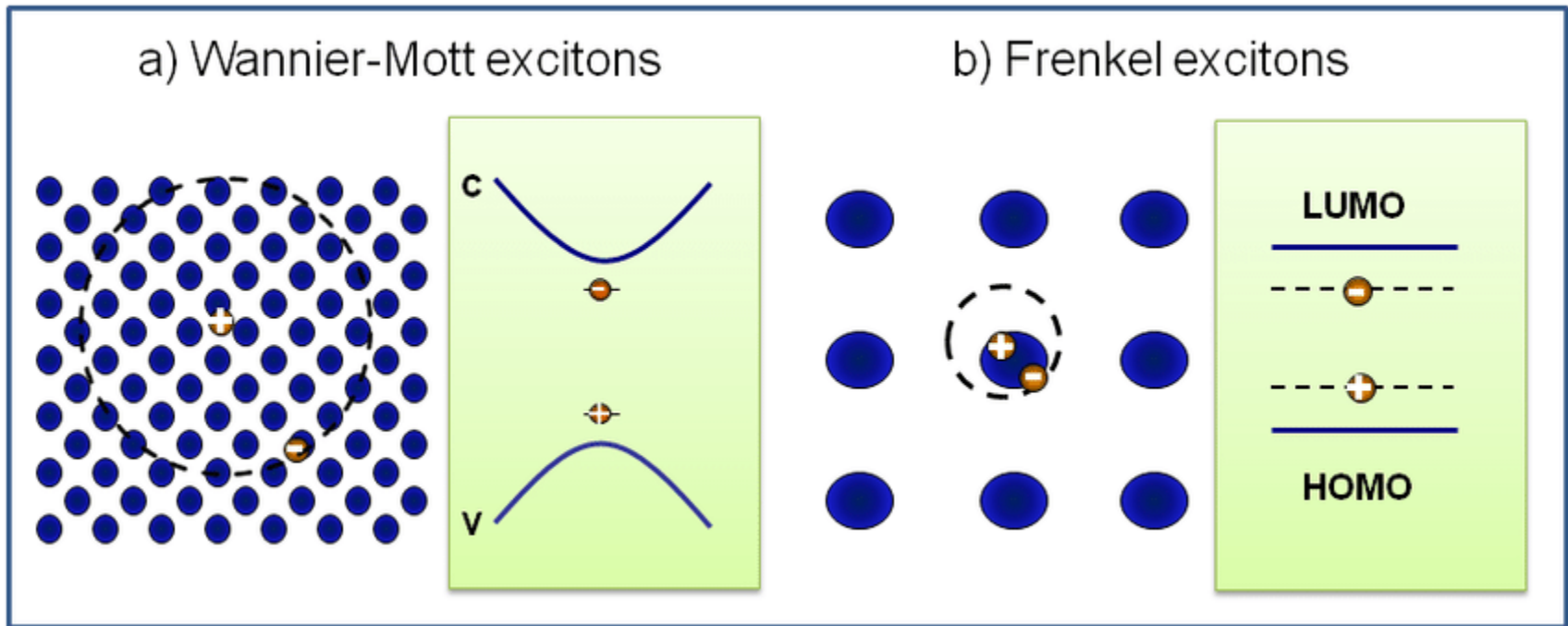
Indirect band-gap



PRB 78, 155204 (2008)

APL 106, 021110 (2015)

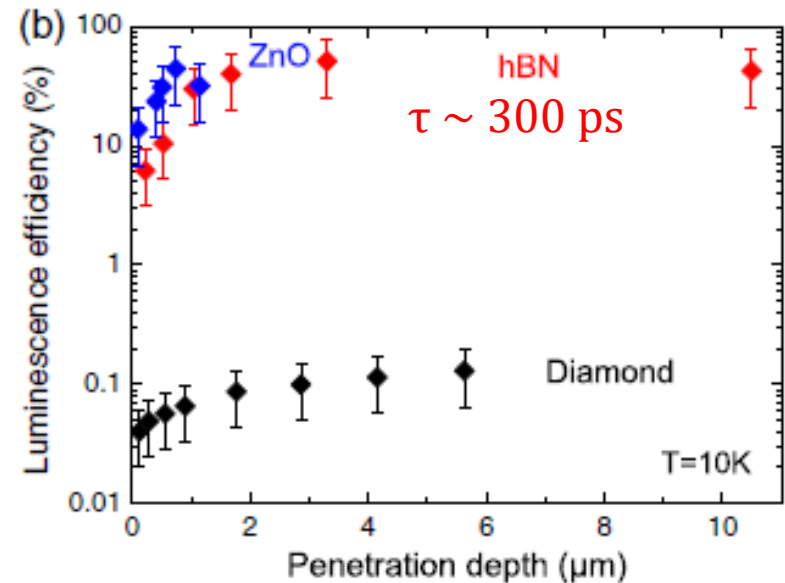
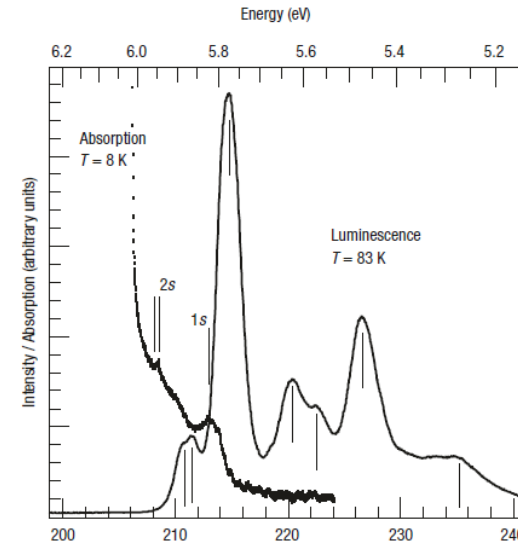
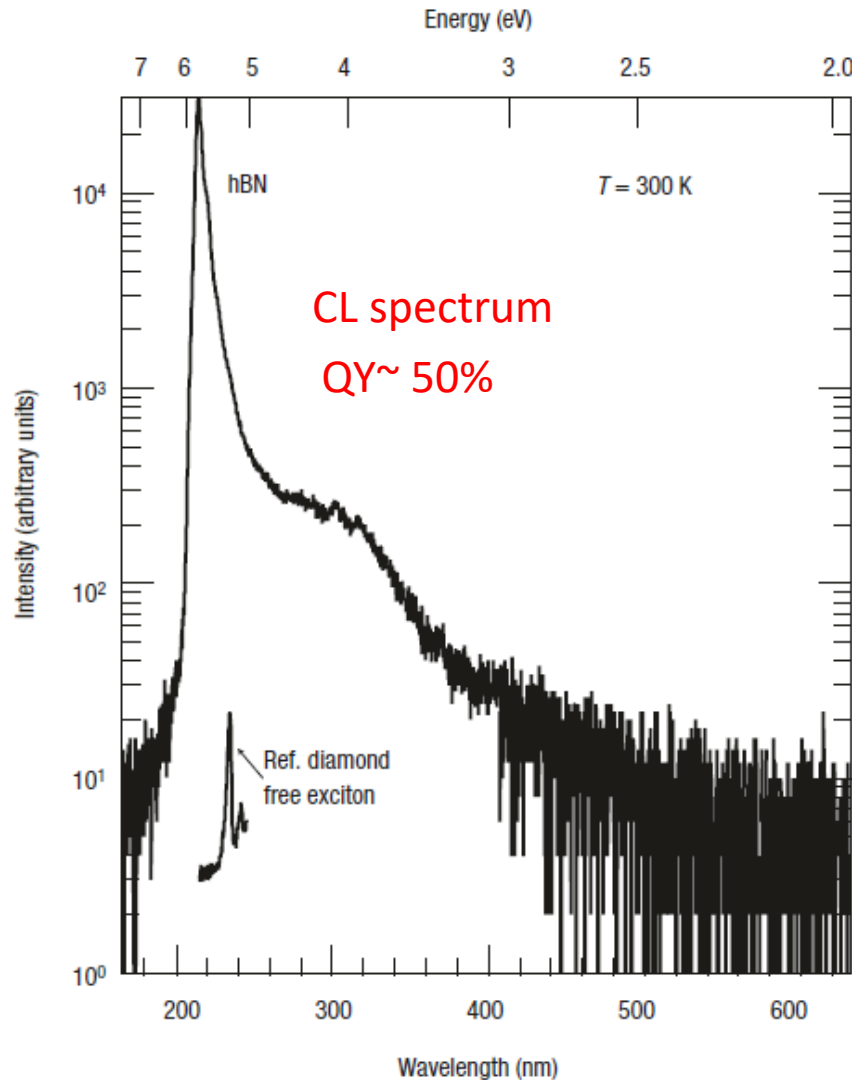
Exciton Type



Binding energy ~ 0.01 eV
Semiconductor, inorganic materials

Binding energy $0.1 \sim 1$ eV
organic materials

Direct Bandgap of Single h-BN Crystal (HP/HT)



DUV Lasing of h-BN Synthesized at AP/HT

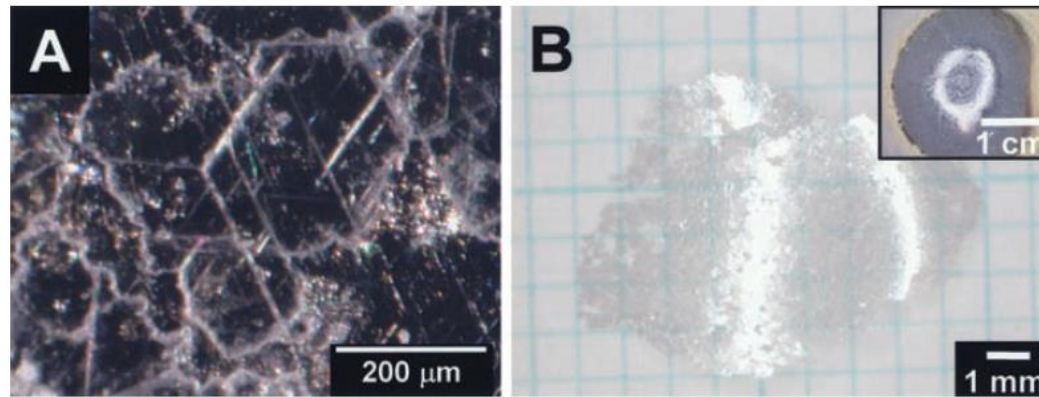
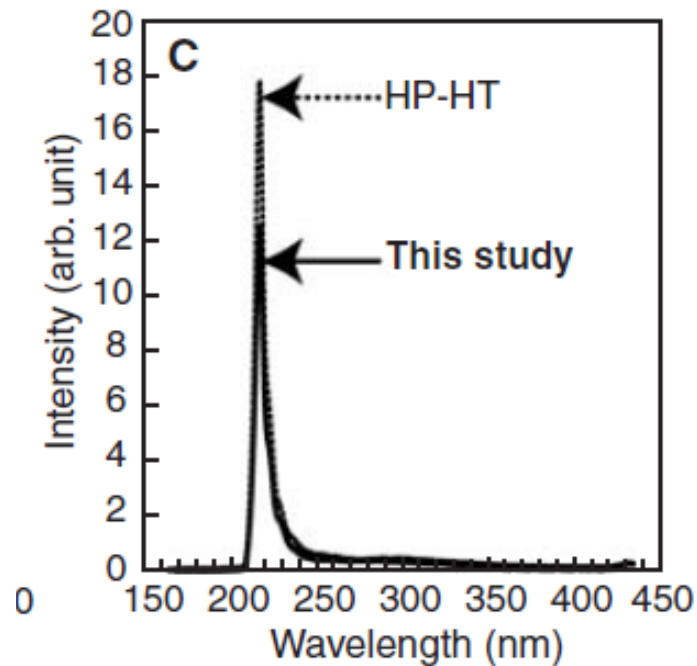
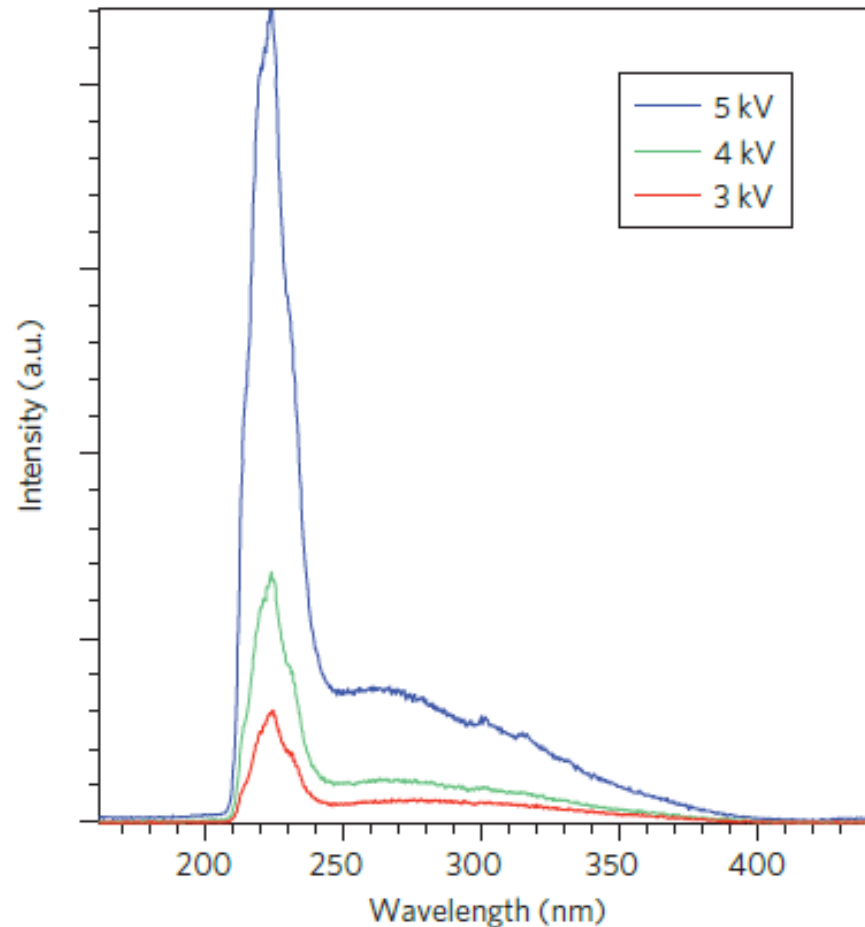
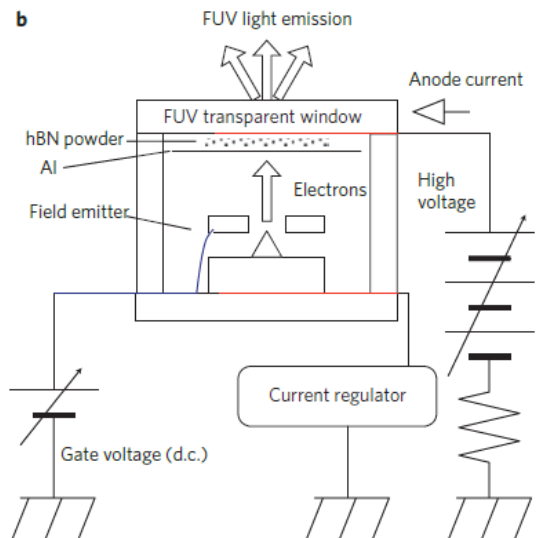


Fig. 1. Optical micrographs of recrystallized hBN obtained with a Ni-Mo solvent. **(A)** Typical hBN crystal on the solidified solvent (as grown). **(B)** A fragment of aggregate hBN crystals after acid treatment (the inset is an optical micrograph of a recovered sample). The shiny white regions are reflected light.

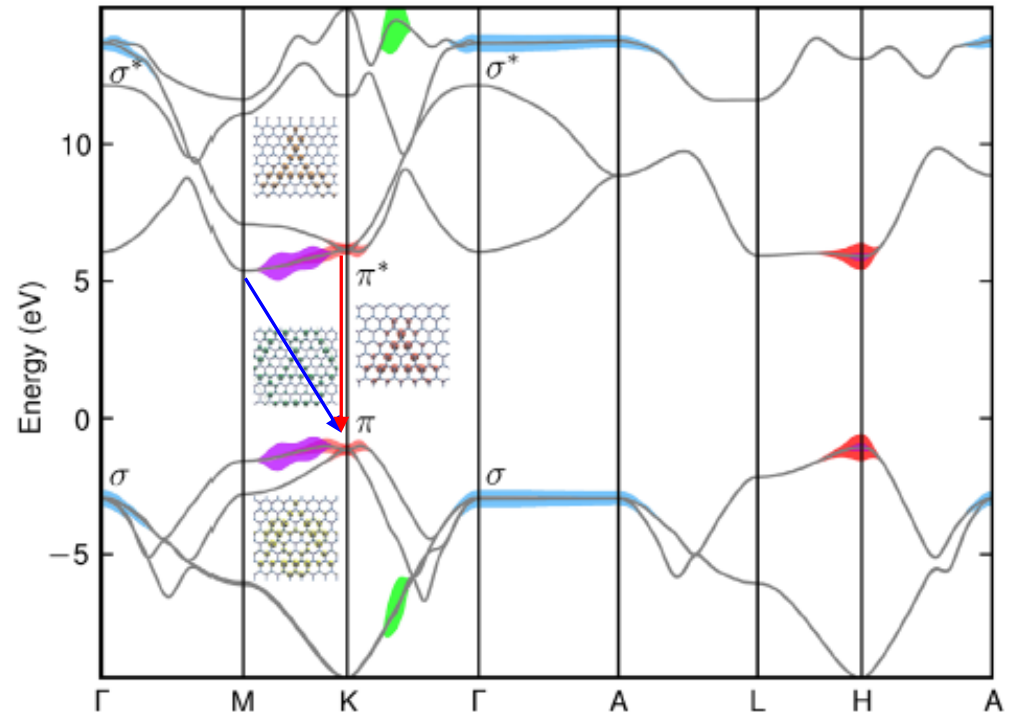
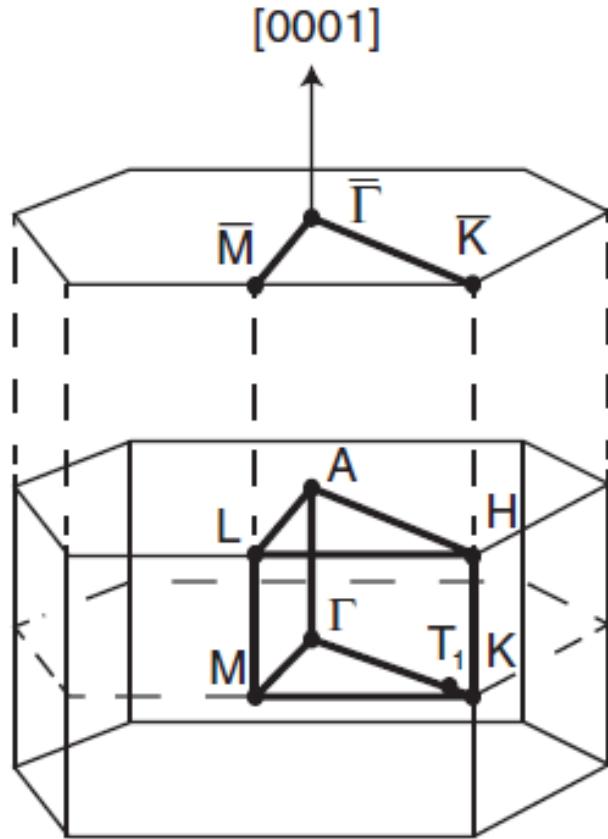


Far-ultraviolet plane-emission handheld device based on hexagonal boron nitride

Kenji Watanabe^{1*}, Takashi Taniguchi¹, Takahiro Niiyama², Kenta Miya² and Masateru Taniguchi²



Predicted Electronic Structures Indicate Indirect Band gap of hBN



M→K 6.03 eV

K→K 6.69 eV

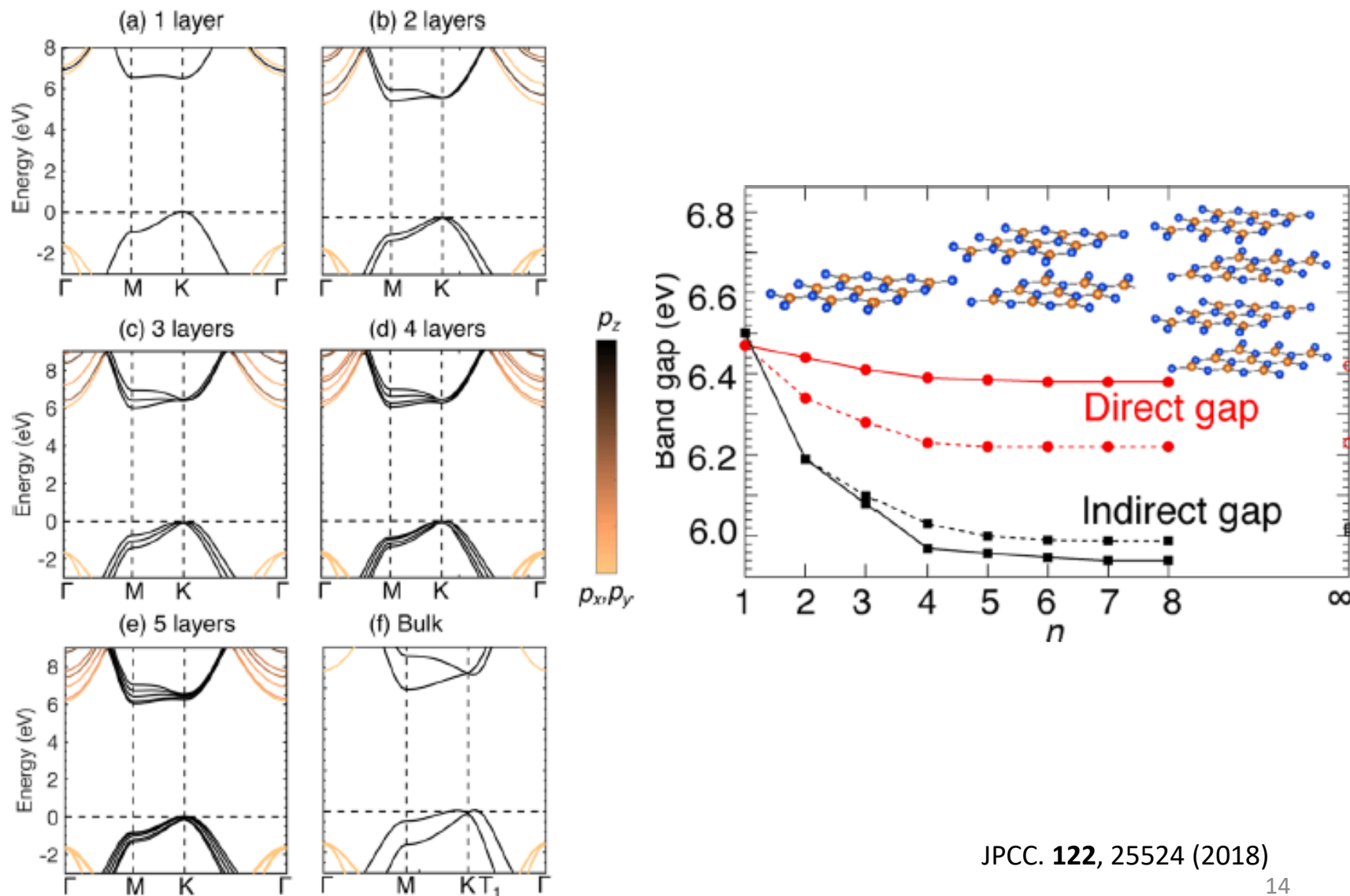
PRL 96, 026402 (2006)

Adv. Photon. Res. 2, 2000101 (2021)

Monolayer to Bulk Properties of Hexagonal Boron Nitride

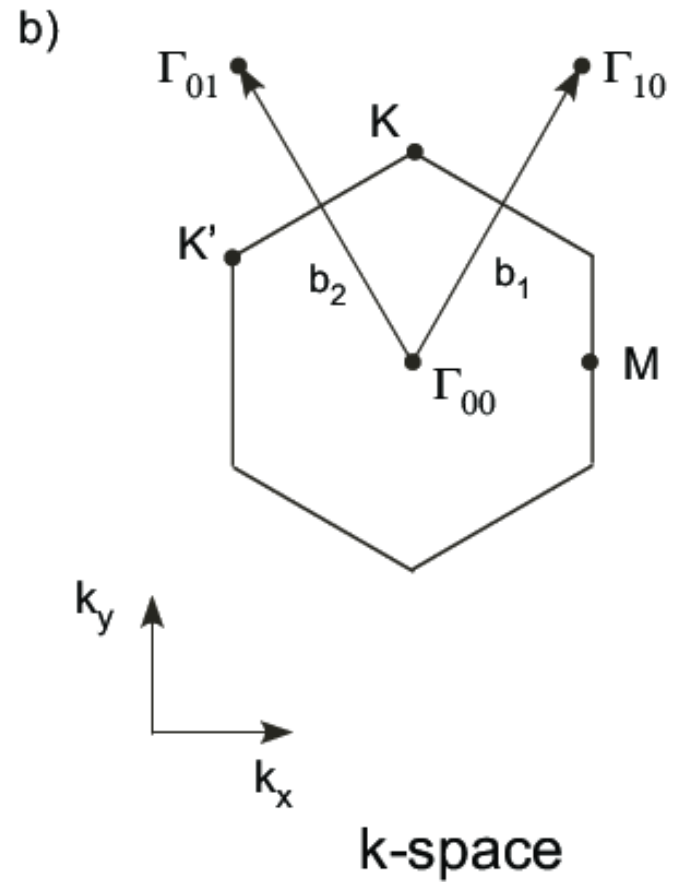
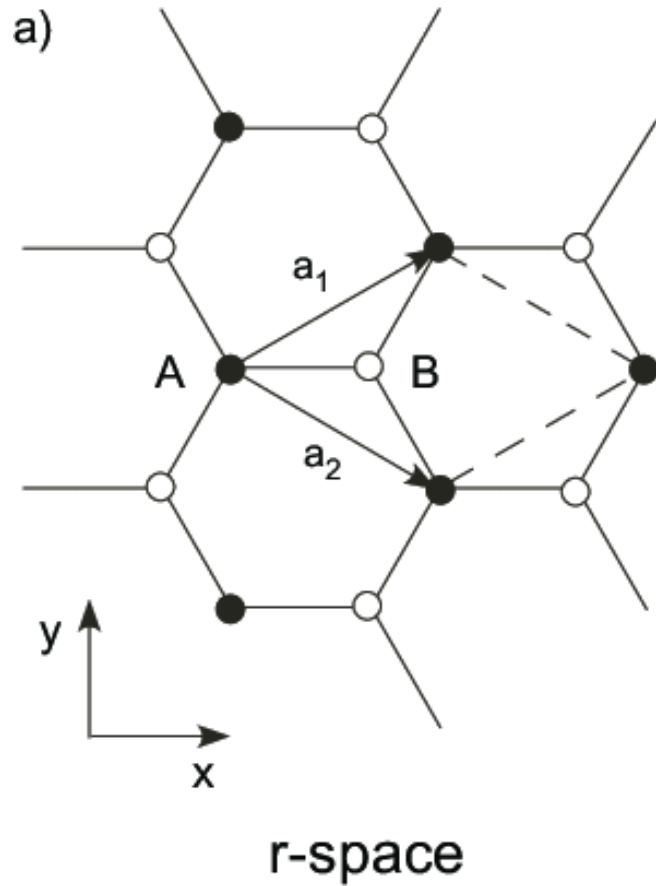
Darshana Wickramaratne,^{*}^{ID} Leigh Weston, and Chris G. Van de Walle^{ID}

Materials Department, University of California, Santa Barbara, Santa Barbara, California 93106-5050, United States

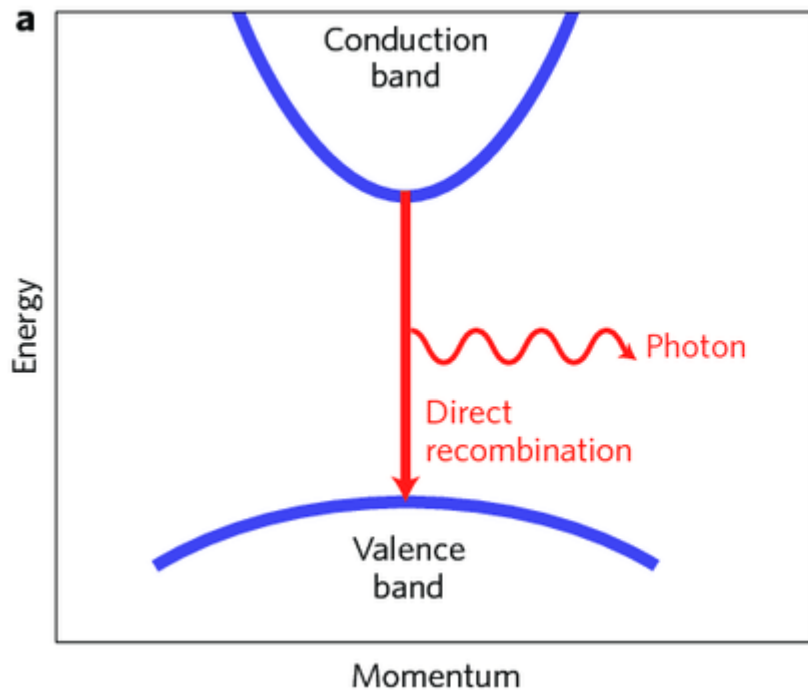


JPCC. **122**, 25524 (2018)

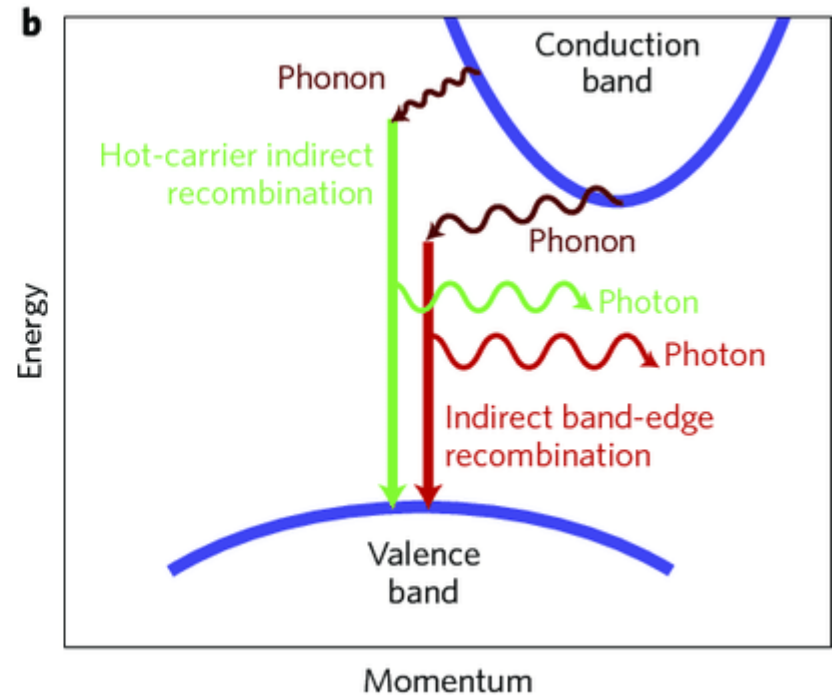
Real Space & K Space in Hexagonal System



Direct and Indirect Transitions: Fluorescence and Phosphorescence

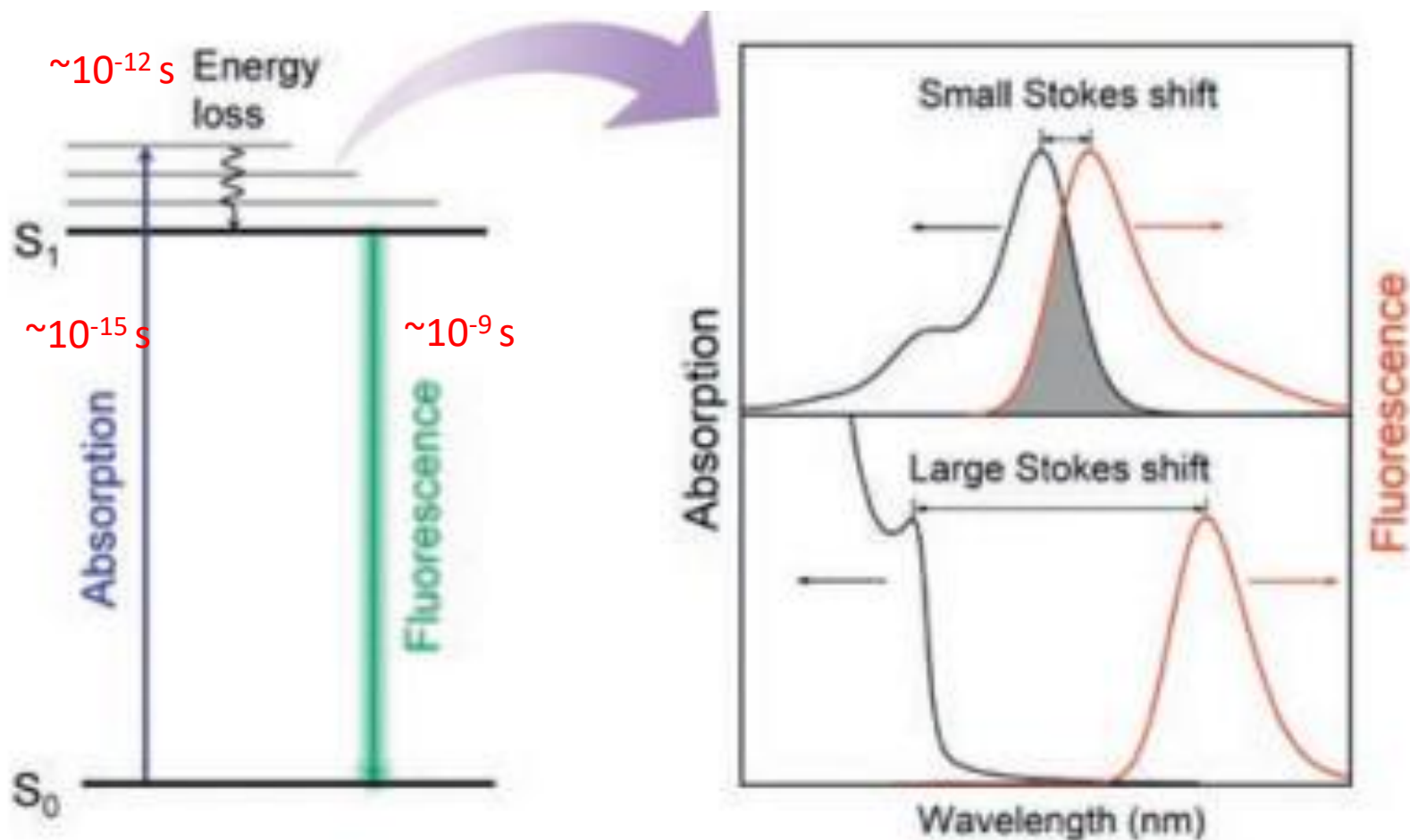


GaAs, InP and GaN



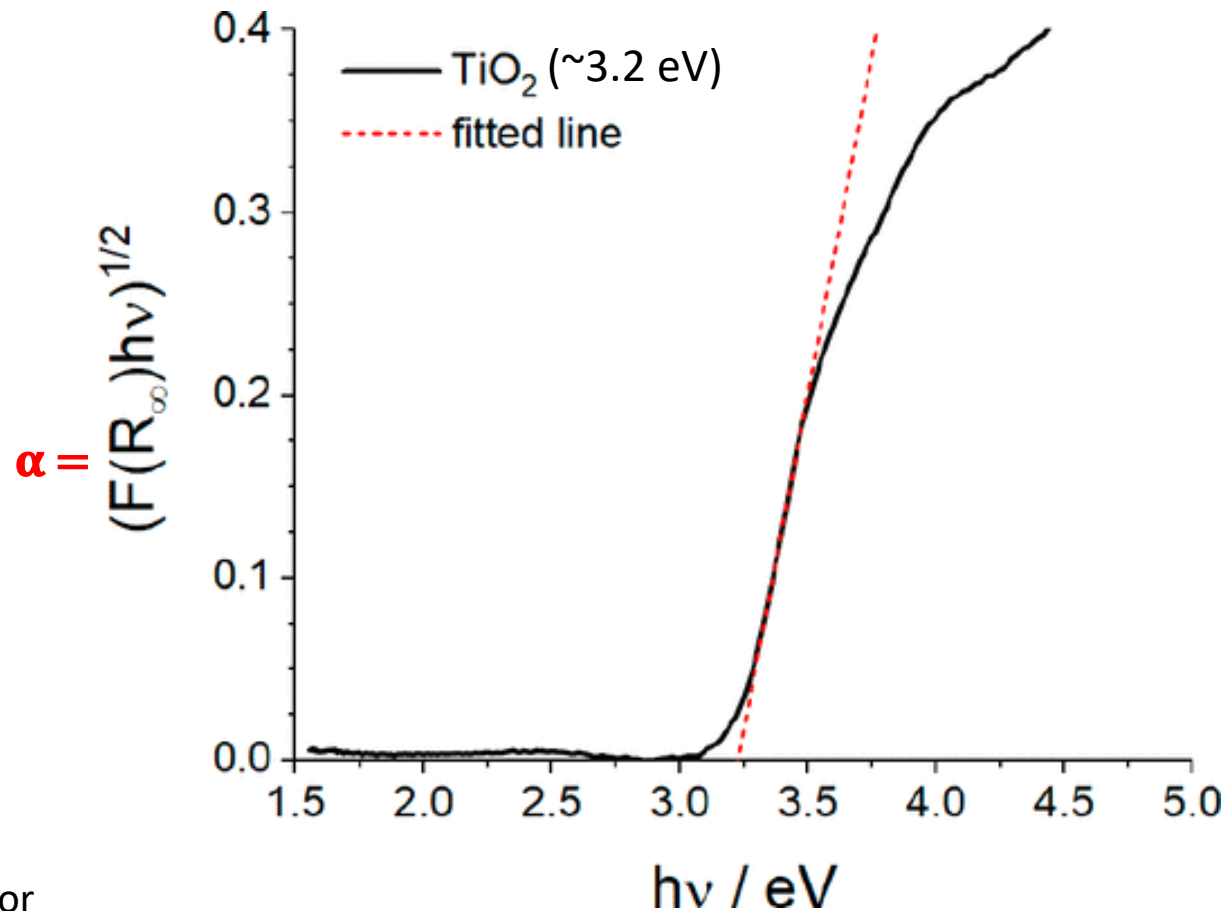
Silicon, diamond

Stoke Shift: Absorption and PL



Quantum Yield (Φ) = Photons emitted / Photons absorbed

Tauc Plot for Determining Optical Bandgap



Semiconductor

$r = 1/2$ for direct allowed transitions

$r = 3/2$ for direct forbidden transitions.

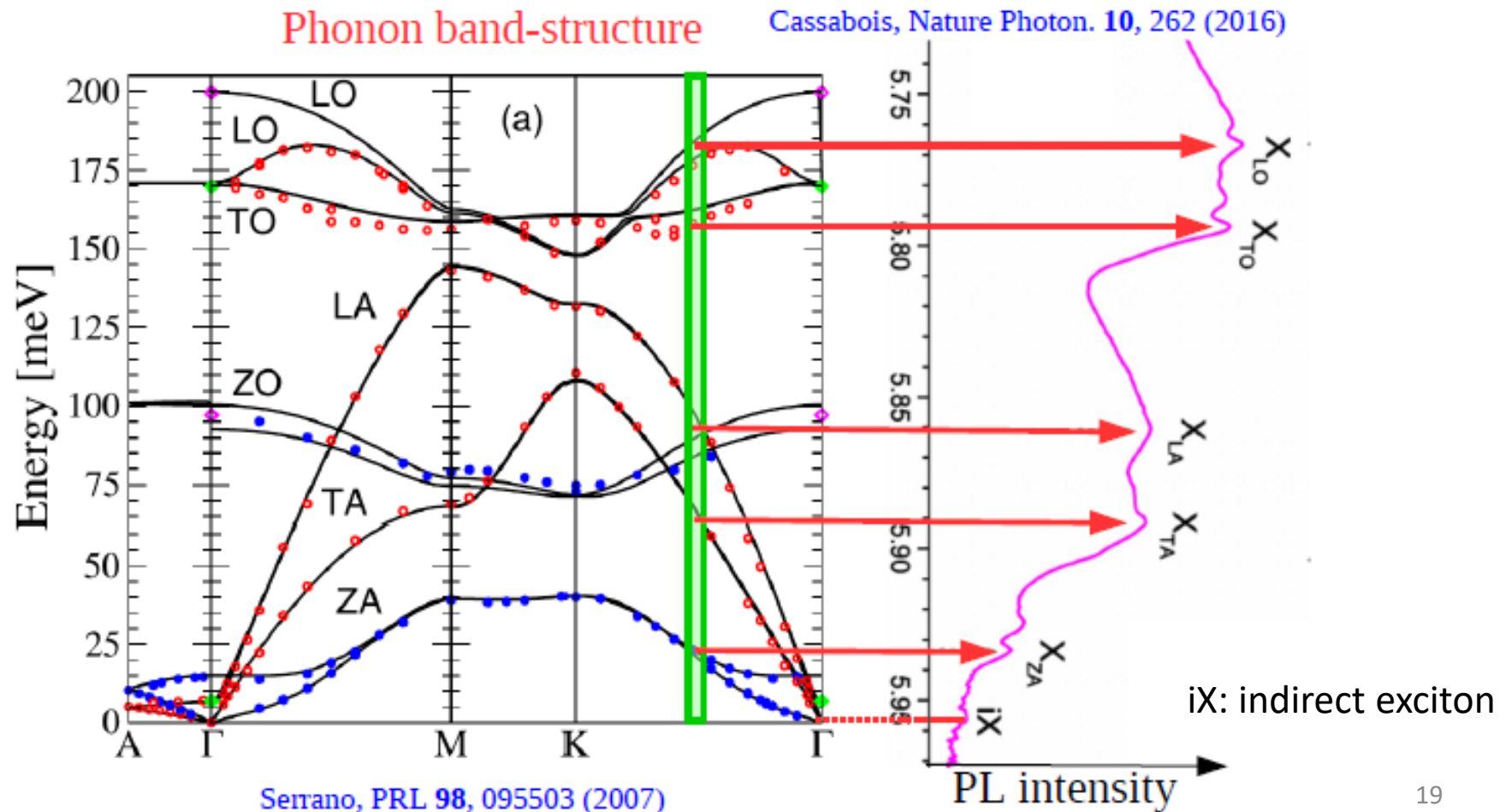
$r = 2$ for indirect allowed transitions

$r = 3$ for indirect forbidden transitions

J. Tauc et al. Phys. Status Solidi B 15, 627 (1966)
P. Makuta et al. J. Phys. Chem. Lett. 9, 6814 (2018)

Bulk hBN is a Indirect Bandgap Materials

Identification of phonon replicas



Bright Luminescence from Indirect and Strongly Bound Excitons in h-BN

Léonard Schué,^{1,2} Lorenzo Sponza,¹ Alexandre Plaud,^{1,2} Hakima Bensalah,² Kenji Watanabe,³ Takashi Taniguchi,³ François Ducastelle,¹ Annick Loiseau,^{1,*} and Julien Barjon^{2,†}

¹Laboratoire d'Etude des Microstructures, ONERA-CNRS, Université Paris-Saclay, BP 72, 92322 Châtillon Cedex, France

²Groupe d'Etude de la Matière Condensée, UVSQ-CNRS, Université Paris-Saclay, 45 avenue des Etats-Unis, 78035 Versailles Cedex, France

³National Institute for Materials Science, 1-1 Namiki, Tsukuba 305-0044, Japan

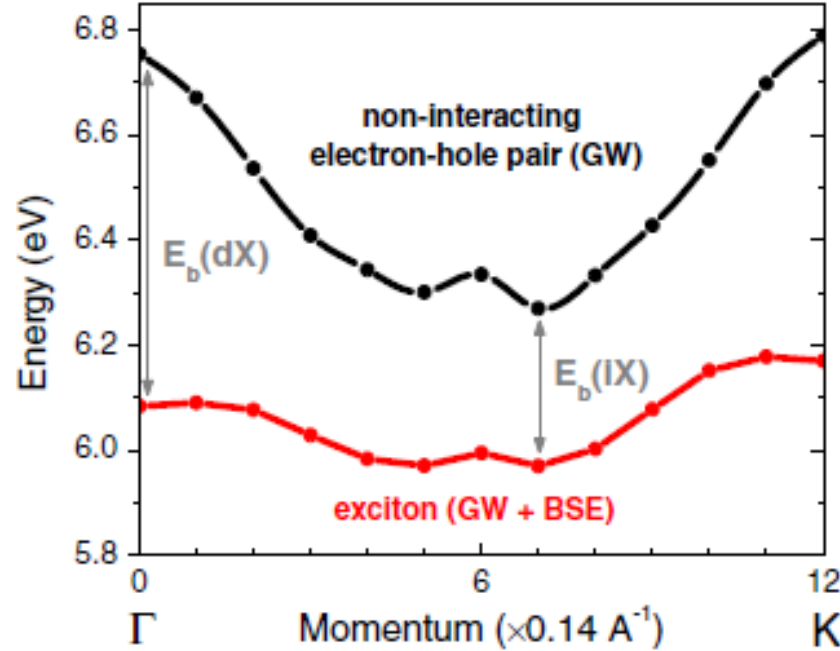
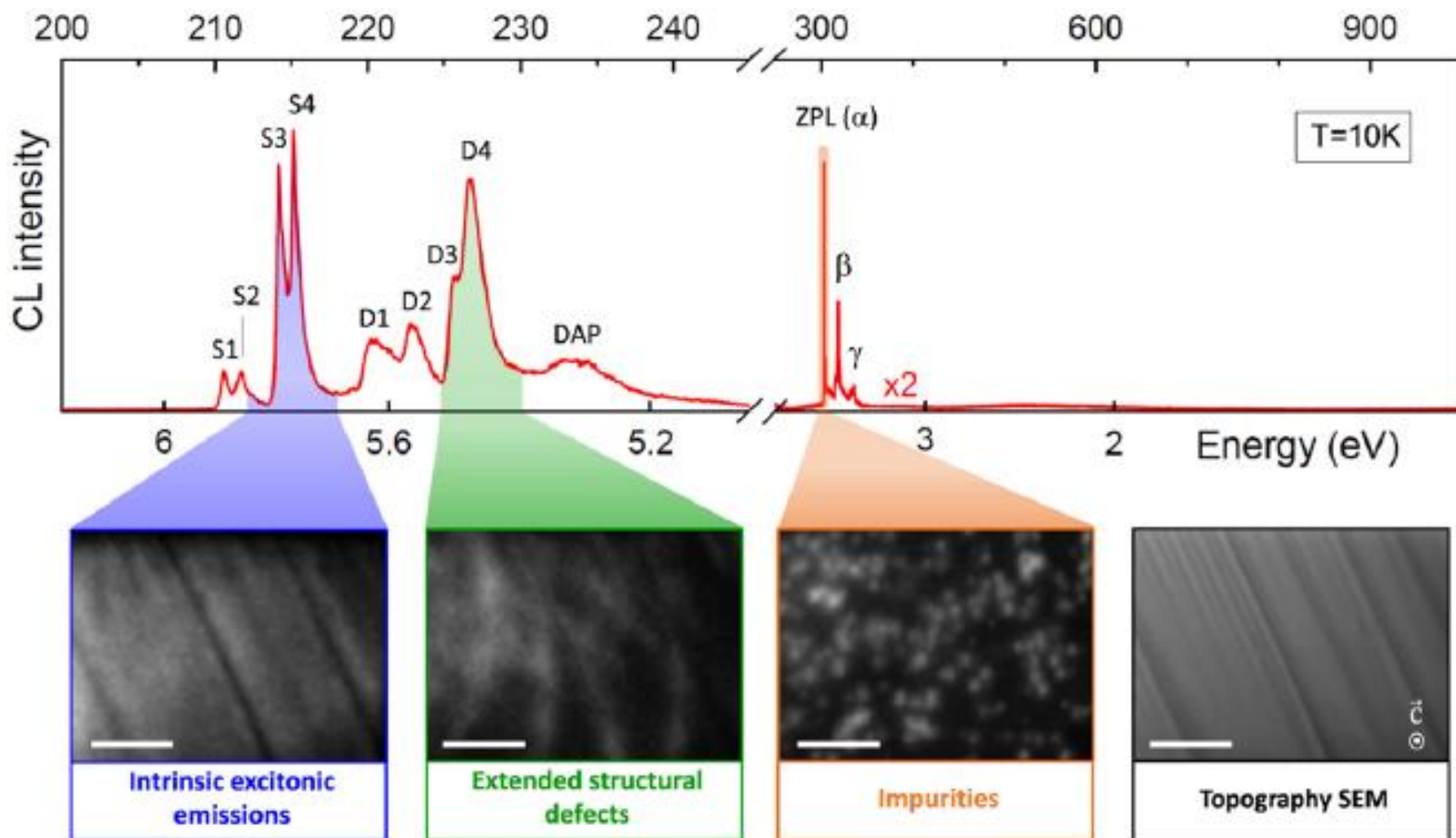
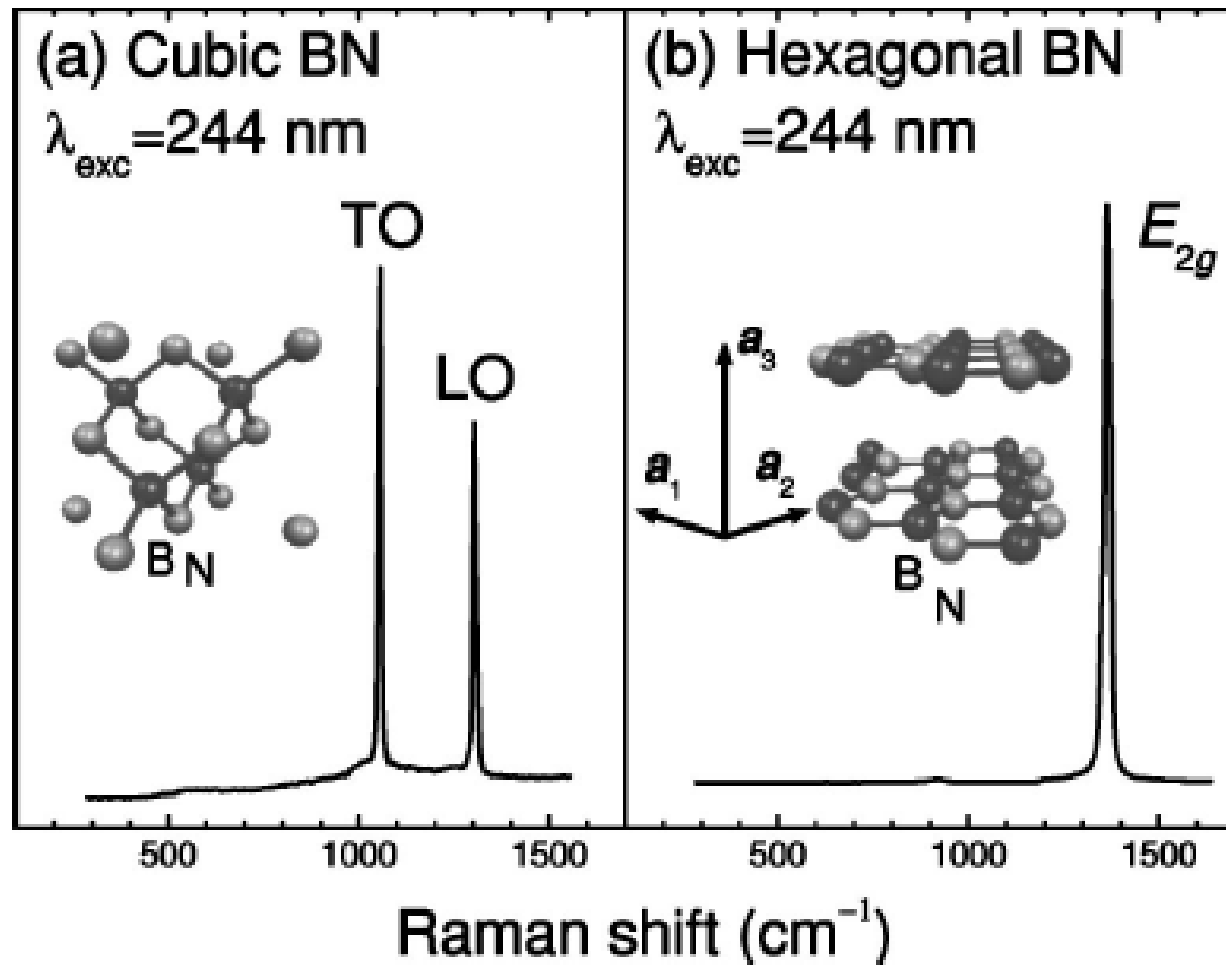


FIG. 3. Dispersion of excitons in h-BN compared to the non-interacting electron-hole pair along the Γ K direction. The vertical arrows indicate the binding energy E_b for the direct (dX) and indirect (iX) excitons. Adapted from Ref. [45].

Emission in Bulk hBN



Raman Spectra of Bulk cBN & hBN

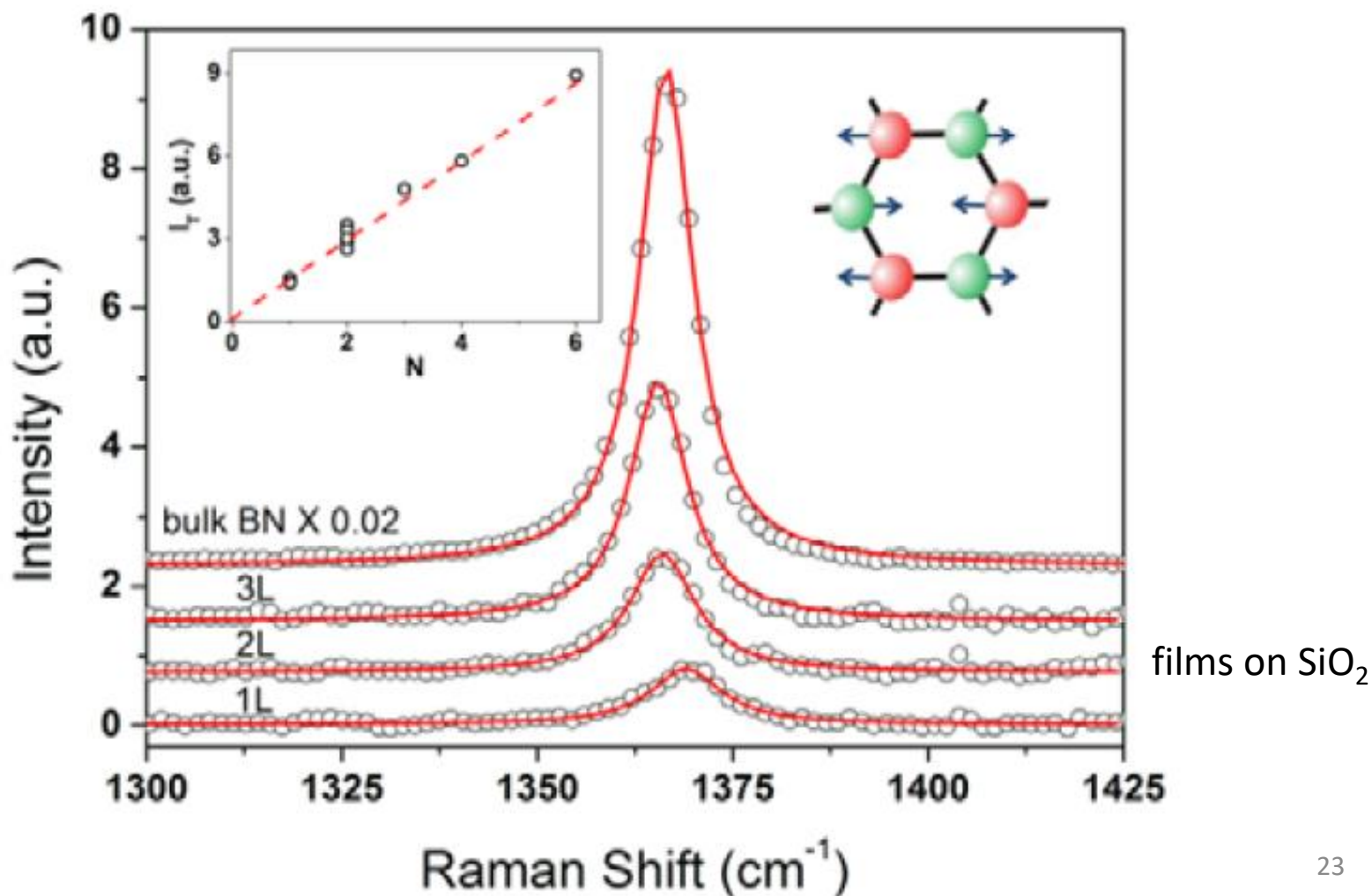


Hunting for Monolayer Boron Nitride: Optical and Raman Signatures

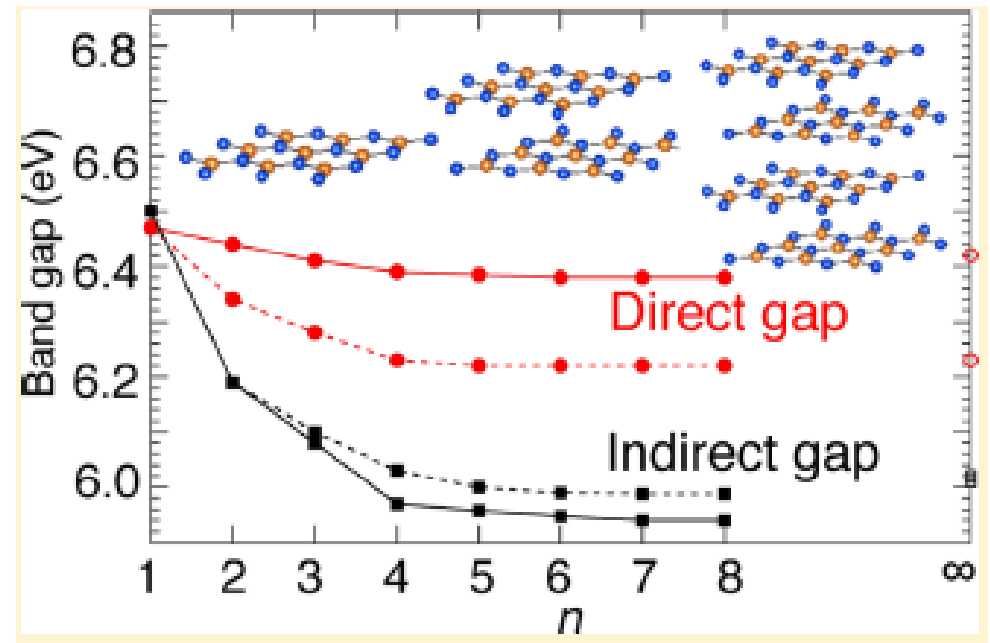
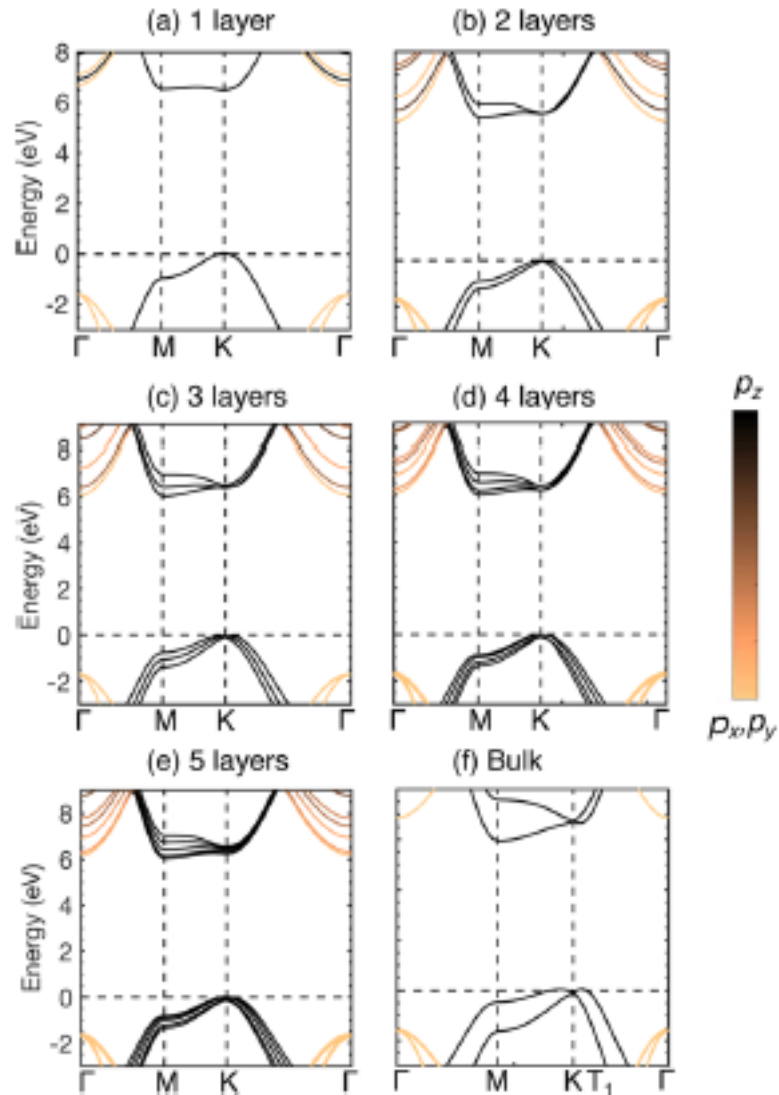
R. V. Gorbachev^{1*}, I. Riaz¹, R. R. Nair¹, R. Jalil¹, L. Britnell¹, B. D. Belle¹, E. W. Hill¹, K. S. Novoselov¹, K. Watanabe², T. Taniguchi², A. K. Geim¹, P. Blake^{1*}

¹Manchester Centre for Mesoscience & Nanotechnology, University of Manchester, Manchester M13 9PL, UK

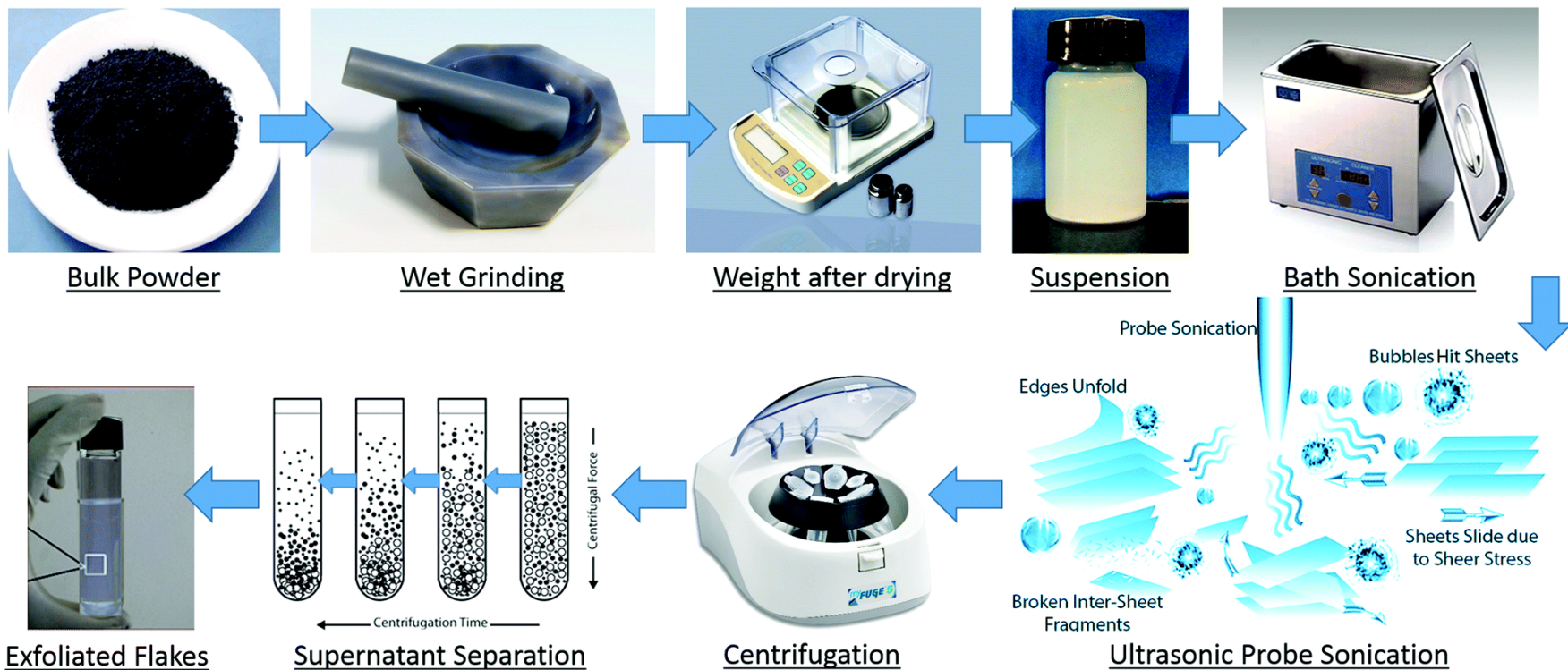
²National Institute for Materials Science, 1-1 Namiki, Tsukuba, 305-0044 Japan



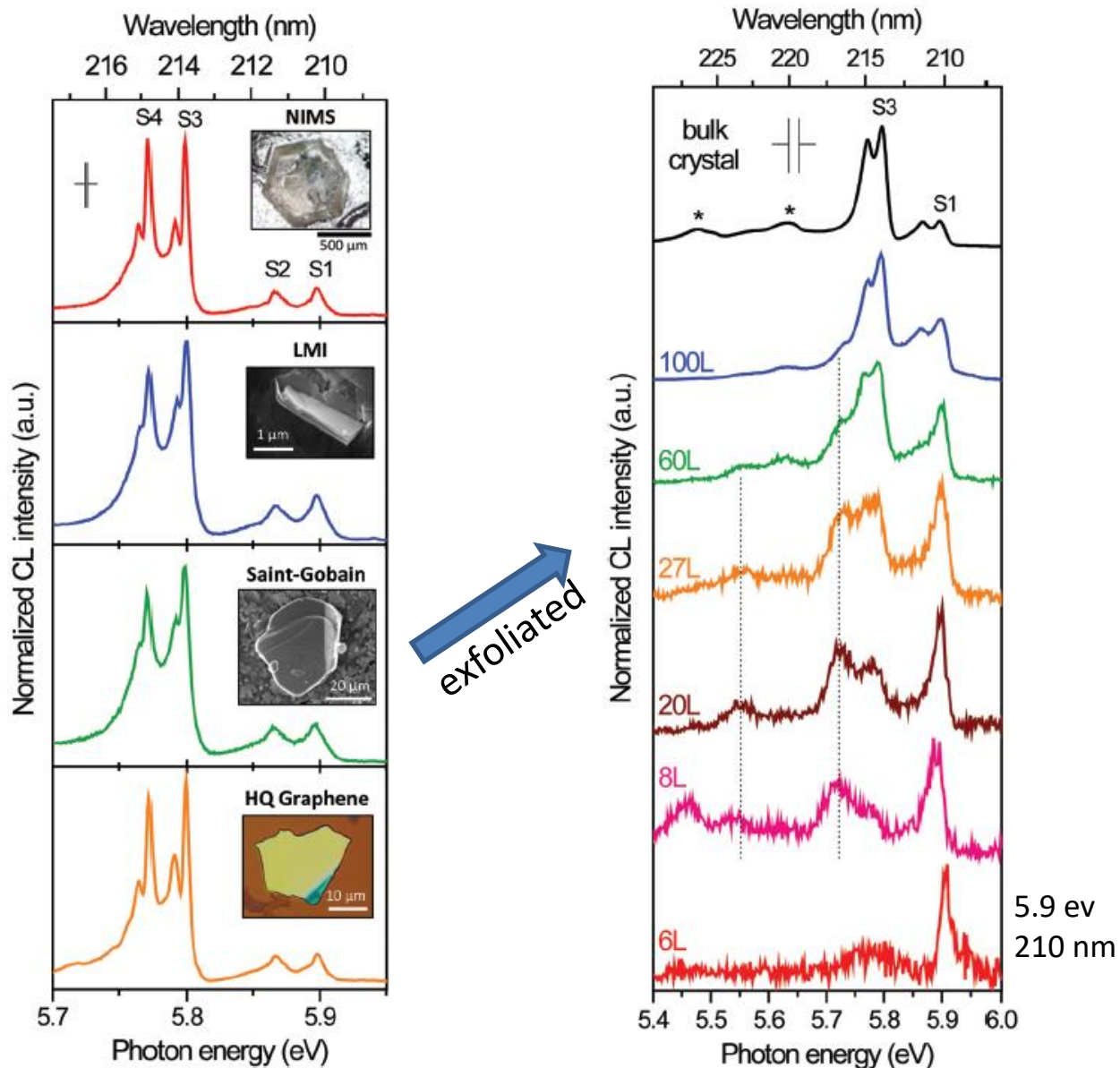
From Monolayer to Bulk, from Direct to Indirect Bandgap



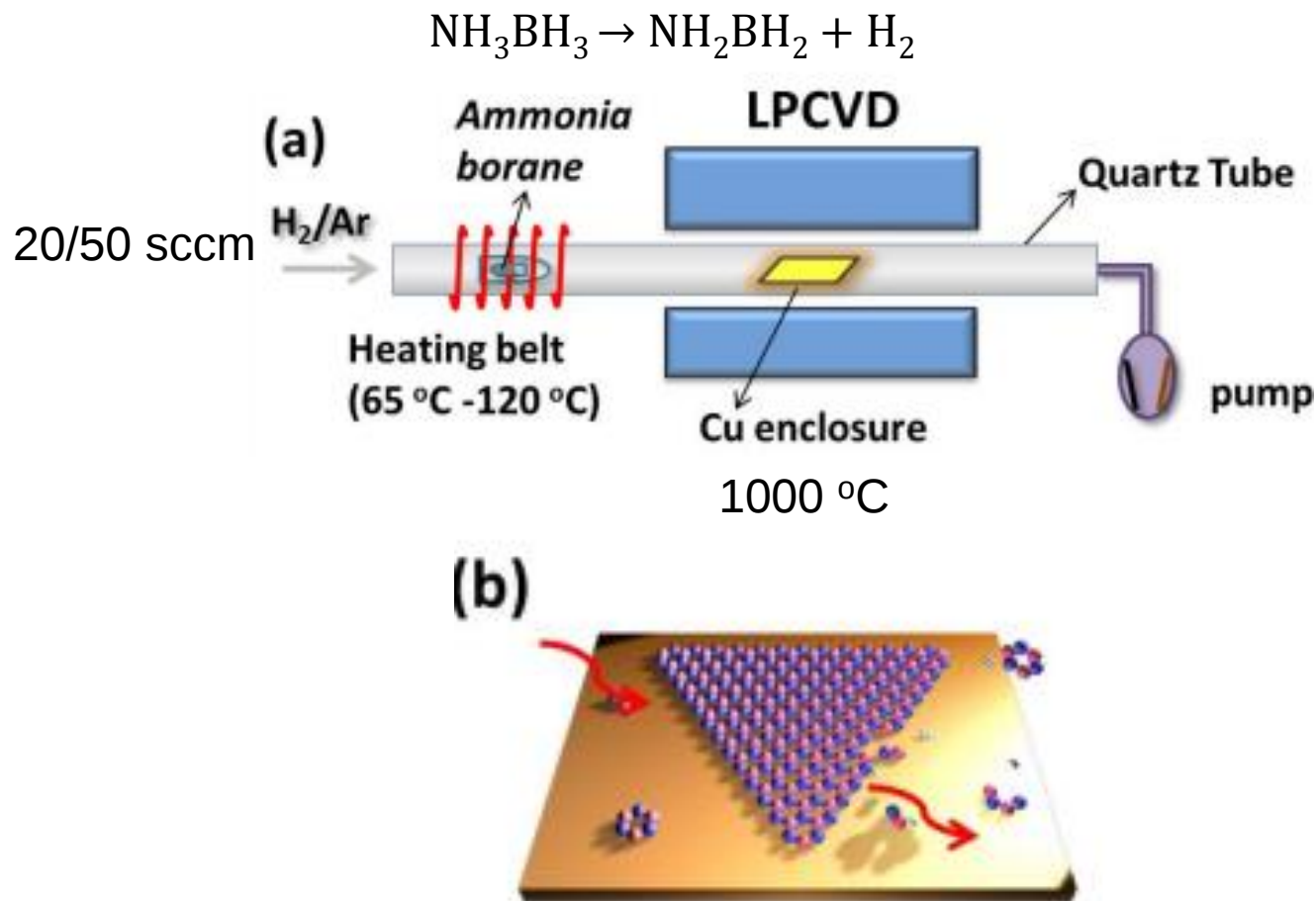
Exfoliation of Bulk hBN to form hBN flakes



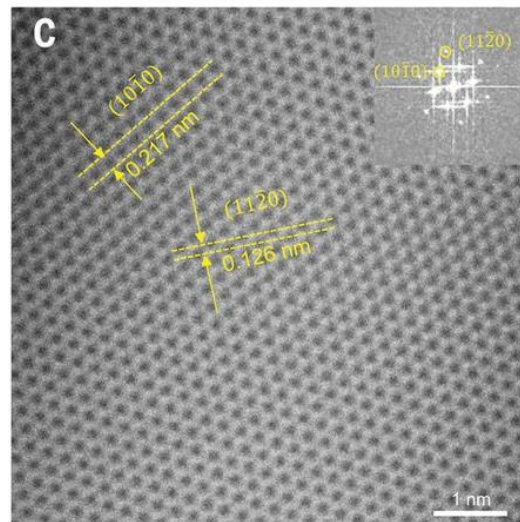
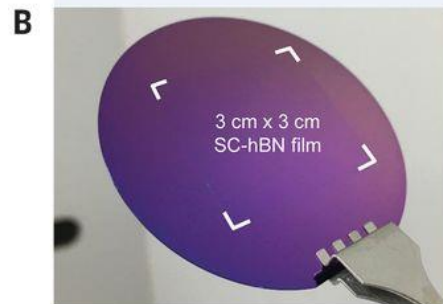
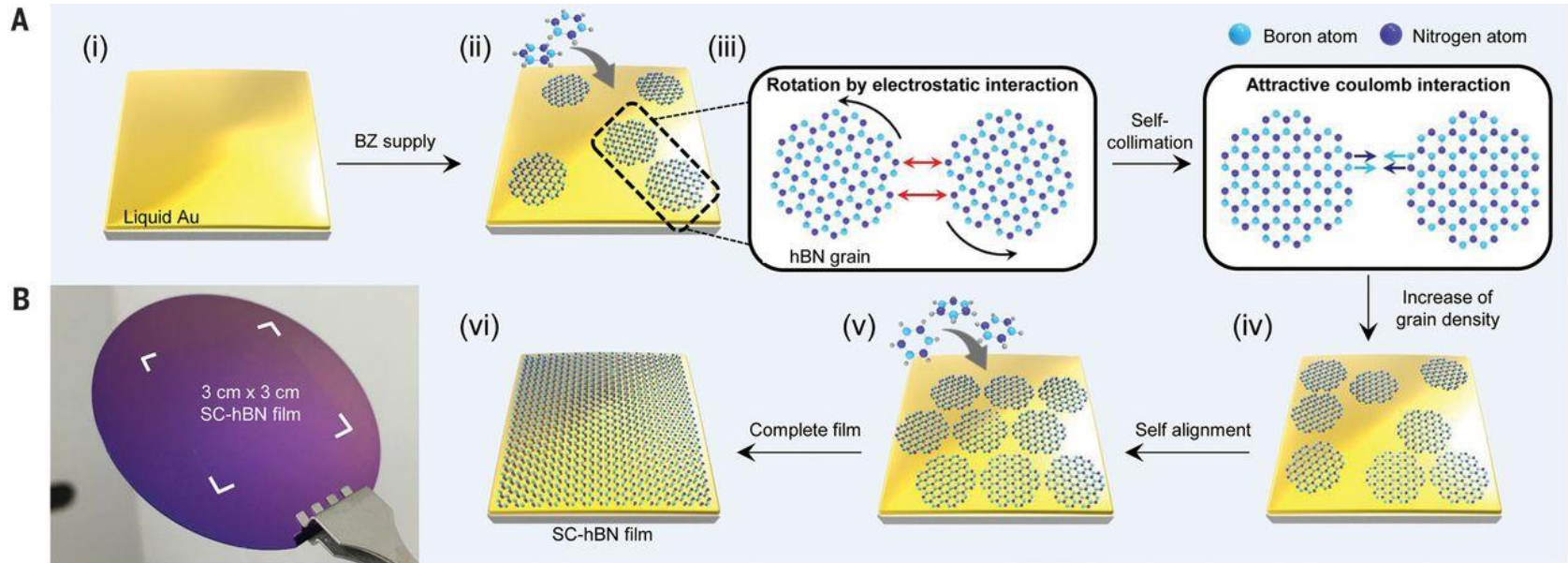
Luminescence from Bulk to Thin Films



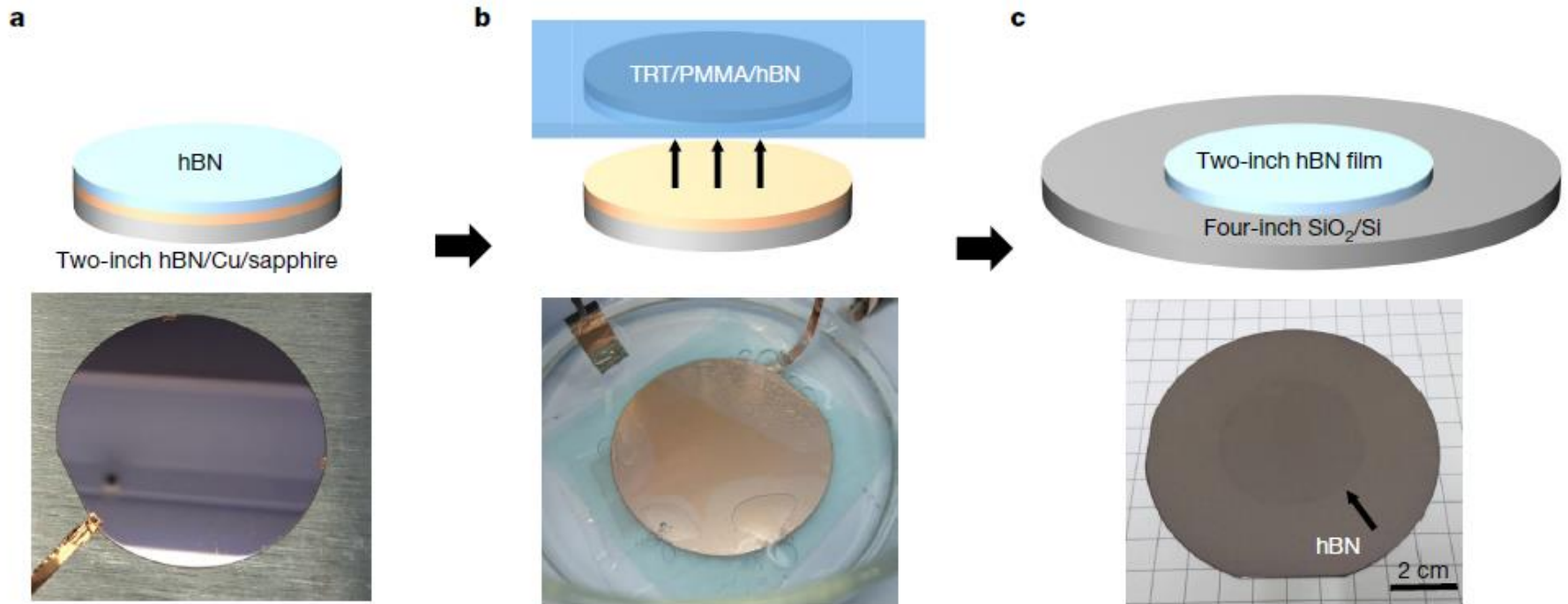
LPCVD hBN Growth & Transfer



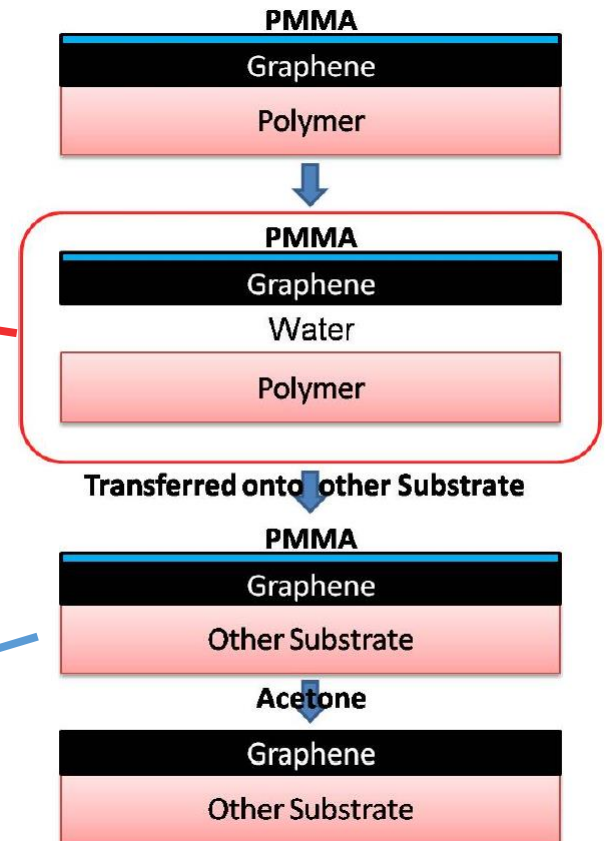
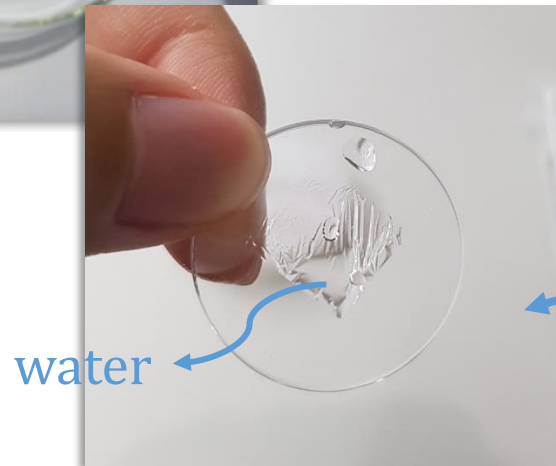
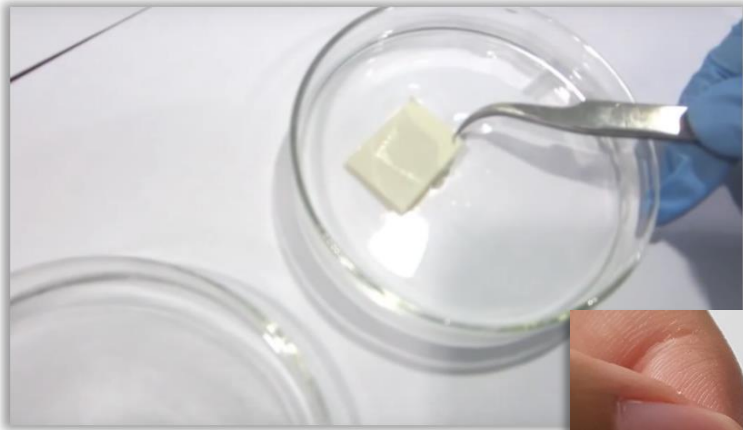
Wafer-scale single-crystal hexagonal boron nitride film via self-collimated grain formation (KIST, Korea)



Wafer-scale single-crystal hexagonal boron nitride monolayers on Cu (111), (tsmc, NCTU)

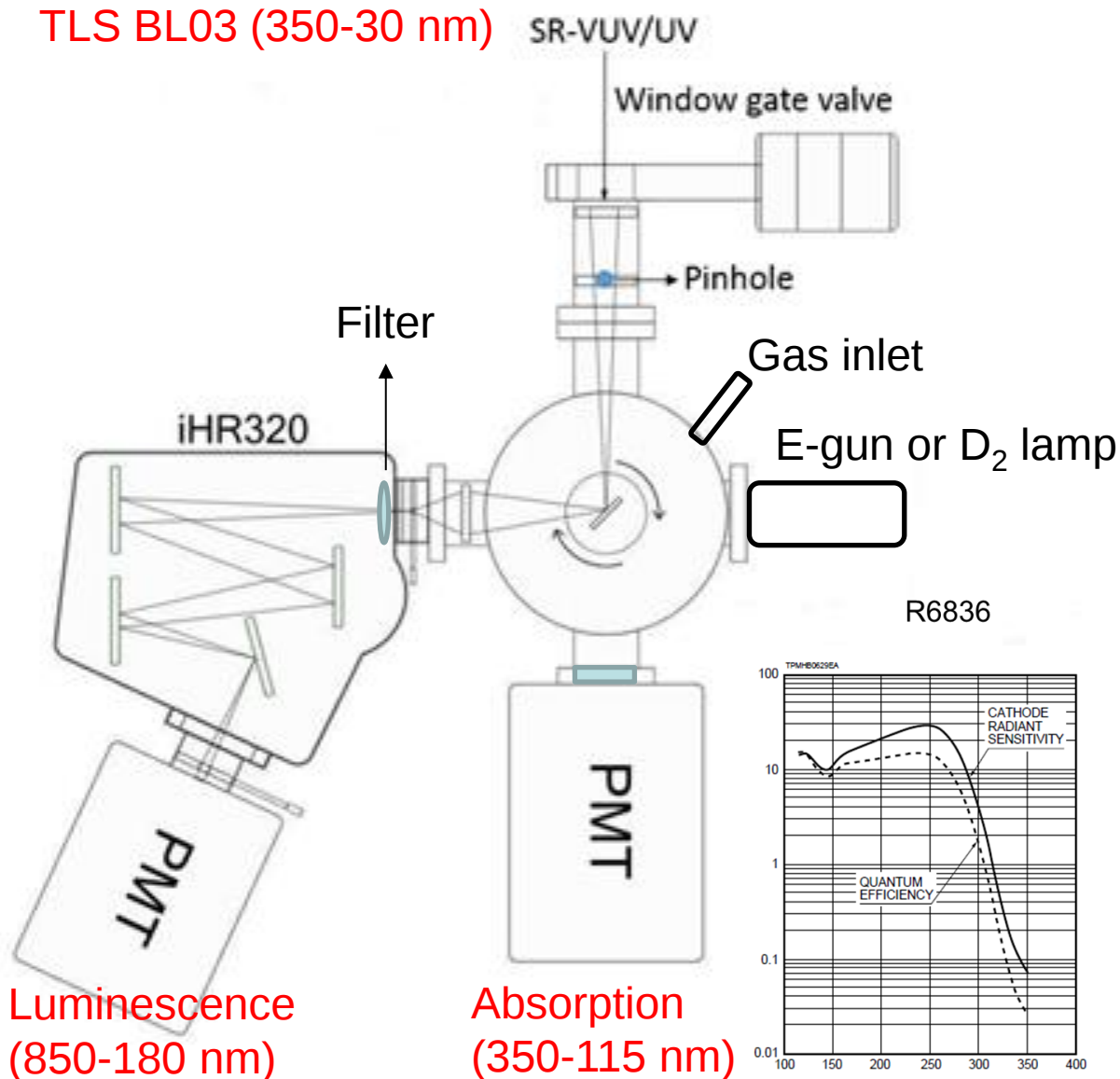


Wet Transfer Process

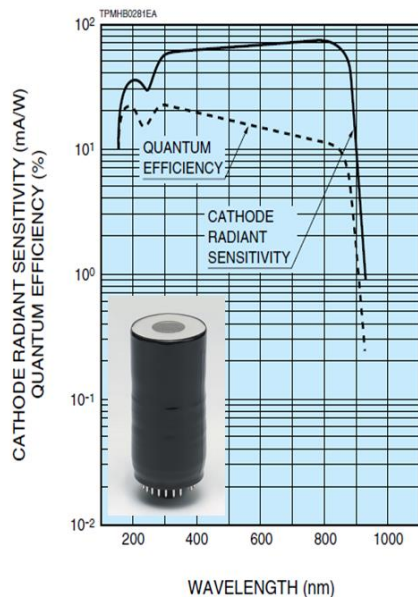


Experimental Setup

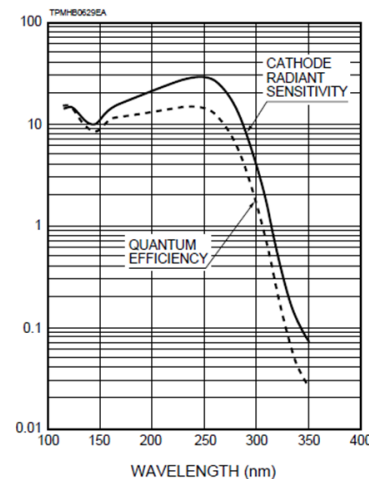
TLS BL03 (350-30 nm)



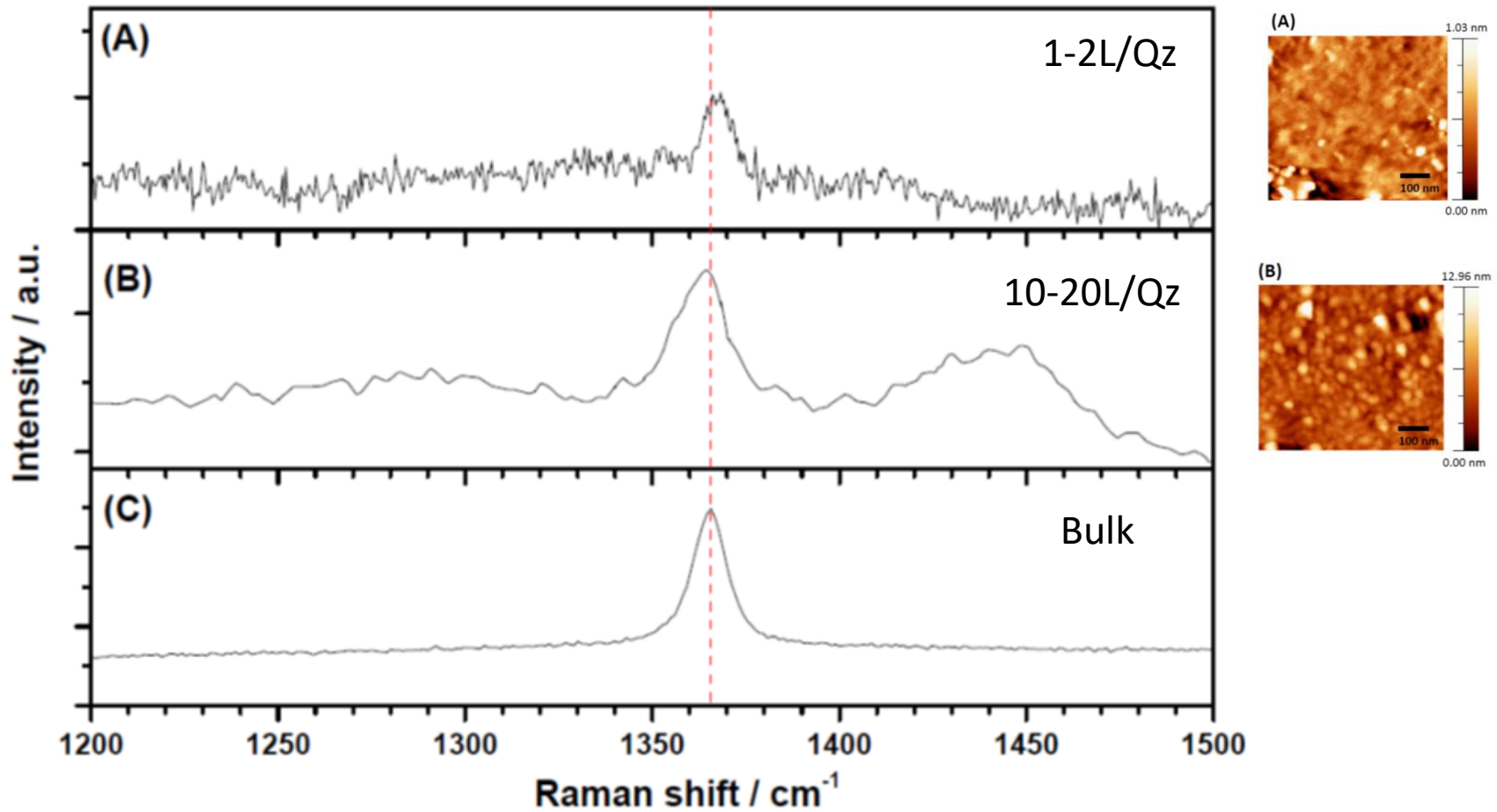
R943-02



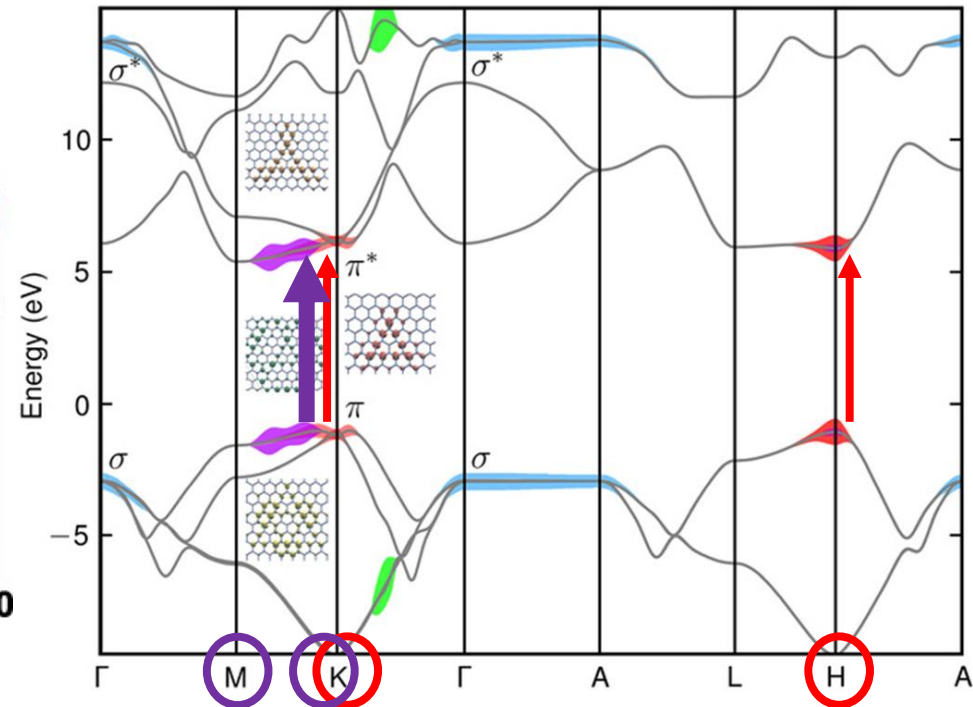
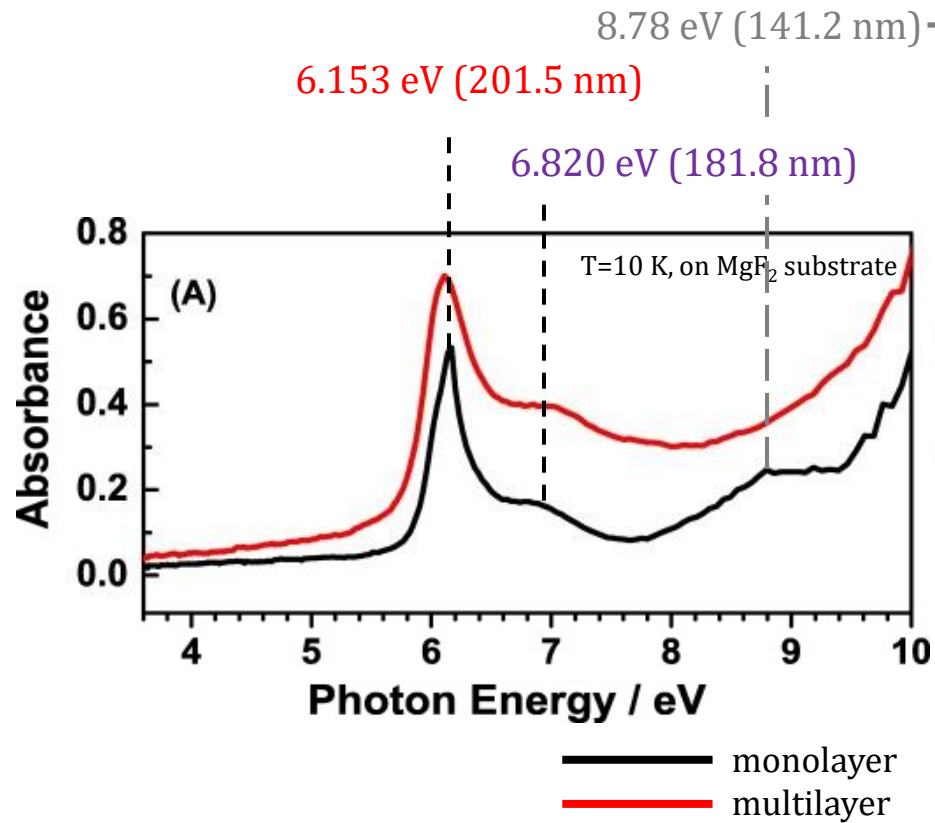
R6836



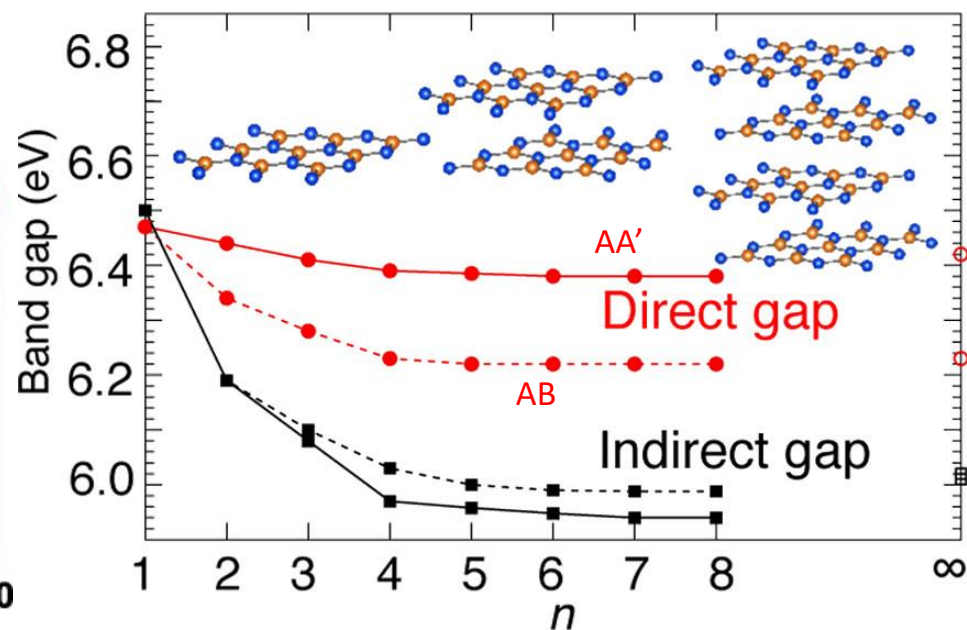
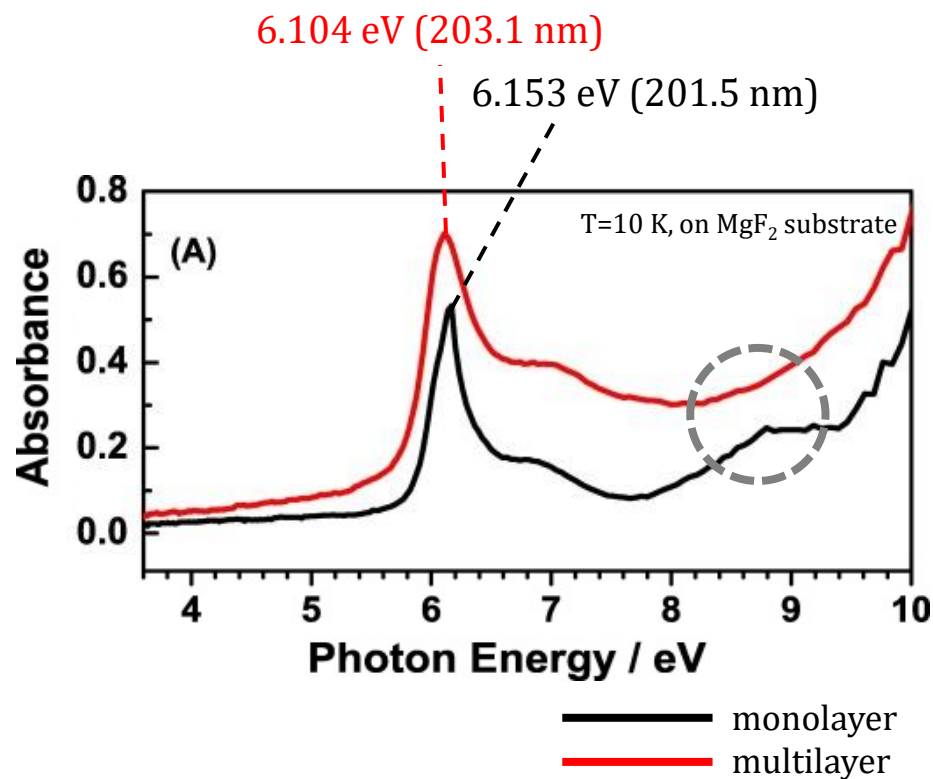
Raman Spectra & AFM Images of hBN Samples



Photoabsorption

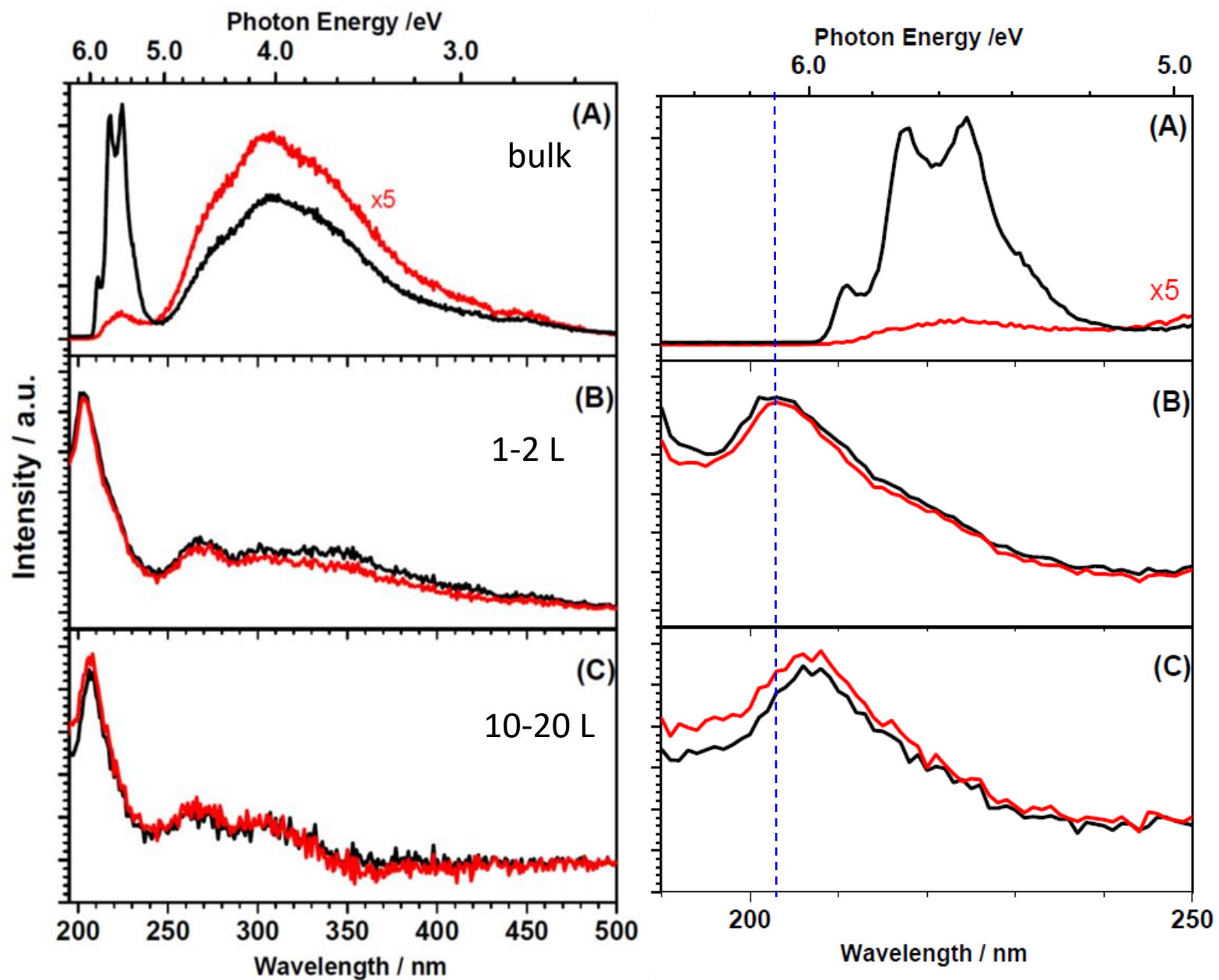


Photoabsorption

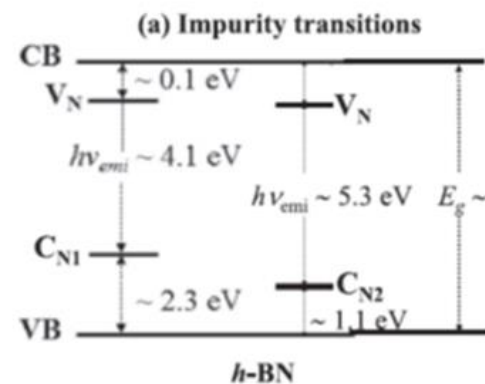
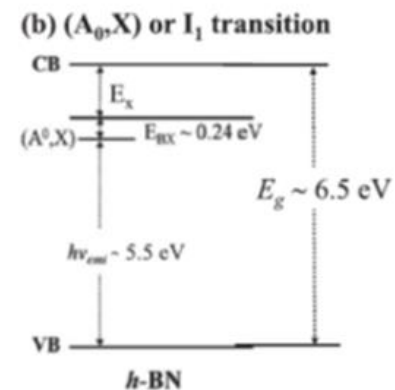
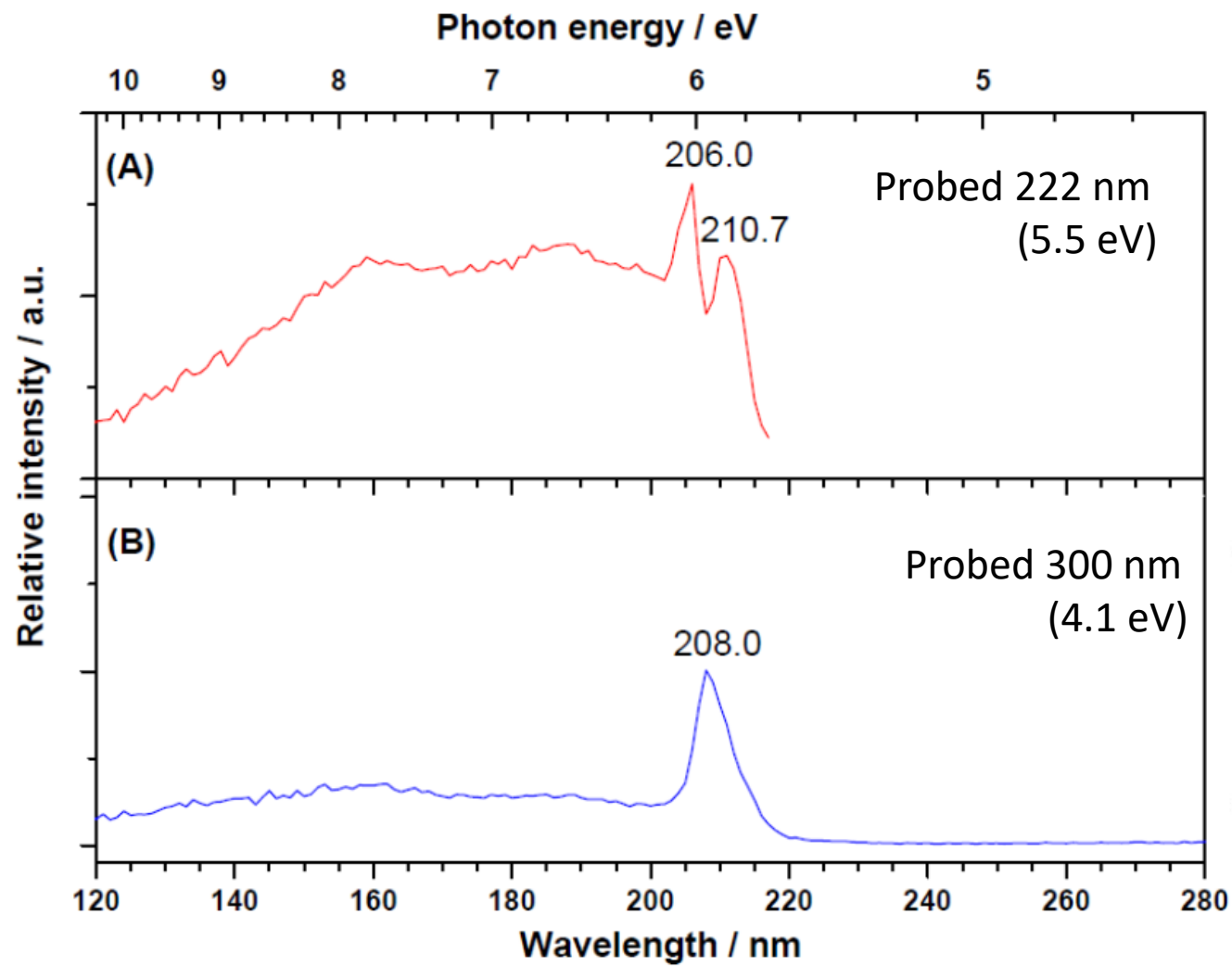


J. Phys. Chem. C 2018, 122, 44, 25524-25529

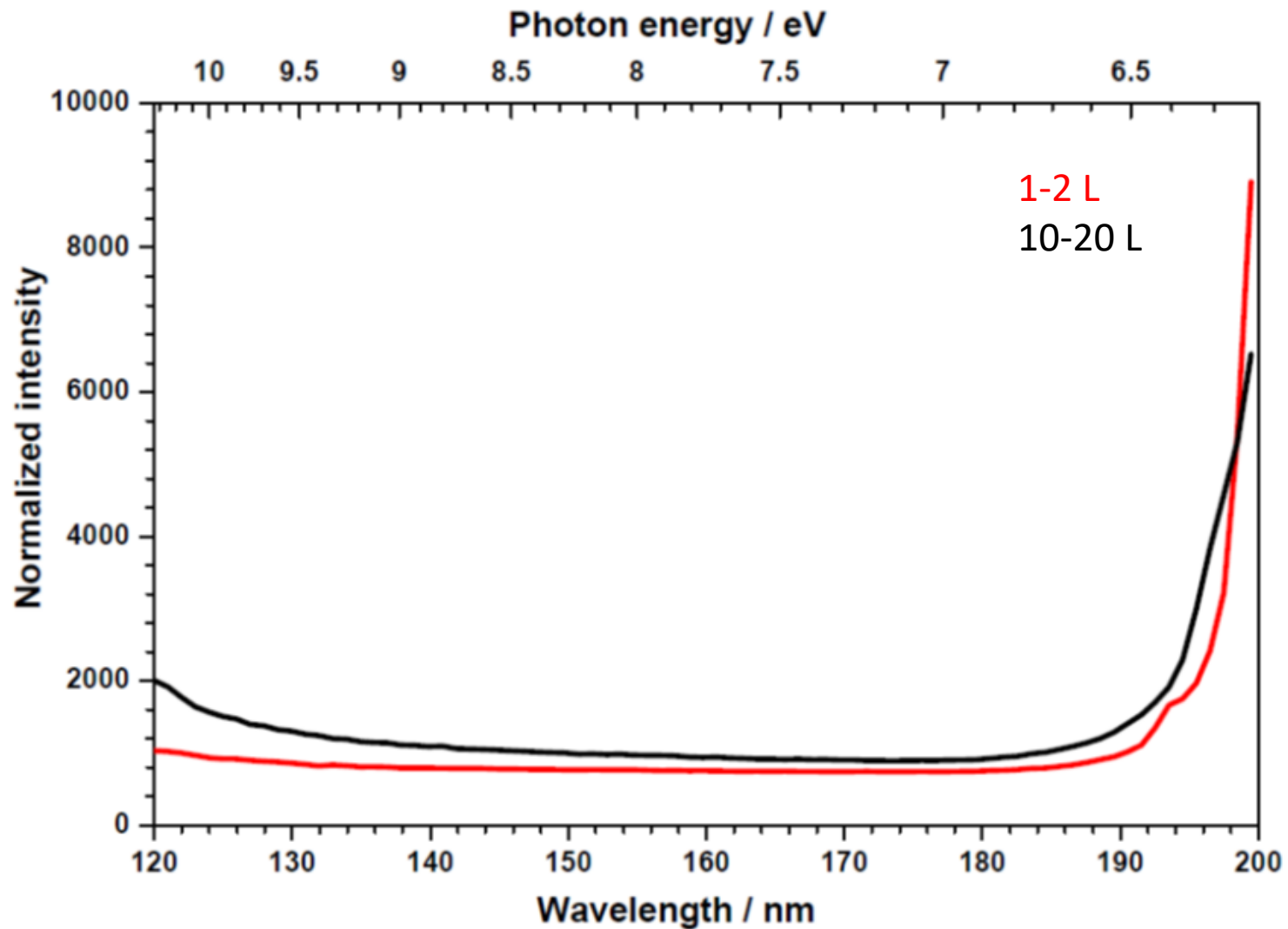
PL Spectra of Thin-film and Bulk hBN Excited at 180 nm



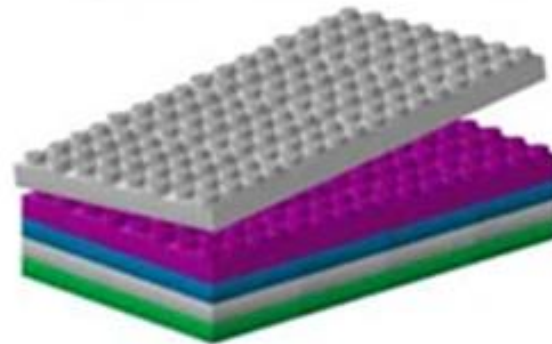
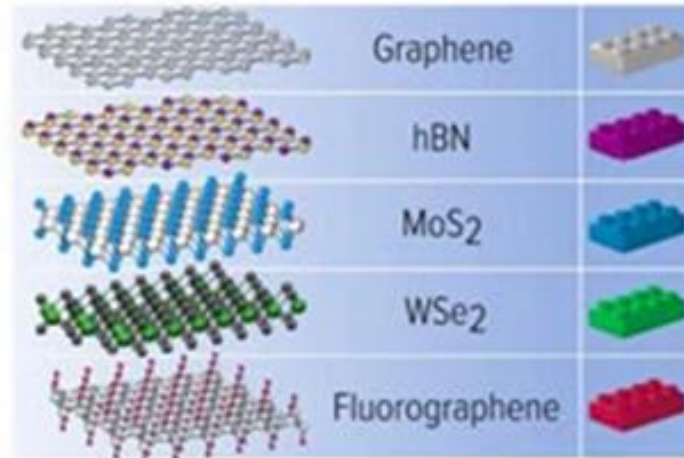
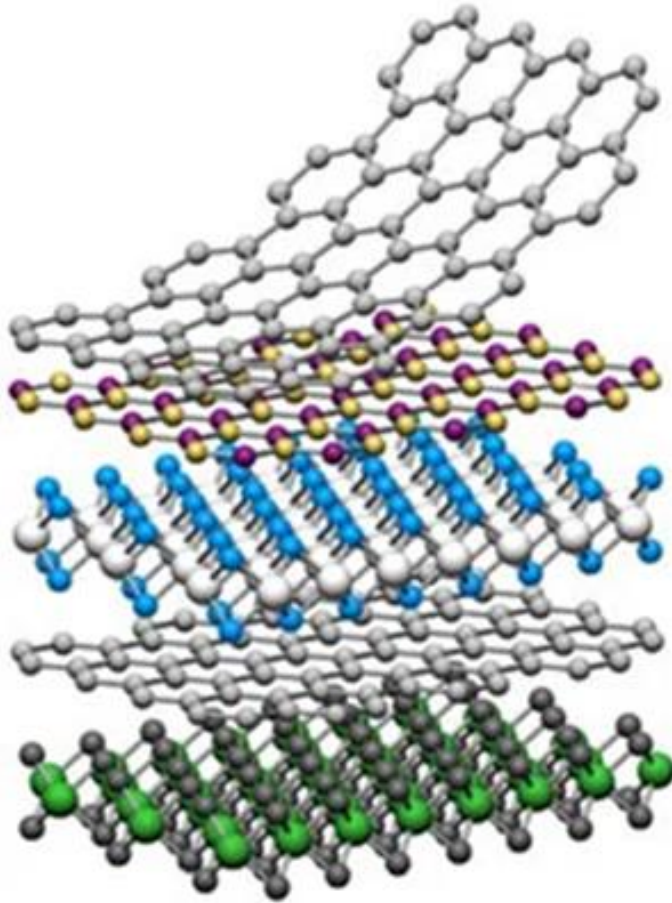
PL Excitation Spectra of Bulk hBN



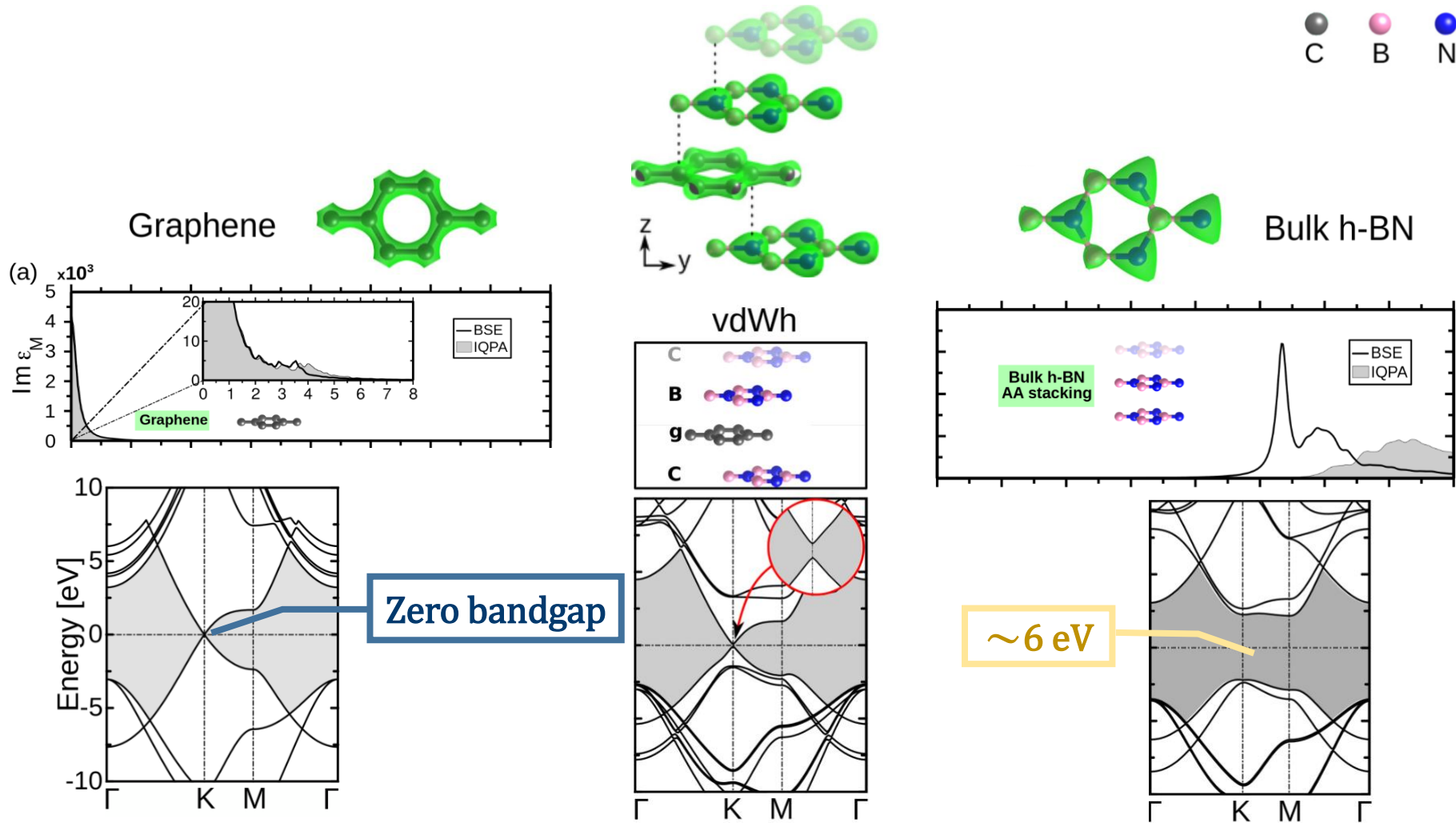
PL Excitation Spectra of hBN Thin Films



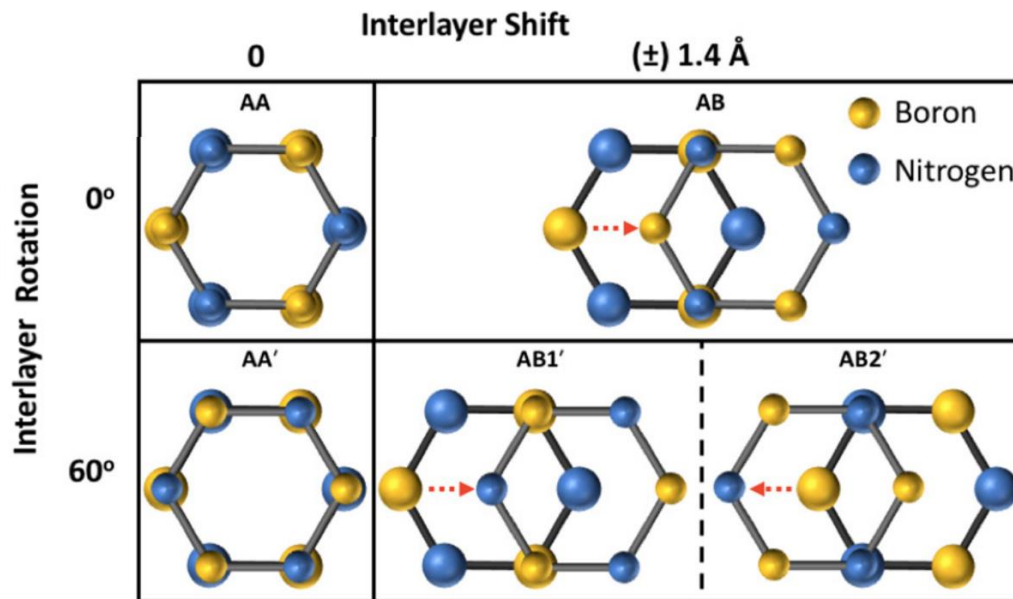
Heterostructured 2D-Materials (vdw materials)



Gr/hBN vdW Materials

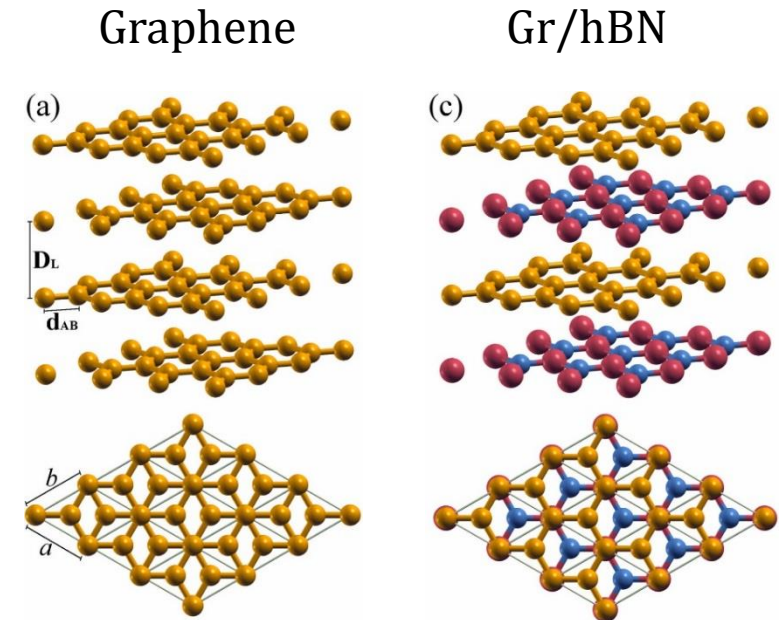


Stacking Order



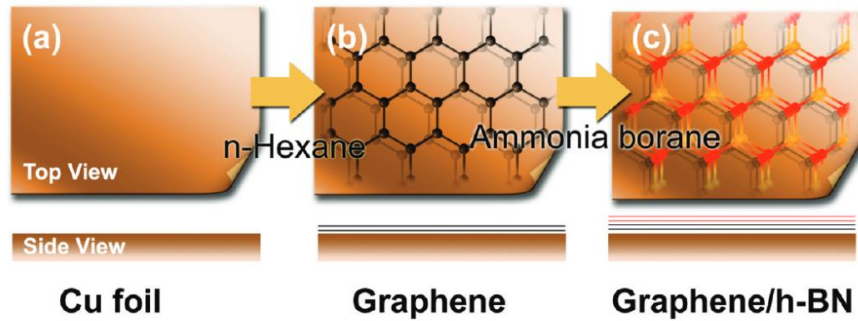
S Matt Gilbert *et al* 2019 *2D Mater.* 6 021006

AA' Stacking

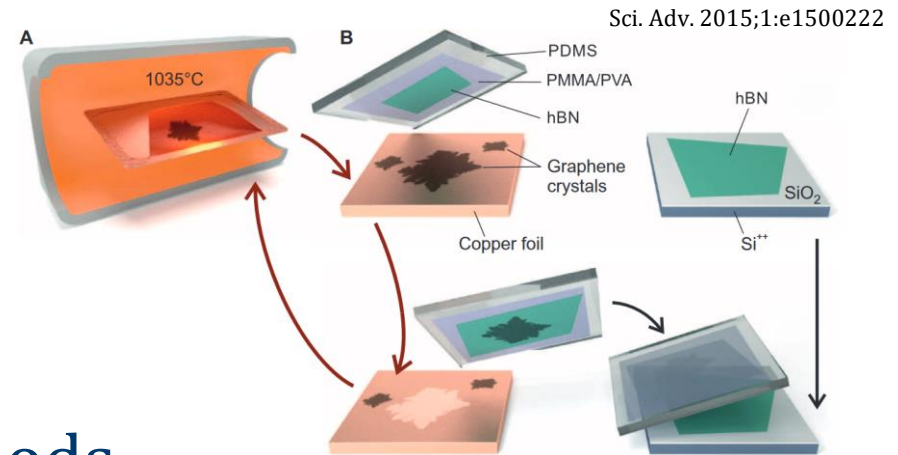


AB Stacking

Multistage deposition techniques on substrates



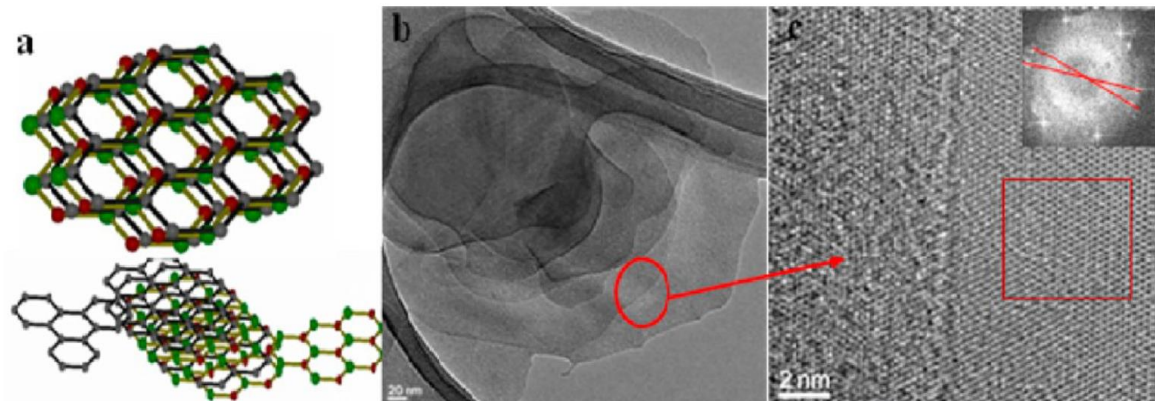
Nano Lett. 2011, 11, 2032–2037



Sci. Adv. 2015;1:e1500222

Liquid phase exfoliation methods

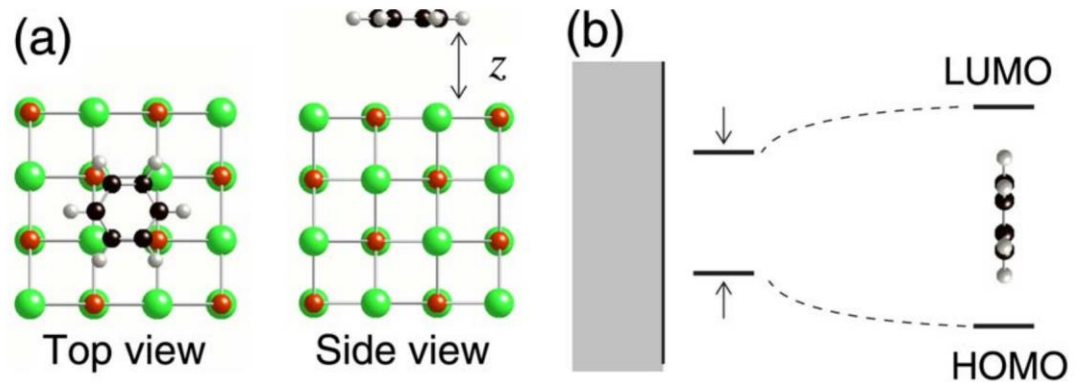
stack randomly



Nano Lett. 2012, 12, 3518–3525

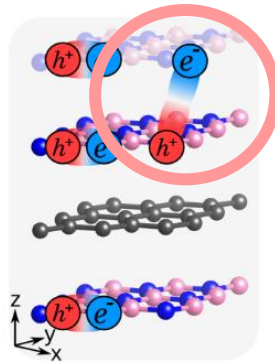
New Properties in Gr/hBN vdWh

Polarization effect

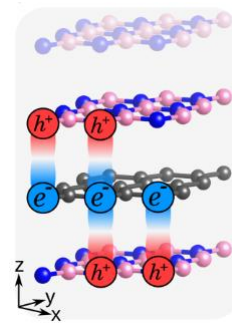


Charge-Transfer

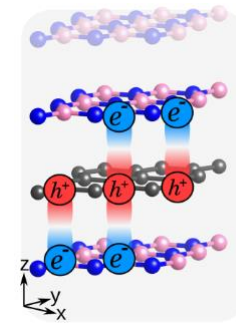
hBN $\rightarrow$ hBN



hBN $\rightarrow$ Gr



Gr $\rightarrow$ hBN

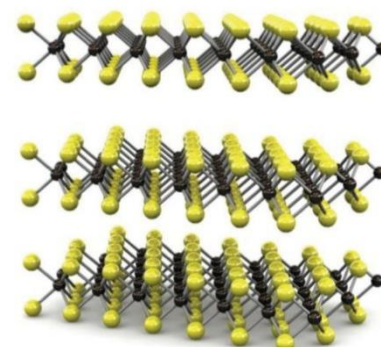


Transition metal dichalcogenide (TMDCs)

Chemical formula : MX_2

H																	He
Li	Be	MX₂ M = Transition metal X = Chalcogen										B	C	N	O	F	Ne
Na	Mg	3	4	5	6	7	8	9	10	11	12	Al	Si	P	S	Cl	Ar
K	Ca	Sc	Ti	V	Cr	Mn	Fe	Co	Ni	Cu	Zn	Ga	Ge	As	Se	Br	Kr
Rb	Sr	Y	Zr	Nb	Mo	Tc	Ru	Rh	Pd	Ag	Cd	In	Sn	Sb	Te	I	Xe
Cs	Ba	La - Lu	Hf	Ta	W	Re	Os	Ir	Pt	Au	Hg	Tl	Pb	Bi	Po	At	Rn
Fr	Ra	Ac - Lr	Rf	Db	Sg	Bh	Hs	Mt	Ds	Rg	Cn	Uut	Fl	Uup	Lv	Uus	Uuo

Chalcogen



VdW interaction



Insulator: HfS_2

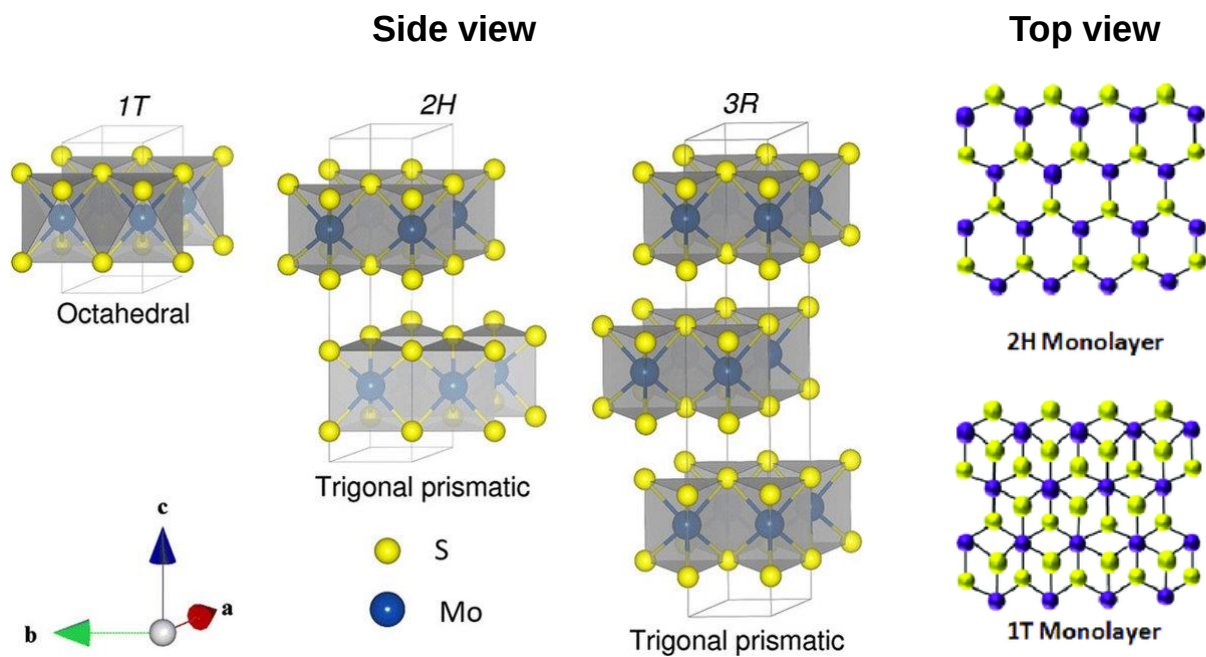
Semiconductor: MoS_2 / WS_2

Semi-metal: WTe_2

Metal: VSe_2

Coordination Chemistry Reviews **2022**, 472, 214765.

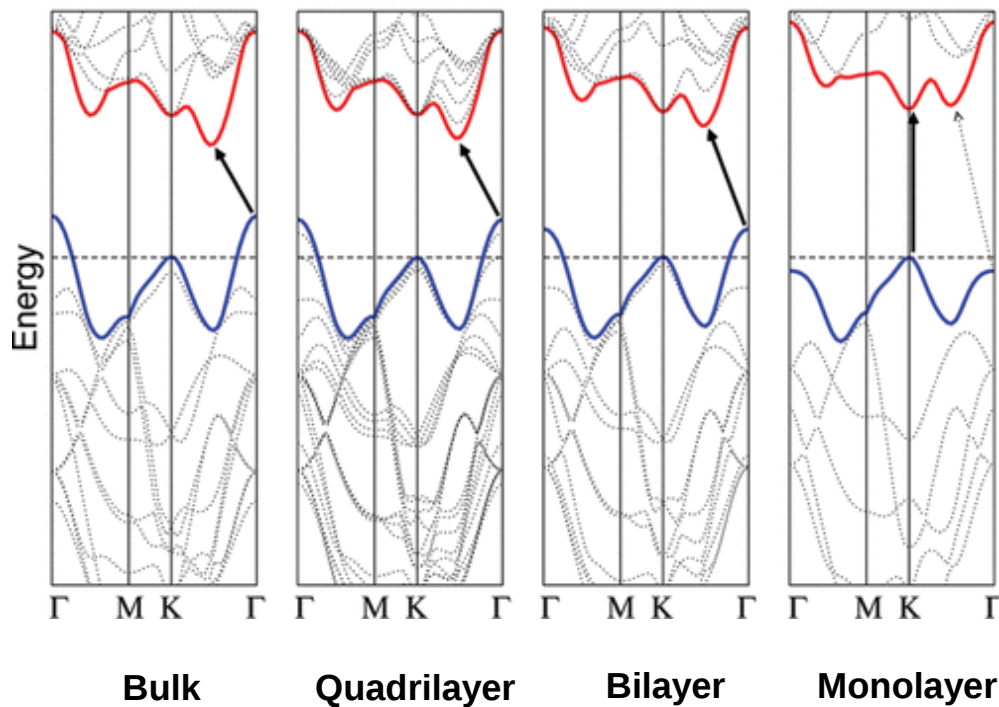
Crystal structures of MoS₂



Energy Science & Engineering **2016**, 4 (5), 285–304.

Materials **2021**, 14 (12), 3283.

Band structure of MoS₂

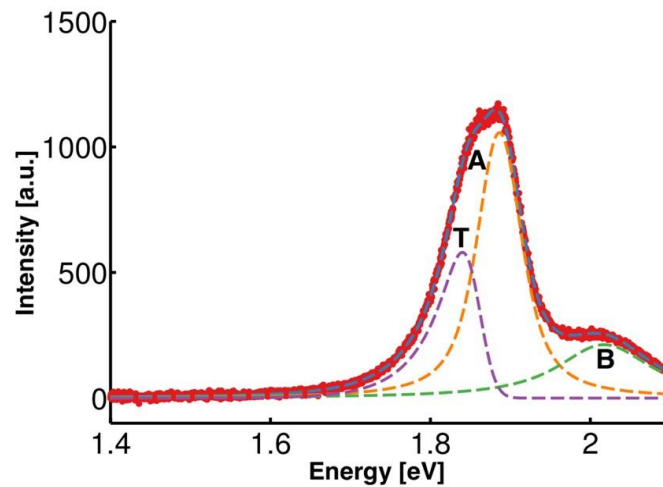
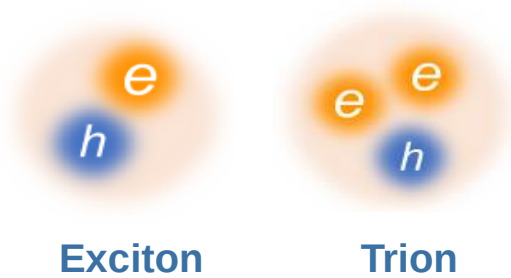


Bulk → **Monolayer**
Indirect → **Direct**

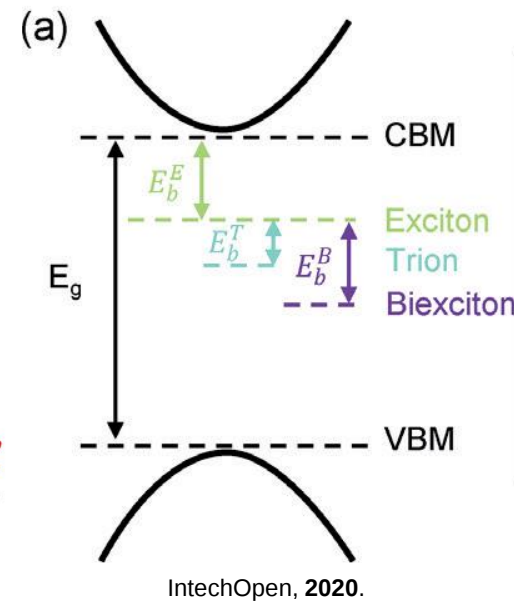
Nano Lett. **2010**, 10 (4), 1271–1275.

Exciton and trion

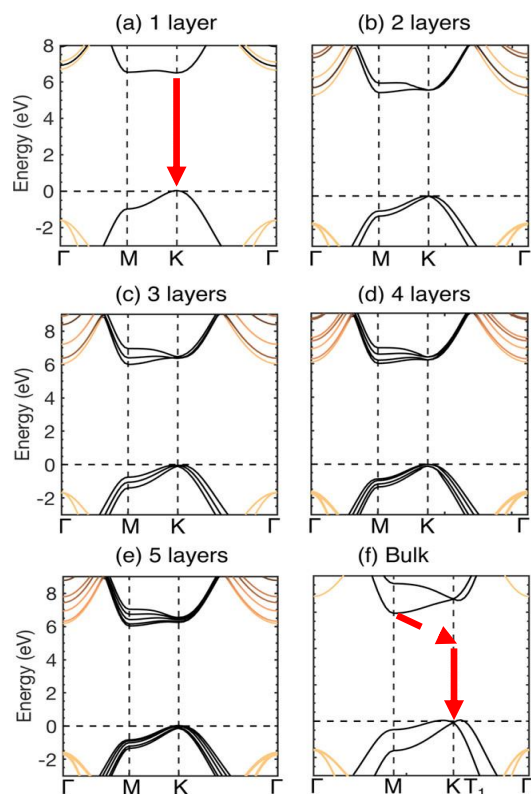
➤ Characteristic property of 2D TMDCs



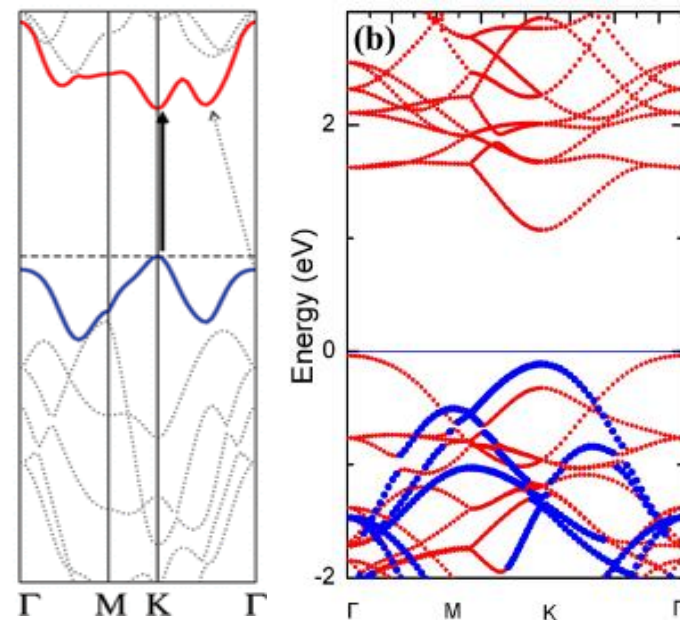
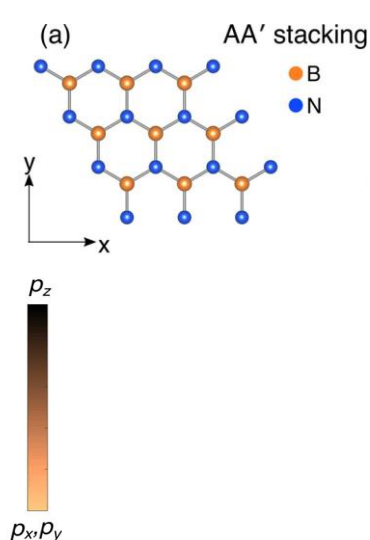
Nat Commun 2021, 12 (1), 6131.



Band structure of hBN and MoS₂ / hBN heterostructure



J. Phys. Chem. C 2018, 122, 44, 25524-25529



Bulk → **Monolayer**

Indirect → **Direct**

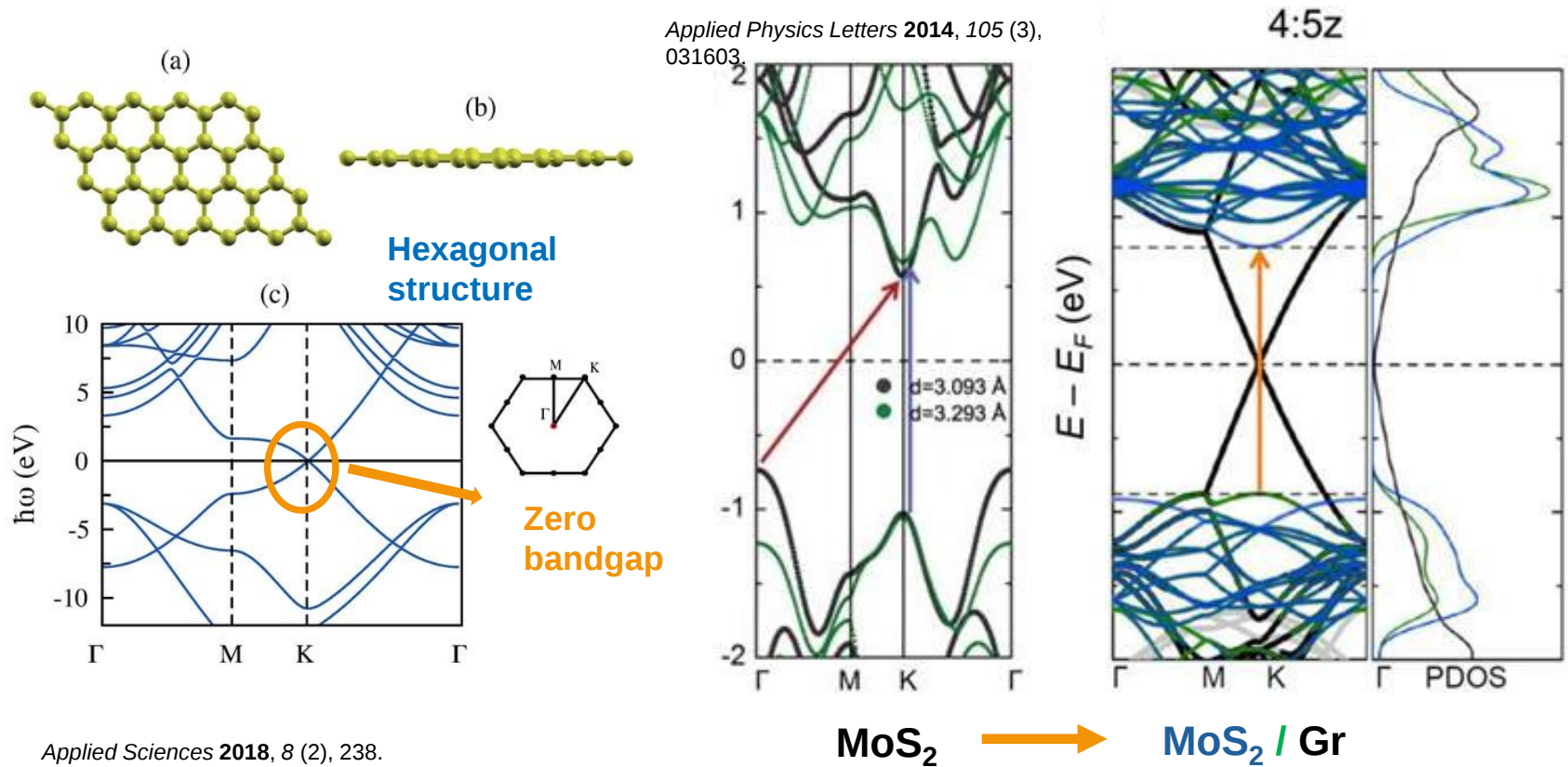
MoS₂



**MoS₂ /
hBN**

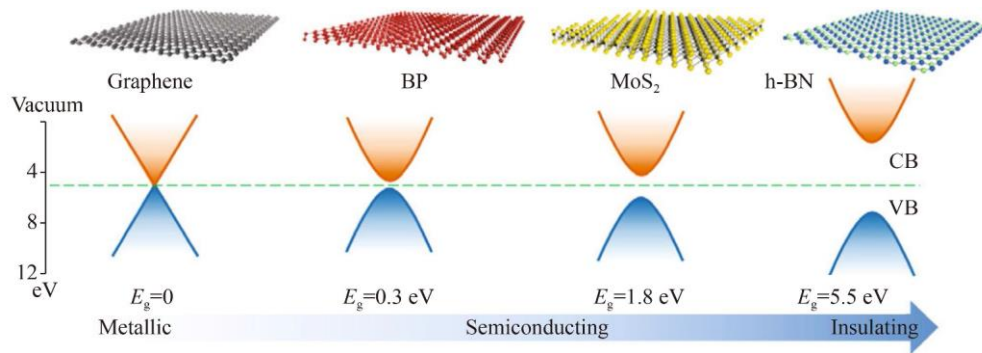
J. Phys. D: Appl. Phys. **2014**, 47 (7), 075301

Band structure of Gr and MoS₂ / Gr heterostructure

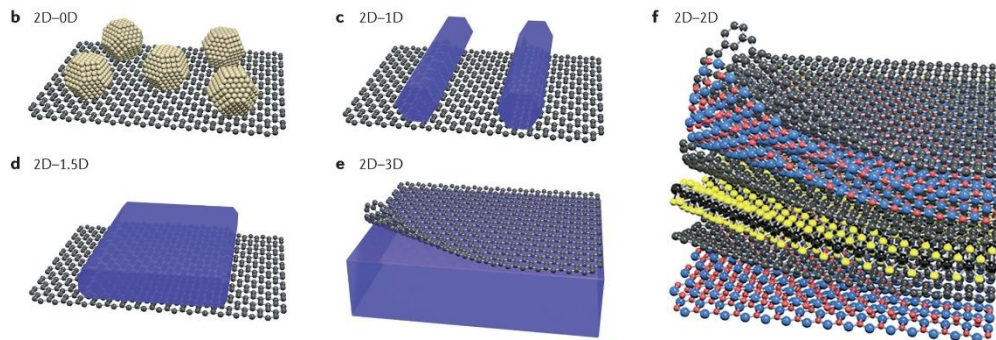


Applied Sciences **2018**, 8 (2), 238.

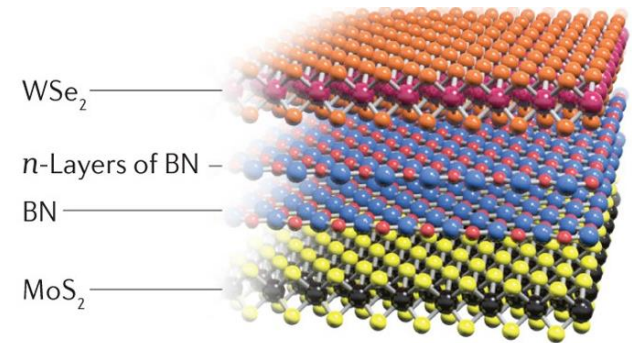
Van der Waals heterostructure



Front. Phys. **2022**, 17 (4), 43202.

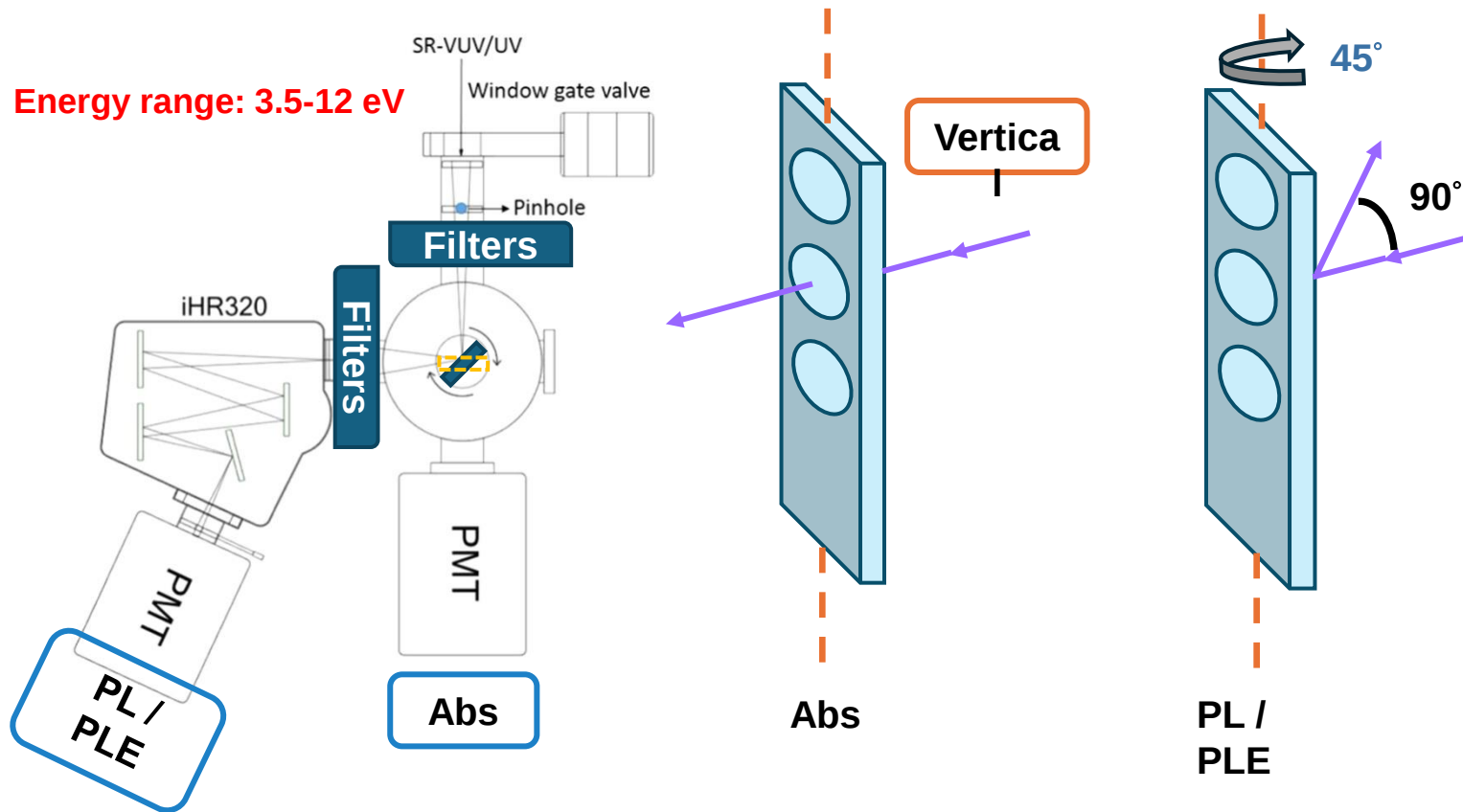


Nature Reviews Materials **2016**, 1 (9), 16042.

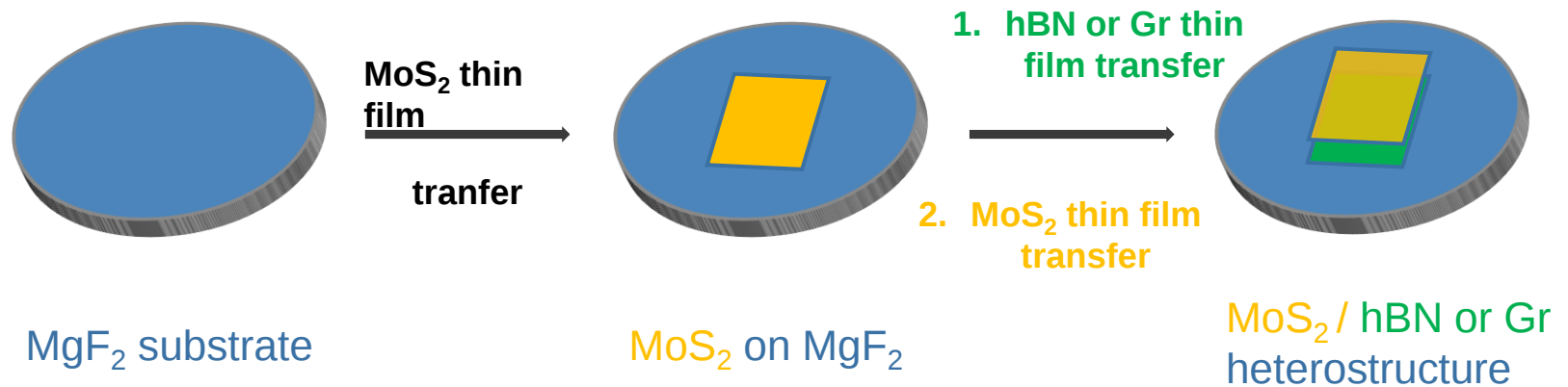


- Van der Waals interactions allow the integration of highly disparate materials without the constraints of crystal lattice matching.

TLS BL03 - Absorption and Photoluminescence measurements



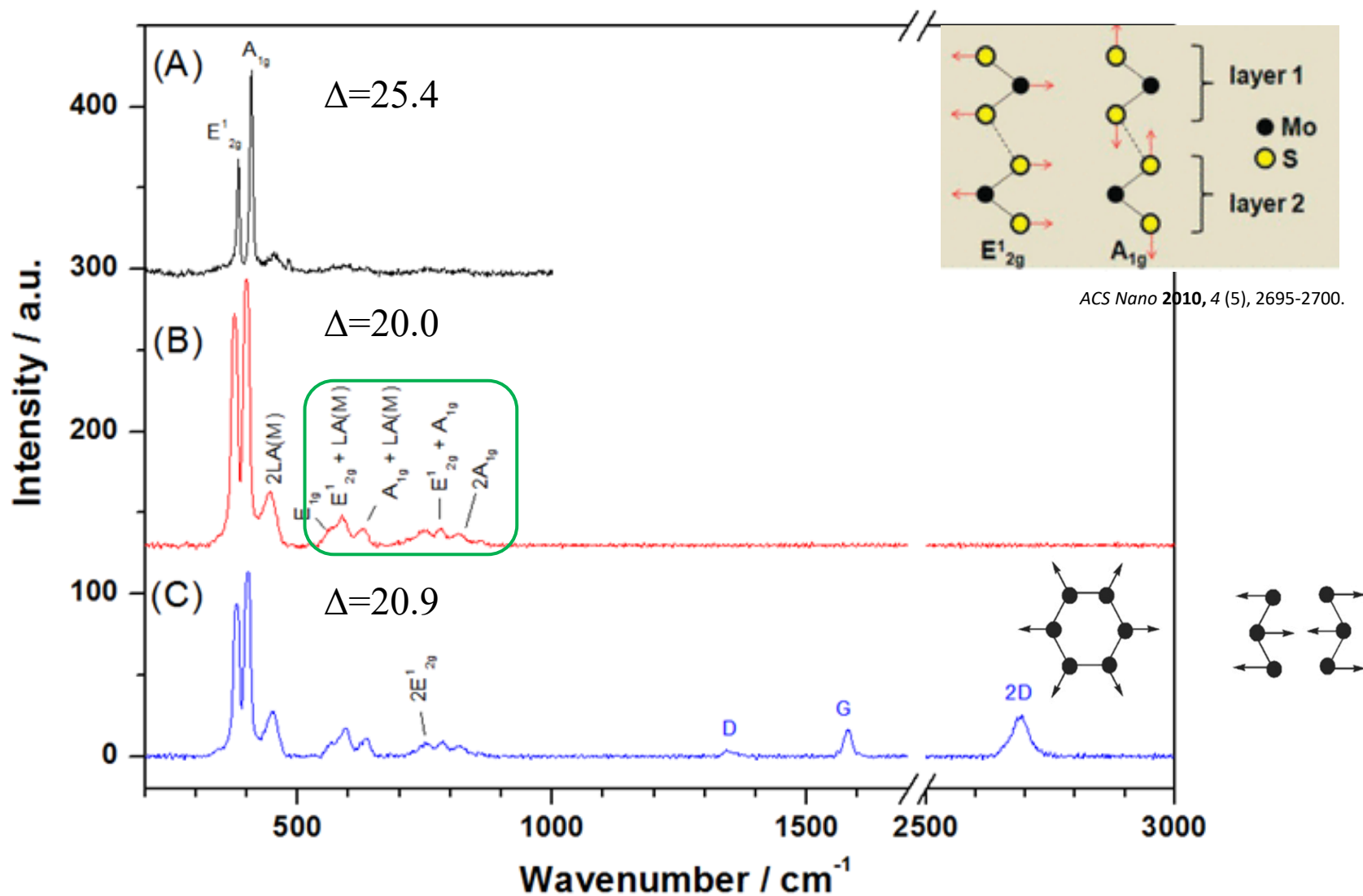
Sample preparation



The aims of the study

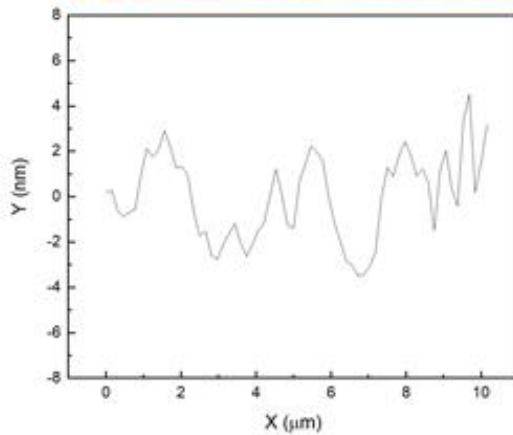
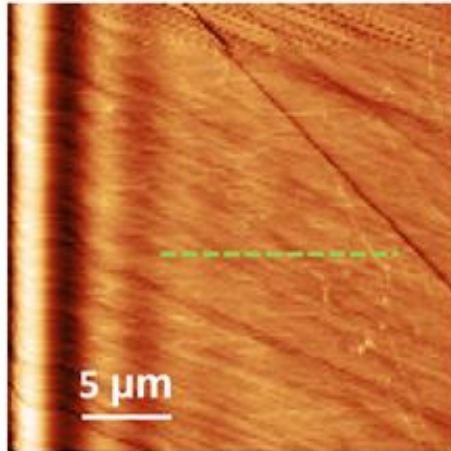
1. This study aims to provide information on the **absorption** and **photoluminescence** spectra of **MoS₂ and its heterostructures**, covering the range from **VUV to the visible** region.
2. This research investigates how **different optical substrates** influence the photoluminescence properties of MoS₂.
3. This study examines the **differences** in absorption and photoluminescence properties between **MoS₂ and its heterostructures**.
4. The study also investigates the characteristic photoluminescence properties of **hBN** or **Gr** layers.

Raman Spectra of MoS₂ and MoS₂ / hBN & MoS₂/Gr



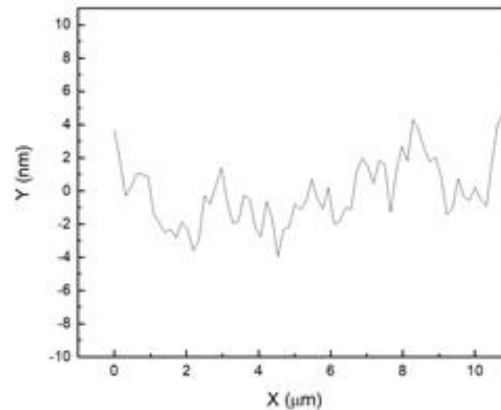
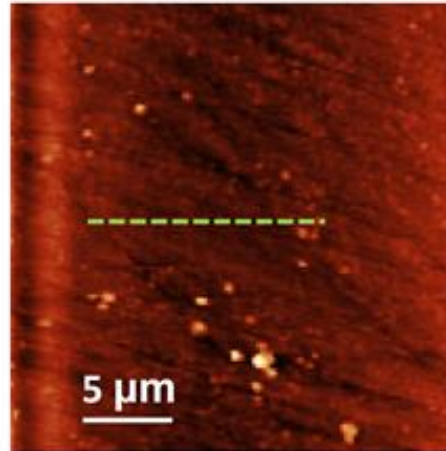
AFM images of MoS₂ and its heterostructures

(A) MoS₂/MgF₂



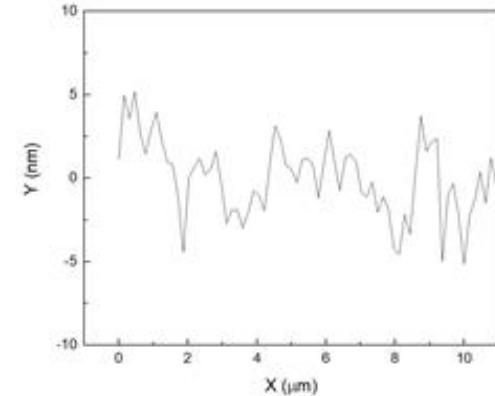
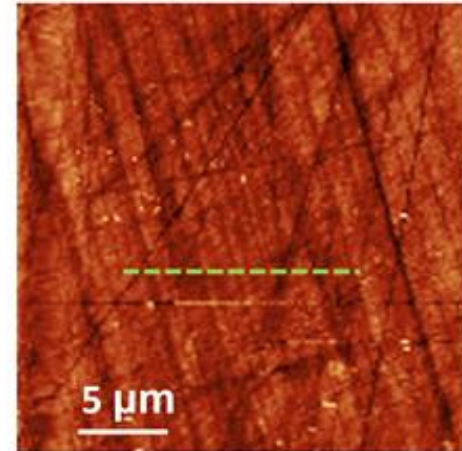
RMS roughness=1.41 nm

(B) MoS₂/hBN/MgF₂



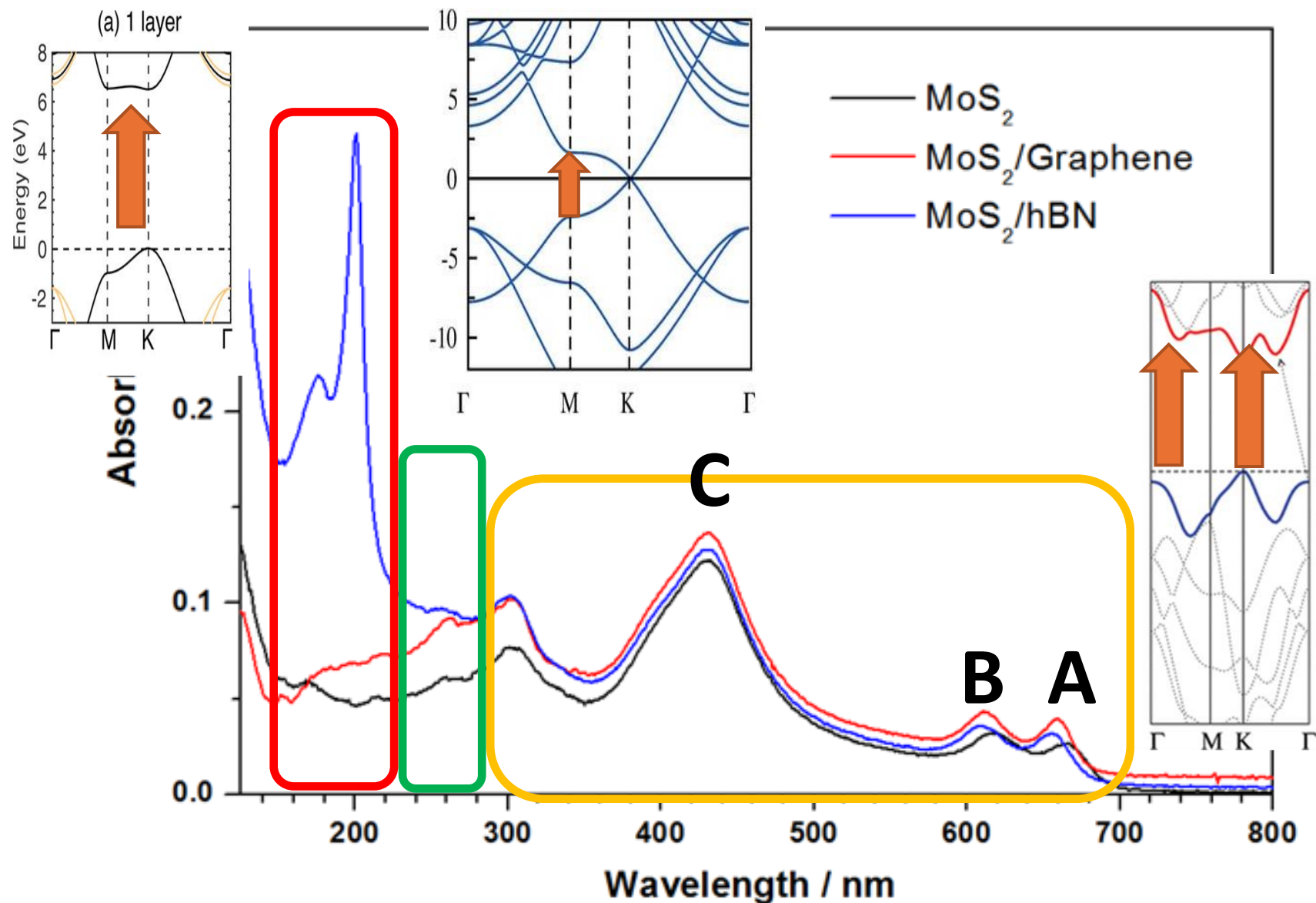
RMS roughness=1.40 nm

(C) MoS₂/Graphene/MgF₂

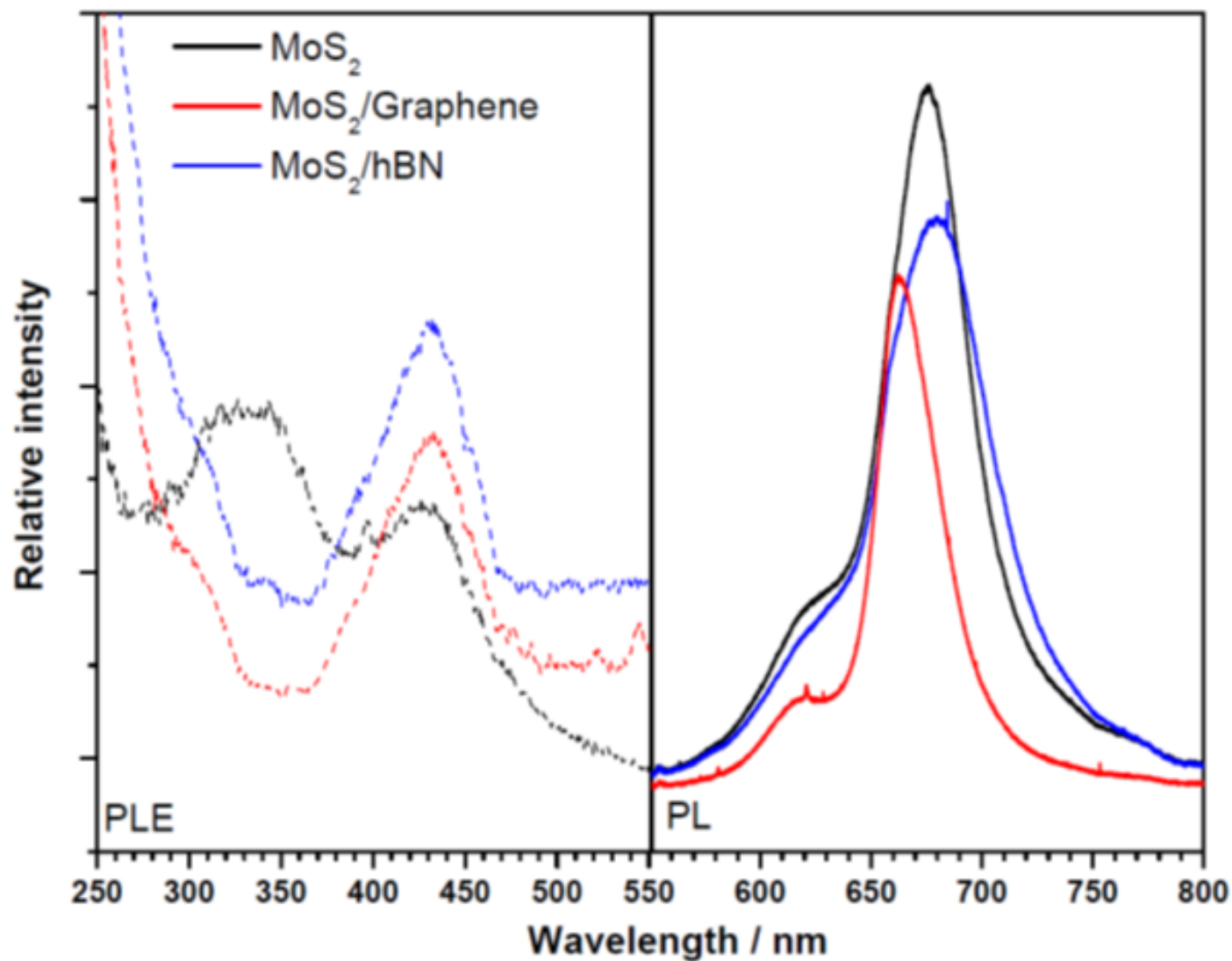


RMS roughness=1.58 nm

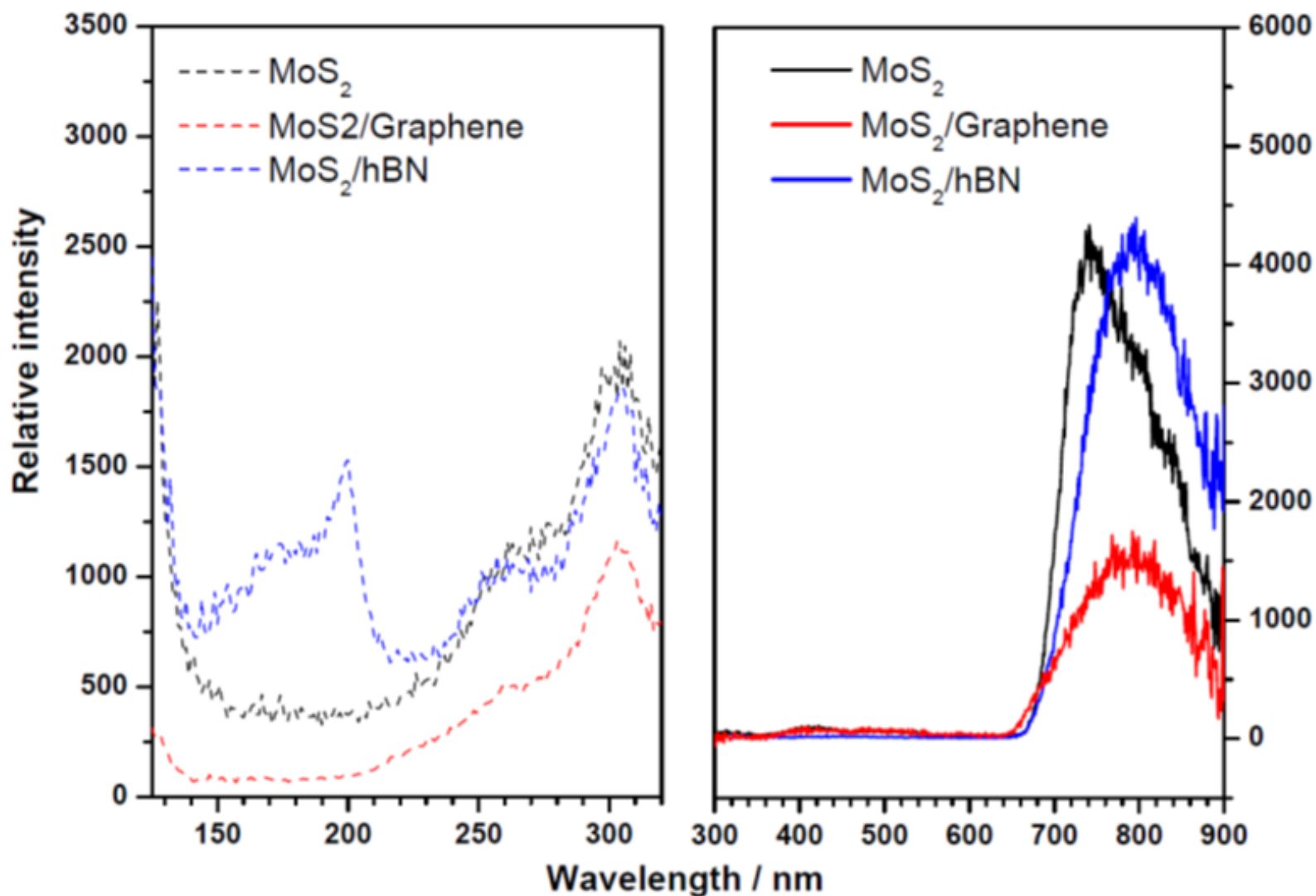
UV/VUV Absorption Spectra



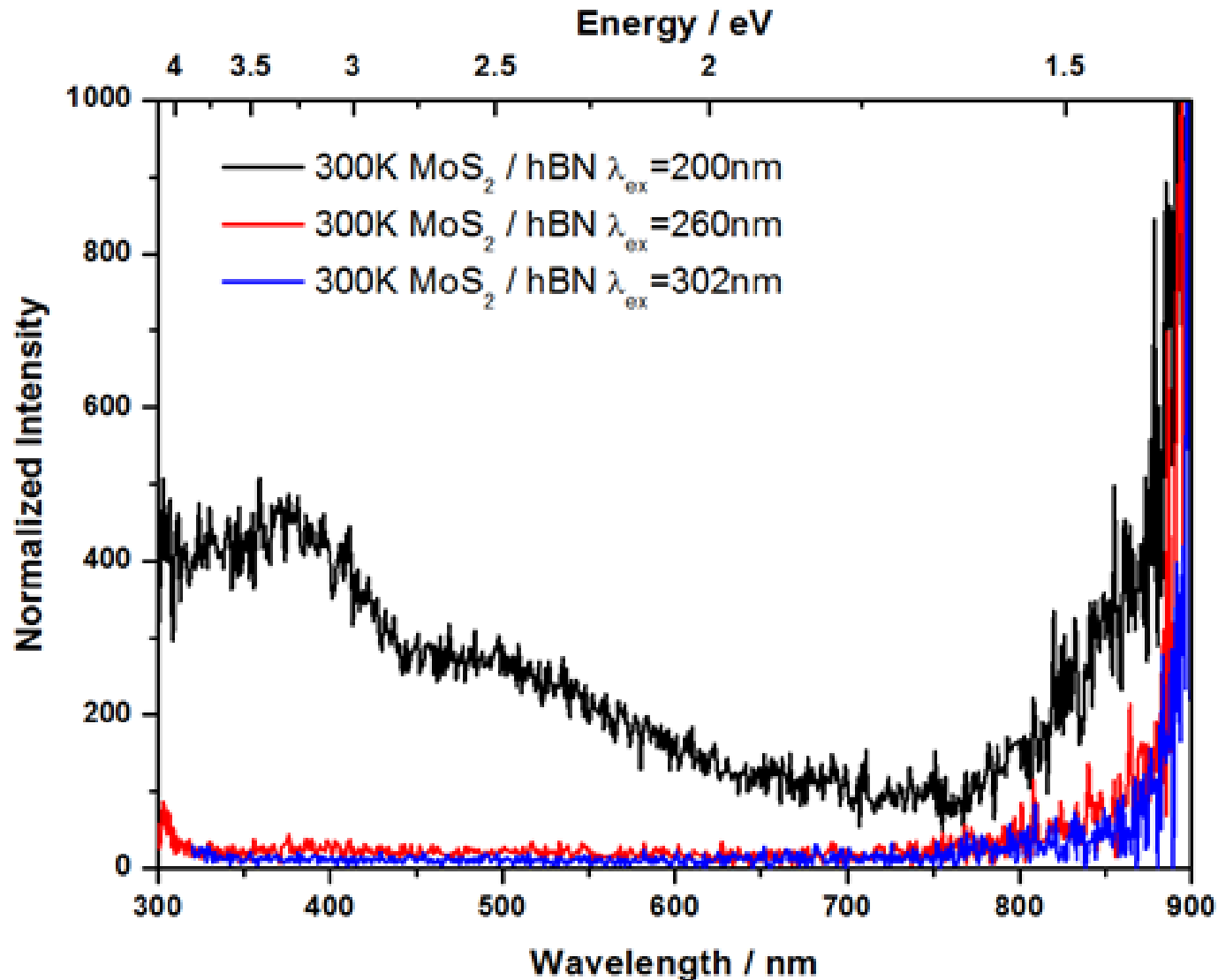
PL Spectra Excited with UV/vis @ RT



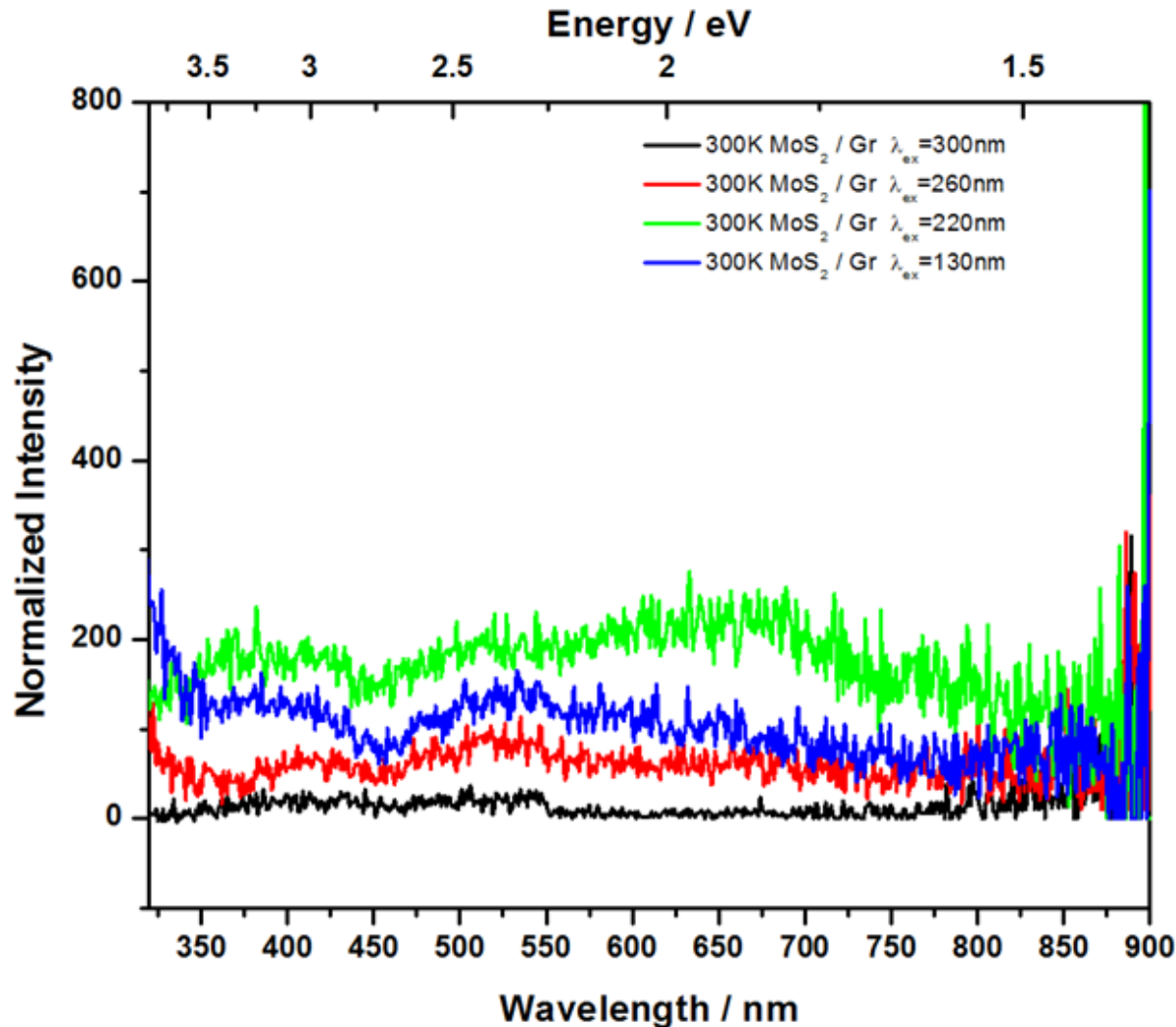
PL Spectra Excited with UV light @ 10 K



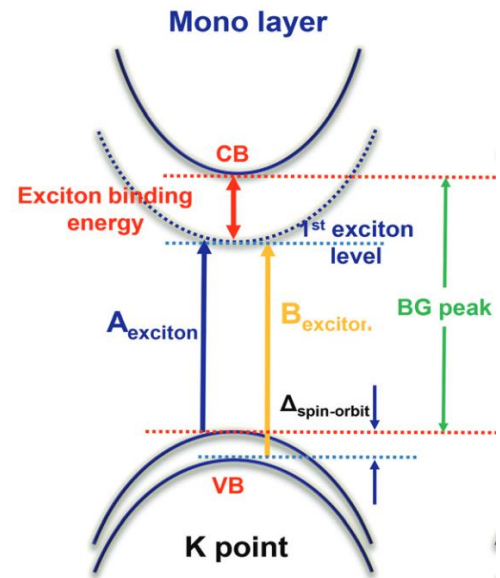
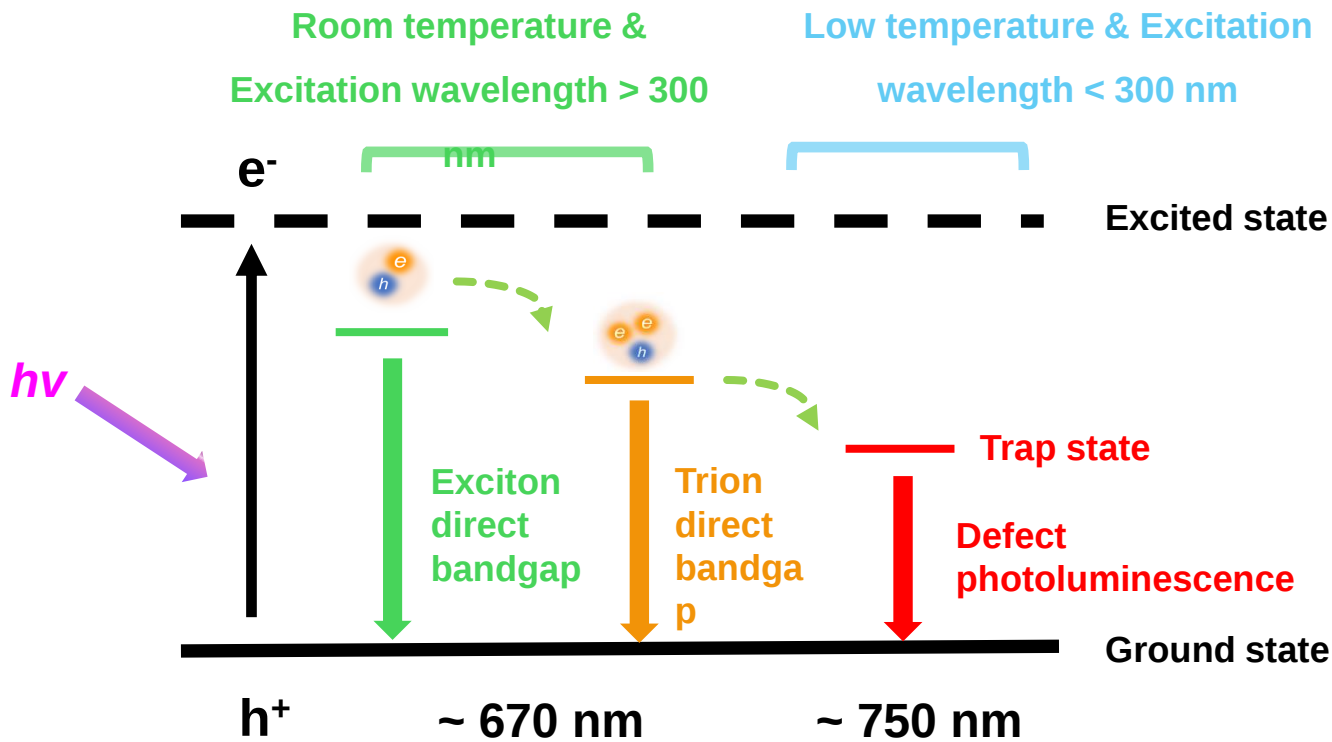
PL Spectra of MoS₂/hBN Excited with UV light @ RT : No A, B- excitonic emissions



PL Spectra of MoS₂/Gr Excited with UV light @ RT : No A, B- excitonic emissions



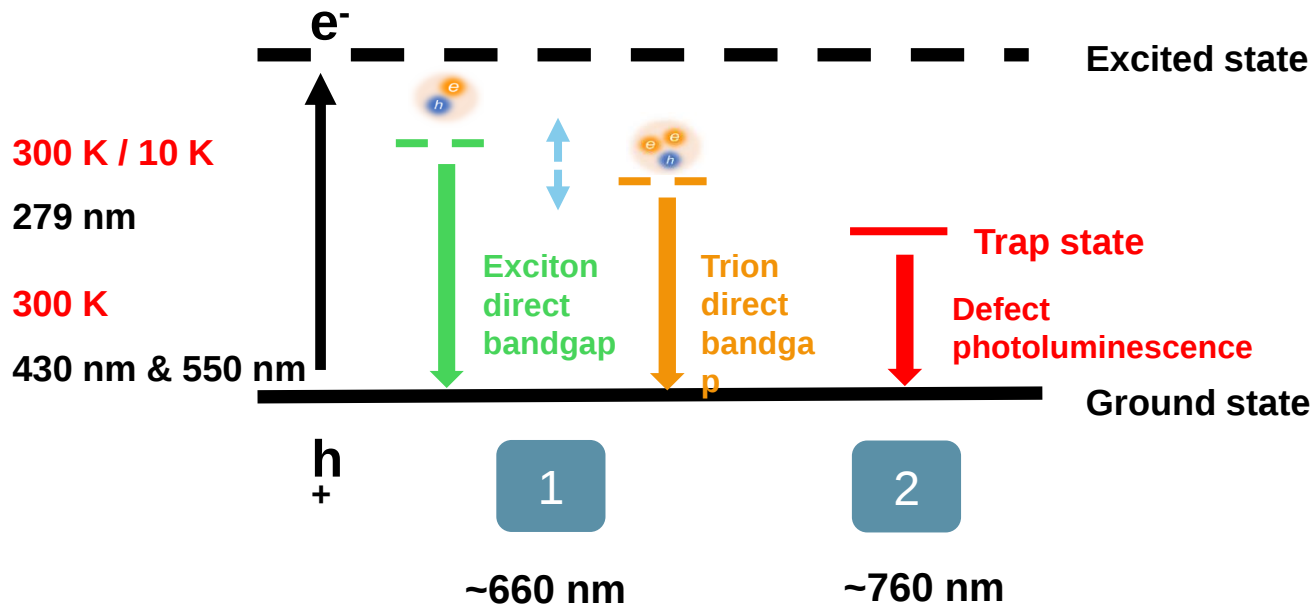
Discussion – Part I



Nanoscale 2014, 6 (21), 13028–13035.

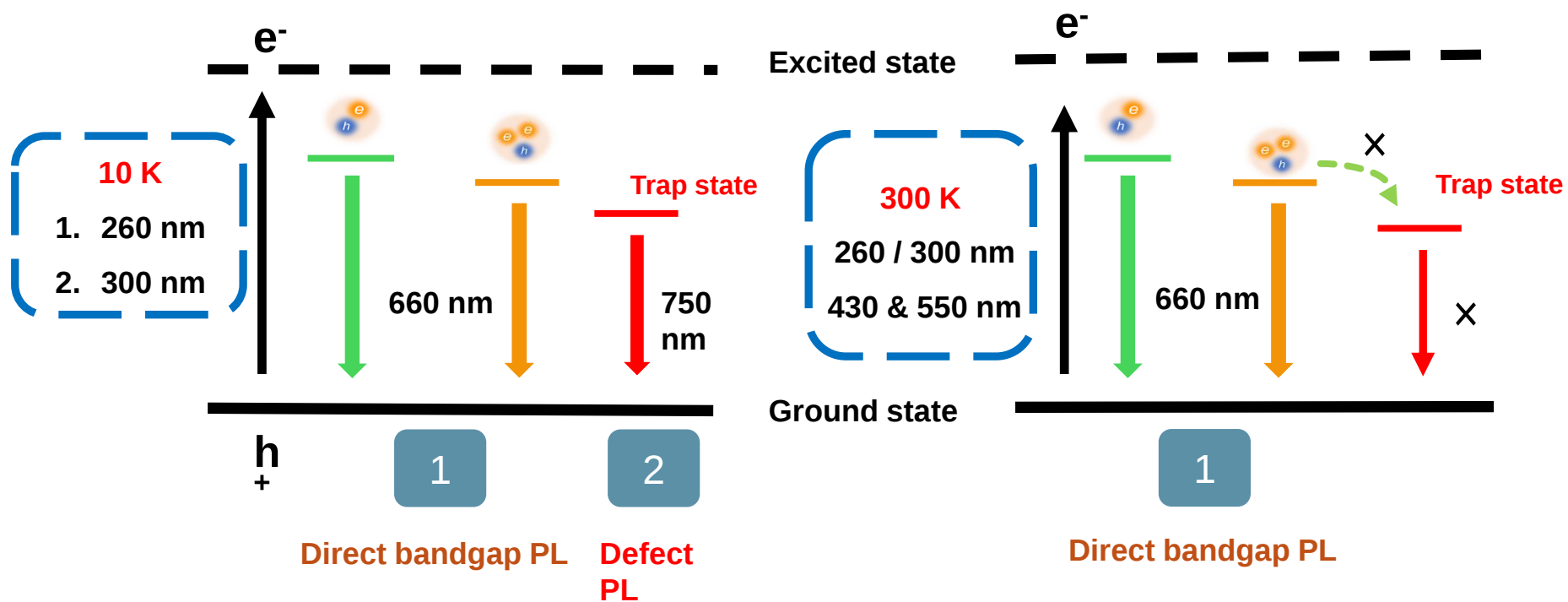
Discussion – Part II

➤ MoS₂ on Sapphire substrate



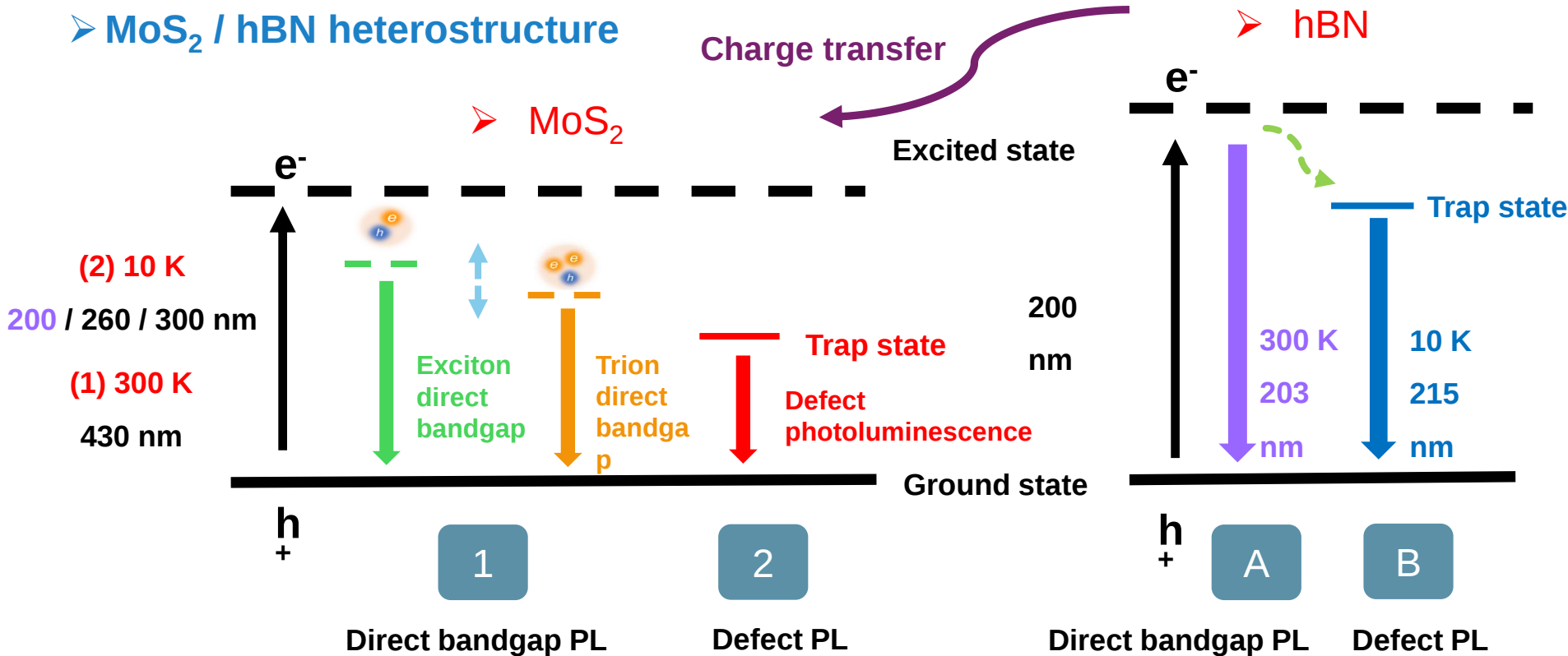
Discussion – Part II

➤ MoS₂ on Quartz substrate



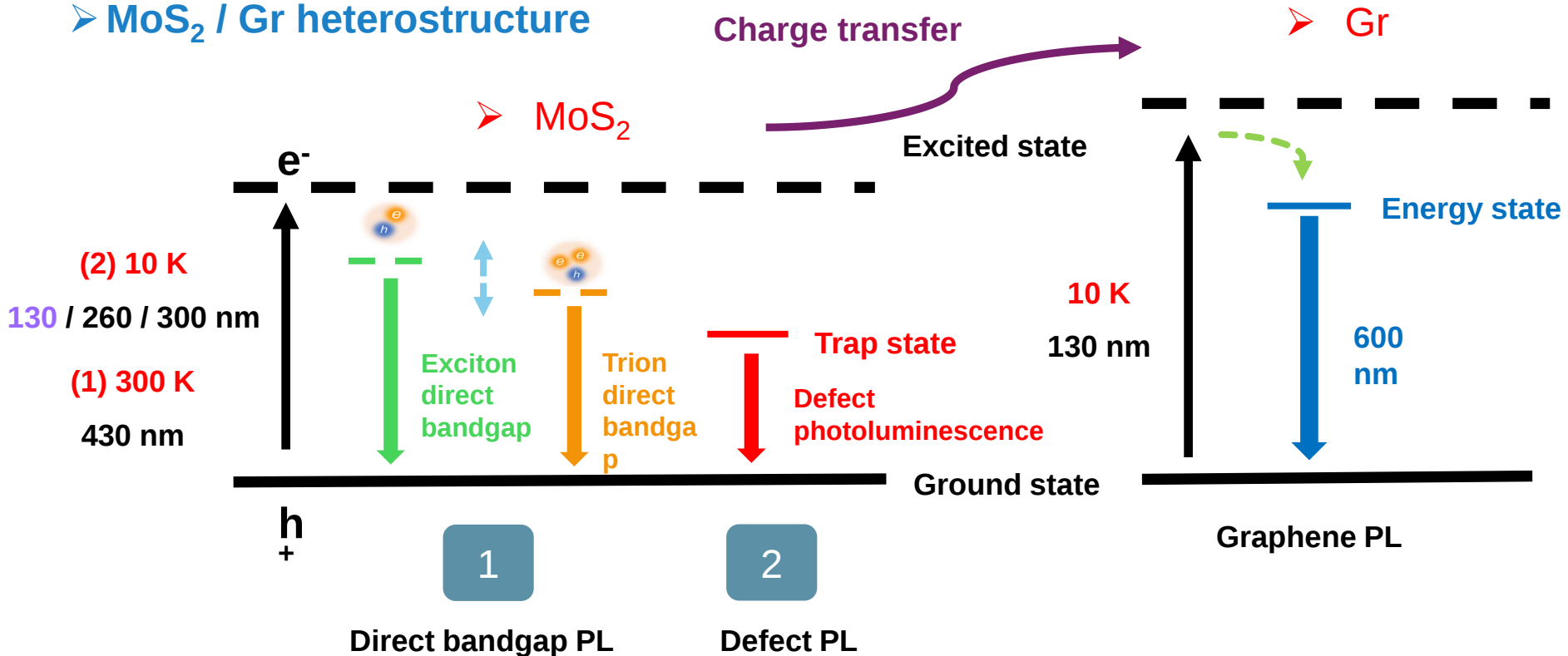
Discussion – Part III

➤ MoS₂ / hBN heterostructure



Discussion – Part III

➤ MoS₂ / Gr heterostructure



Conclusion

1. 新型光致發光通道的發現

單層 MoS₂ 在可見光激發下只呈現典型的 A 激子發光 (~660 nm)。然而，在深紫外 (DUV, <300 nm) 激發下，於低溫 (~10 K) 的 MoS₂/hBN 與 MoS₂/graphene 異質結構中，出現寬帶近紅外發光 (750 - 900 nm)。

2. 界面能量轉移機制

hBN 層：在 ~200 nm 激發時， $\pi - \pi^*$ 過渡吸收能量可轉移至 MoS₂，觸發其寬帶發光。Graphene 層：在 ~260 nm 激發時，石墨烯的 π 電子吸收產生高能載子，部分可穿隧到 MoS₂ 缺陷或局域態，進而產生紅外發光。

3. hBN 與 Graphene 的對比效應

hBN：絕緣性大能隙材料，避免界面電荷轉移，能有效保留並強化 MoS₂ 的輻射復合。Graphene：導電性強，常在可見激發下淬熄 MoS₂ 的發光，但在 DUV 激發時仍能經由熱載子注入 MoS₂ 觸發紅外發光。整體而言，MoS₂/hBN 的發光較強，MoS₂/graphene 較弱。

4. 科學與應用意涵

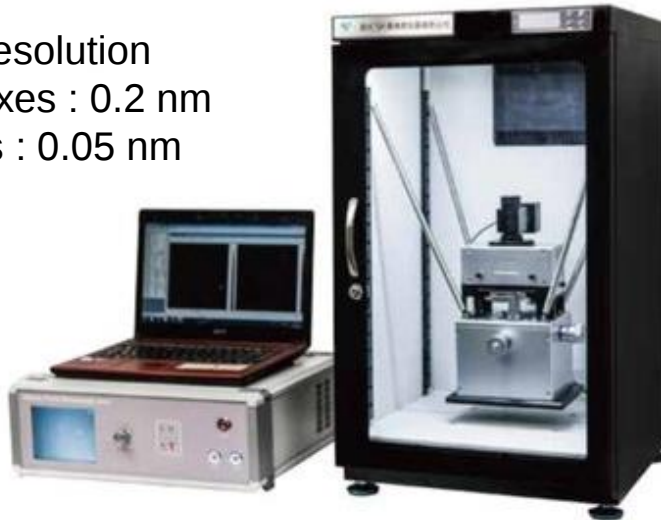
本研究證明了透過 異質結構設計與 DUV 光敏化，可開啟 MoS₂ 原本無法展現的隱藏輻射通道。這提供了一種新策略來 調控 2D 材料的光學特性，對光電元件設計有潛在價值，例如：分光吸收與發光分離的裝置。

AFM and Raman system

Atomic Force Microscopy

Spatial resolution

- ✓ X/Y axes : 0.2 nm
- ✓ Z axis : 0.05 nm



Confocal micro-Raman spectroscopy system

- ✓ 532 nm laser source
- ✓ Liquid N₂-cooled CCD
- ✓ Resolution : 0.5 cm⁻¹



Commercial spectrofluorometer

Visible region information

- ✓ Light source: 150 W Xenon lamp
- ✓ Spectral coverage : 230-870 nm
- ✓ Scan mode: Absorption / photoluminescence
- ✓ Different filters

